IN THE UNITED STATES DISTRICT COURT ' FOR THE DISTRICT OF DELAWARE

LG DISPLAY CO., LTD.,

Plaintiff,

Liamini

Civil Action No. 06-726 (JJF) Civil Action No. 07-357 (JJF)

٧.

CHI MEI OPTOELECTRONICS CORPORATION, et al.,

Defendants.

CONSOLIDATED CASES

JOINT CLAIM CONSTRUCTION CHARTS

Pursuant to the Court's May 19, 2008 Stipulation and Order Modifying the Scheduling Order (D.I. 208), LG Display Co., Ltd. and LG Display America, Inc. ("LG Display"), Chi Mei Optoelectronics Corporation and Chi Mei Optoelectronics USA, Inc. ("CMO"), and AU Optronics Corporation America ("AUO") submit their Joint Claim Construction Charts as follows:

I. Patents asserted by LG Display:¹

U.S. Patent No. 4,624,737	Exhibits $A-1$, $A-2$, and $A-3$
U.S. Patent No. 5,019,002	Exhibits $B-1$, $B-2$, and $B-3$
U.S. Patent No. 5,825,449	Exhibits $C-1$, $C-2$ and $C-3$
U.S. Patent No. 6,664,569	Exhibits $D-1$ and $D-2$
U.S. Patent No. 6,803,984	Exhibits $E-1$, $E-2$, and $E-3$
U.S. Patent No. 5,905,274	Exhibits $F - 1$, $F - 2$, and $F - 3$
U.S. Patent No. 6,815,321	Exhibits $G-1$, $G-2$, and $G-3$
U.S. Patent No. 7,176,489	Exhibits $H - 1$, $H - 2$, and $H - 3$
U.S. Patent No. 7,218,374	Exhibits $I - 1$, $I - 2$, and $I - 3$

LG Display's proposed constructions are indicated on Exhibits A-1, B-1, C-1, etc. AUO's proposed constructions are indicated on Exhibits A-2, B-2, C-2, etc. CMO's proposed constructions are indicated on Exhibits A-3, B-3, C-3, etc. As to LG Display patent 6,664,569, which is subject to a motion to amend as to CMO, there are only two sets of Exhibits (LG Display's at D-1 and AUO's at D-2). The parties intend to file promptly an amended version of these Joint Claim Construction Charts, with each of the parties' proposed constructions appearing side-by-side on the same chart.

Patents asserted by AUO: 2 II.

U.S. Patent No. 5,748,266	Exhibits $J - 1$ and $J - 2$
U.S. Patent No. 6,689,629	Exhibits $K - 1$ and $K - 2$
U.S. Patent No. 6,734,944	Exhibits $L-1$ and $L-2$
U.S. Patent No. 6,778,160	Exhibits $M - 1$ and $M - 2$
U.S. Patent No. 6,976,781	Exhibits $N-1$ and $N-2$
U.S. Patent No. 7,090,506	Exhibits $O - 1$ and $O - 2$
U.S. Patent No. 7,101,069	Exhibits $P - 1$ and $P - 2$
U.S. Patent No. 7,125,157	Exhibits $Q - 1$ and $Q - 2$

Patents asserted by CMO: 3 III.

U.S. Patent No. 5,619,352	Exhibits $R-1$ and $R-2$
U.S. Patent No. 6,008,786	Exhibits $S-1$ and $S-2$
U.S. Patent No. 6,013,923	Exhibits $T - 1$ and $T - 2$
U.S. Patent No. 6,134,092	Exhibits $U-1$ and $U-2$
U.S. Patent No. 6,734,926	Exhibits $V - 1$ and $V - 2$
II S. Patent No. 7 280 179	Exhibits $W - 1$ and $W - 2$

July 29, 2008

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² AUO's proposed constructions are indicated on Exhibits J-1, K-1, L-1, etc. LG Display's proposed constructions are indicated on Exhibits J-2, K-2, L-2, etc.

 $^{^3}$ CMO's proposed constructions are indicated on Exhibits R – 1, S – 1, T – 1, etc. LG Display's proposed constructions are indicated on Exhibits R-2, S-2, T-2, etc.

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Document 363

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CERTIFICATE OF SERVICE

I, Karen L. Pascale, Esquire, hereby certify that on July 29, 2008, I caused to be electronically filed a true and correct copy of the foregoing document with the Clerk of the Court using CM/ECF, which will send notification that such filing is available for viewing and downloading to the following counsel of record:

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I further certify that I caused a copy of the foregoing document to be served by e-mail on the above-listed counsel of record and on the following non-registered participants in the manner indicated:

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A-1

Disputed Constructions

ę	Claim Terms a process for producing a thin-film transistor
	n-film C
Intrinsic Support 1:6-29; 1:56-58; 1:61-68; 2:1-2; 2:8-68; 3:1-62; 4:1- 23; Figs 1a-3d.	a method for manufacturing thin-film transistors such as for a liquid crystal display
	CMO Construction
	AUO Construction

		thin-film transistor	Claim Terms
		C C	Toc
Intrinsic Support 1:6-29; 1:56-58; 1:61-68; 2:1-2; 2:8-68; 3:1-62; 4:1- 23; Figs 1a-3d.	which the current flow through one pair of terminals, the source and drain, is controlled or modulated by an electric field that penetrates the semiconductor; this field is introduced by a voltage applied at the third terminal, the gate, which is separated from the semiconductor by an insulating layer. The thin-film transistor is formed using thin-film techniques on an insulating substrate rather than a single crystal silicon wafer.	A three-terminal	CMO Const
		ACO CONSTRUCTION	

	forming on								insulating substrate	
Intrinsic Support 1:14-17; 2:8-17; 3:21-39; Figs 1a, 2a, 3a.	Figs 1a-3d. giving form or shape toabove and supported by or in Contact with	Intrinsic Support 1:14-21; 2:8-24; 3:21-39;	mechanical support and electrical insulation	insulator coated metal) upon which the transistor is	as glass, quartz, ceramic, insulator-coated silicon or	drain electrode that is above and supported by or in	through the channel between the source electrode and	conductive material that	patterned electrically	LGD Construction CMO Construction
		-					-			AUO Construction

1: F:	co th pr	insulating substrate C th	Claim Terms Des.
Intrinsic support 1:14-21; 2:8-24; 3:21-35; Figs 1a-3d.	quartz, ceramic, insulator- coated silicon or insulator coated metal) upon which the transistor is fabricated to provide mechanical support and electrical insulation.	the material (such as glass,	LGD Construction CMO Construction
	,		AUO Construction

							semiconductor film and a conducting film	gate electrode and substrate a gate insulating film, a high-resistivity	continuously depositing on said
			<i>P. 1. 1.</i>					_	C
Figs 2a-3d; Abstract.	1:14-53; 1:55-58; 2:8-45; 3:21-35; 3:54-62; 4:3-24;	provide mechanical support and electrical insulation. Intrinsic support	coated silicon or insulator coated metal) upon which the transistor is fabricated to	material (such as glass, quartz, ceramic, insulator-	through the channel between the source electrode and drain electrode and	in contact with (i) the patterned electrically conductive material that controls current flow	film and conducting film (without intervening films) above and supported by or	insulating film, the high- resistivity semiconductor	the formation of the gate
				-					CIAO Constituction
			_			_		571	AUO Construction

	•	
S. D. String On	continuously depositing depositing on	Claim Terms
	C ACL	Des.
insulating film, the high-resistivity semiconductor film and conducting film above and supported by or in contact with Intrinsic Support 1:14-21; 2:8-45; 3:28-35; 3:54-62; 4:1-13; Abstract; Figs 2b and 3b.	the formation of the gate insulating film, the high-resistivity semiconductor film and conducting film without intervening films Intrinsic Support 1:17-21; 2:17-45; 3:28-35; 3:54-62; 4:1-13; Abstract; Figs 2b and 3b.	LGD Construction
		CMO Construction
		AUO Construction

				gate insulating film				depositing	Claim Terms
				C				Α	Des.
1:12-21, 2:18-38; 3:28-35; Abstract; Figs. 1b-1d, 2b-2e, and 3b-3d.	Intrinsic Support	insulates the transistor gate from the semiconductor.	conductive material (such as SiNx) that has a high	a thickness of non-	3:54-62; 4:1-13; Abstract; Figs 2b and 3b.	Intrinsic Support 1:17-21; 2:17-45; 3:28-35;	resistivity semiconductor film and conducting film	insulating film, the high-	LGD Construction
									CMO Construction
				•					AUO Construction

		conducting film			high-resistivity semiconductor film
		Ċ			C
1:25-29; 1:32-51; 2:10-36; 2:43-68; 3:1-10; 3:28-35; 3:48-62; 4:1-23; Abstract; Figs. 2b-2e and 3b-3d.	Intrinsic Support	a thickness of electrically conductive material	1:8-29; 1:32-49; 2:17-32; 2:38-43; 2:54-60; 3:7-10; 3:16-21; 3:28-41; 4:48-62; 4:1-23; Abstract; Figs. 1b- 1d, 2b-2e, and 3b-3d.	Intrinsic Support	a thickness of semiconductor material (such as amorphous silicon, hydrogenated amorphous silicon, amorphous silicon-fluorine alloy, amorphous silicon-hydrogen-fluorine alloy, or a microcrystalline amorphous silicon) that has a higher resistance to current flow relative to the low-resistivity semiconductor film.
					AUO Construction

			least a low-resistivity semiconductor film A	Claim Terms Des.
1:18-36; 1:43-57; 2:17-37; 3:28-41; 3:48-62; 4:1-13, Abstract, Figs.2b-2e and 3b-3d.	Intrinsic Support	film and possibly other conductive films	composed of a low-	LGD Construction
				CMO Construction AUO Construction

														semiconductor film	low-resistivity	Claim Terms
															C	Des.
1:25-29; 1:32-51; 2:17-50; 2:54-68; 3:1-10; 3:28-41; 3:48-62; 5:1-23; Abstract; Figs. 1d, 2b-2e, 3b-3d.	Intrinsic Support	high-resistivity semiconductor film.	current flow relative to the	the conductivity of the film)	other impurities to enhance	amorphous silicon which	alloy, or a microcrystalline	silicon-hydrogen-fluorine	fluorine alloy, amorphous	silicon, amorphous silicon-	hydrogenated amorphous	amorphous silicon,	(such as low-resistivity	semiconductor material	a thickness of	LGD Construction CMO Construction
	-						a					-				AUO Construction

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
without exposing them to an oxidizing atmosphere	C	without exposing the gate insulating film, the high-	
		film, and the conducting	
		film containing at least the	
		semiconductor film to an	
		atmosphere that would	
		create a detectable amount	
		of oxidation on a film.	
		Intrinsic Support	
		1:32-46; 1:47-53; 2:17-36; 3:28-35; 3:53-62; 4:1-12; Figs. 2b-2e, 3b-3d.	
them	С	the gate insulating film, the high-resistivity	
		semiconductor film, and the conducting film containing at least the low-resistivity	
		Intrinsic Support	
		2:17-36; 3:28-35; 3:53-62; 4:1-12; Abstract; Figs. 2b-	
		26, 30-3q.	

	selectively etched	*		oxidizing atmosphere	Claim Terms
	C			C	Des.
wet etching, plasma etching, reactive ion etching, and ion etching) in order to produce a desired pattern on the surface. Intrinsic Support 1:14-21; 1:25-29; 1:32-35; 2:10-16; 2:54-66; 3:7-10; 3:28-41; 3:44-48; 4:3-9; Figs 1a-d; 2a-e; 3a-d.	The removal of selected portions of a surface using etching techniques (such as	1:21-51; 2:17-53; 3:28-35; 3:53-4:23; Figs. 2b-2e, 3b-3d; Abstract.	Intrinsic Support	d nt	LGD Construction CMO Construction
-		-			AUO Construction

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island region on said gate electrode	Claim Terms they are partly left as an island region on said gate electrode
C	L L
a portion of the high resistivity semiconductor film and conducting film has been etched around its perimeter into a region located over the gate electrode of a thin-film transistor. Intrinsic Support 1:14-17;_1:25-29; 2:7-16; 2:54-66; 3:22-; Figs. 2-3.	a portion of the high resistivity semiconductor film and conducting film has been etched around its perimeter into a region located over the gate electrode of a thin-film transistor Intrinsic Support 1:14-17;1:25-29; 2:7-16; 2:54-66; 3:22-; Figs. 2-3.
-	AUO Construction

		selectively forming			a fourth step for selectively forming a source electrode and drain electrode						Claim Terms I
IANU-		С			ΑC	**			>	С	Des.
1:14-17; 1:25-29; 2:10-36; 2:60-68; 3:1-10; 3:24-52; 4:3-9; Abstract; Figs. 1a-1d, 2a-2e, 3a-3d.	Intrinsic Support	forming in selected regions only	1:21-29; 1:32-51; 2:17-68; 3:1-14; 3:28-62; 4:1-12; Abstract; Figs. 1d, 2d-2e, 3c-3d.	Intrinsic Support	forming a source electrode and drain electrode in selected regions only	1:14-18; 2:7-16; 3:33-29; Figs 1a-3d.	Intrinsic Support	through the channel between the source electrode and drain electrode	conductive material that controls current flow	,	C C C C C C C C C C C C C C C C C C C
											CMO Construction
			-				-				AUO Construction

A conductive material formed over the drain region. Current flows through the channel between the source and drain electrode under the control of the gate electrode.	<u>Intrinsic Support</u>	1:21-29; 1:32-51; 2:17-68; 3:1-14; 3:28-62; 4:1-12;
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<u>Intrin</u> 1:14- 3:1-1 Figs	a fifth step for selectively removing said conducting film selectrodes and drain electrodes serving as at least a part of the mask the sc electrodes and drain electrodes electrodes electrodes at least a part of the sc drain least above mater remo mater remo mater resist techn mater	<u>Intrin</u> 2:54- Figs	Claim Terms Contacting a part of the surface of L surface of Said island region A L touch Surface of A
Intrinsic Support 1:14-54; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	a fifth step for removing selected regions only of the conducting film on the island region not covered by the source electrode, drain electrode or mask wherein the source electrode and drain electrode serve as at least a part of the pattern above a surface from which material is to be selectively removed; the pattern is made of material that is resistive to the removed technique relative to the material to be removed	Intrinsic Support 2:54-3:10; 3:53-62; 4:1-2; Figs 2d-2e; 3c-3d.	LGD Construction CMO Constouching a part of the surface of the island region
		-	Construction AUO Construction

	selectively removing		•	conducting film exposed on said island region	Claim Terms J selectively removing said
	С				Des.
1:14-29; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	removing selected regions only Intrinsic Support	1:14-54; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	Intrinsic Support	only of the conducting film on the island region not covered by the source electrode, drain electrode or mask	LGD Construction CMO removing selected regions
	p 101				CMO Construction
-		, - <u>-</u> .	-		AUO Construction

said source and drain electrodes serving as at least a part of the mask	Claim Terms said conducting film exposed on said island region
≯ C	Des.
the source and drain electrodes serving as at least a part of the pattern above a surface from which material is to be selectively removed, where the pattern is made of material that is resistive to the removal technique relative to the material to be removed Intrinsic Support 1:14-54; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	the conducting film on the island region that is not covered by the source electrode, drain electrode or mask Intrinsic Support 1:14-54; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.
-	AUO Construction

	at least a part of the mask			Serving as at least a part of the mask
Intrinsic Support 1:14-29; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	at least a part of the pattern above a surface from which material is to be selectively removed, where the pattern is made of material that is resistive to the removal technique relative to the material to be removed.	Intrinsic Support 1:14-29; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract Figs. 1a-1d, 2a-2e, 3a-3d.	selectively removed, where the pattern is made of material that is resistive to the removal technique relative to the material to be removed	CMO Const
				ruction AUO Construction

mask	a part of the mask
>	A Des.
A pattern above a surface from which material is to be selectively removed. The pattern is made of material that is resistive to the removal technique relative to the material to be removed. Intrinsic Support 1:14-29; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.	a part of the pattern above a surface from which material is to be selectively removed, where the pattern is made of material that is resistive to the removal technique relative to the material to be removed. Intrinsic Support 1:14-29; 2:10-14; 2:54-68; 3:1-16; 3:24-52; Abstract; Figs 1a-1d, 2a-2e, 3a-3d.
-	AUO Construction

C a thickness of material that provides protection such as electrical stability and chemical isolation Intrinsic Support 1:29-31; 3:11-21; 3:44-48; Figs 2e, 3d. C removing portions of one or more layers to uncover a part of each of said source electrode, drain electrode and gate electrode Intrinsic Support 1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d. A removing portions of one or more layers to uncover Intrinsic Support 1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d. Fig. 2e; 3d.		֓֞֞֓֞֓֞֓֓֓֓֓֓֓֓֓֓֓֓֓֓֓֓֓֓֓֡֓֓֓֡֓֡֓֓֓֡֓֓			15 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1
exposing a part of each of said source electrode, drain electrode and gate electrode exposing a Part of each of said Source electrode A	Claim Lerms	Des.		Tuction	UU Construction
exposing a part of each of said C source electrode, drain electrode A and gate electrode exposing A	surface passivation film	C	a thickness of material that provides protection such as		
exposing a part of each of said C source electrode, drain electrode A and gate electrode exposing A			electrical stability and chemical isolation		
each of said C frain electrode A			Intrinsic Support		ŭ.
each of said C Irain electrode A			1:29-31; 3:11-21; 3:44-48; Figs 2e, 3d.		-
A	exposing a part of each of said source electrode, drain electrode and gate electrode	AC	removing portions of one or more layers to uncover a part of each of said source electrode, drain electrode and gate electrode		
A			Intrinsic Support		
Α			1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d.		
Intrinsic Support 1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d.	exposing	Α	removing portions of one or more layers to uncover	-	
1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d.			Intrinsic Support		
			1:6-31; 3:11-21; 3:36-52; Fig. 2e; 3d.		

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Claim Terms	Des.	Agreed Constructions
insulating substrate	C	the material (such as glass, quartz, ceramic, insulator-coated silicon or insulator coated
		metal) upon which the transistor is fabricated to provide mechanical support and electrical
		insulation.

Disputed Constructions

												_												
																							thin-film transistor	Claim Terms
,						,											***************************************						C	Des.
																								LGD Construction
																								CMO Construction
Figs. 2-3; 1:8-29; 1:56-58; 2:8-4:2	E.g.,	Intrinsic Support	silicon wafer.	on an insulating substrate rather than a single crystal	using thin-film techniques	film transistor is formed	insulating layer. The thin-	semiconductor by an	which is separated from the	electrode, the gate electrode,	applied at the third	introduced by a voltage	semiconductor; this field is	field that penetrates the	modulated by an electric	electrode, is controlled or	electrode and drain	electrodes, the source	through one pair of	which the current flow	semiconductor device in	Alternate: A three-terminal	Plain meaning.	AUO Construction

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			forming on					insulating substrate	forming a gate electrode on an	Claim Terms
			С						С	Des.
										LGD Construction CMO Construction
Figs. 2-3; 2: 8-16; 3: 23-35	E GG	Intrinsic Support	Producing above, supported by, and in contact with	Figs. 2-3; 2: 8-16; 3: 23-28	E 89;	Intrinsic Support	substrate	above, supported by, and in	Producing a gate electrode	AUO Construction

			continuously depositing on said gate electrode and substrate a gate insulating film, a high-resistivity semiconductor film and a conducting film	Olaim Tamas
			C	7
			LGD Construction	
·			CMO Construction	
Abstract; Figs. 2-3; 1:32-46; 2:17-53; 3:22-4:12	E.g.,	Intrinsic Support	Precipitating a gate insulating film, a high resistivity semiconductor film and a conductive film on the gate electrode and the substrate without intervening films in between.	

			depositing on										continuously depositing	Claim Terms
		· · · · · · · · · · · · · · · · · · ·	С							,	>	<u>С</u>	I	Des.
					,									LGD Construction
									,					CMO Construction
Figs. 2-3; 2: 17-53; 3:22-4:12	E.g.	Intrinsic Support	Chemically precipitating above, supported by and in contact with	3:22-4:12	2: 17-53;	1:32-46;	Figs. 2-3;	Abstract;	E.g.,	Intrinsic Support	(intervening films	Precipitating without	AUO Construction

<u> </u>									- MI - M	
					gate insulating film				depositing	Claim Terms
					C	,			Α	Des.
										LGD Construction
										CMO Construction
Figs. 2-3; 2:17-53;	E.g.,	Intrinsic Support	Insulating film formed over the gate region	Of	Plain meaning	Figs. 2-3; 2:17-53; 3:22 – 4:12	Ţ ġa ;	Intrinsic Support	Precipitating	AUO Construction

		conducting film						Claim Terms high-resistivity semiconductor film
		С						Des.
								LGD Construction CN
								CMO Construction
E.g., Figs. 2-3; 2:17-53; 3:22 - 4:12	Intrinsic Support	Plain meaning	Figs. 2-3; 2:17-53; 3:22-4:12	E.g.	Intrinsic Support	Semiconductor having the property of high resistivity	or	AUO Construction Plain meaning

F						· · · · · · · · · · · · · · · · · · ·	*				
				semiconductor nim	low-resistivity			Semiconductor Liam	least a low-resistivity	a conducting film containing at	Claim Terms
					С			Α	> C	T	Des.
											LGD Construction
						,					CMO Construction
Figs. 2-3; Abstract; 2:17-53; 3:22-4:12	Eg.	Intrinsic Support	semiconductor having the property of low resistivity	or	Plain meaning	Figs. 2-3; 2: 17-53; 3:22 - 4:12	E.g.,	Intrinsic Support		Plain meaning	AUO Construction

			them						oxidizing atmosphere	without exposing them to an	Claim Terms
			С	140 · ·	,					C	Des.
											LGD Construction CMO Construction
Figs. 2-3; 2:17-53; 3:22-4:12	E.g.,	Intrinsic Support	Indefinite.	2:17-53; 3:22-4:12	Abstract; 1:32-46;	Figs. 2-3;	E.g.,	Intrinsic Support	an atmosphere containing an oxidizing agent	Without exposing them to	AUO Construction

Claim Terms	Des.	LGD Construction CMO C	CMO Construction	AUO Construction
oxidizing atmosphere	C			Atmosphere containing an oxidizing agent
				Intrinsic Support
				E.g.,
				Figs. 2-3;
				1:32-46;
				2:17-53;
				3:22-4:12
selectively etched	C			Selectively removed or corroded by a chemical agent
				Intrinsic Support
				E.g.,
				Figs. 2-3; 2:54-60; 3:22-4:12

			island region on said gate electrode			rogion on said gan electione	they are partly left as an island
			C				Des. LGD Construction L
							CMO Construction
Figs. 2-3; 2:54-60; 3:22-4:12	E.g.	Intrinsic Support	Isolated region above, supported by, and in contact with the gate electrode	Figs. 2-3; 2:54-60; 3:22-4:12	E.g.,	Intrinsic Support	AUO Construction Indefinite

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
gate electrode	У	,	A patterned, electrically conductive material formed
			in the gate region. Current
			flows through the channel
			electrode and the drain
			electrode under control of
			the gate electrode.
			Intrinsic Support
,			E.g.
			Figs. 2-3; 2:8-16; 3:23-28
a fourth step for selectively	С		Step-plus function element.
drain electrode	A		Function is "selectively forming a source electrode and drain electrode"
			Step is disclosed: E.g.,
			Figs. 2-3; 2:60-3:10; 3:22-4:12

<u></u>										
					source electrode				selectively forming	Claim Tamma
					A C				C C	J.,.
									LGD Construction CMO Construction	
Abstract; 1:17-29; 2:60-3:10; 3:36-41	Eg.	Intrinsic Support	electrode and the drain electrode under control of the gate electrode.	over the source region. Current flows through the	A patterned, electrically conductive material formed	Figs. 2-3; 2:60-3:10; 3:22-4:12	E gg	Intrinsic Support	Selectively producing	

		said island region	contacting a part of the surface of										drain electrode	Claim Terms
		> <	J L									Α	Q	Des.
														LGD Construction CMO Construction
Figs. 2-3; 2:60-3:10; 3:22-4:12	E.g.,	Intrinsic Support	Plain meaning	1:17-29; 2:60-3:10; 3:36-41	Abstract;	E.g.,	Intrinsic Support	the gate electrode.	electrode and the drain	channel between the source	Over the drain region. Current flows through the	conductive material formed	A patterned, electrically	AUO Construction

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
a fifth step for selectively	Α		a fifth step for using the
removing said conducting film			source and drain electrodes
exposed on said island region with said source and drain electrodes			to partially define the boundary for the removal of
serving as at least a part of the mask			the conducting film exposed on the island region
			Intrinsic Support
			E.g.,
			Figs. 2-3; 2:60-3:10; 3:22-4:12
selectively removing said	С		Plain meaning
said island region			Intrinsic Support
			E.g.,
			Figs. 2-3; 2:60-3:10; 3:22-4:12

Claim Terms	Des. LGD Construction	CMO Construction	AUO Construction
selectively removing	С		Plain meaning
			Intrinsic Support
			E.g.,
			Figs. 2-3; 2:60-3:10; 3:22-4:12
said conducting film exposed on said island region	A		the conducting film on top of the island region is exposed to the atmosphere
			Intrinsic Support
			E.g.,
			Figs. 2-3; 2:60-3:10; 3:22-4:12

serving as at least a part of the mask	said source and drain electrodes serving as at least a part of the mask
L	A C
	LGD Construction
	CMO Construction
using to partially define the boundary for the removal process Intrinsic Support E.g., Figs. 2-3; 2:60-3:10; 3:22-4:12	Using the source and drain electrodes to partially define the boundary for the removal or formation of the conductive film Intrinsic Support E.g., Figs. 2-3; 2:60-3:10; 3:22-4:12

				 					8-25
			a part of the mask					at least a part of the mask	Claim Terms
			A					С	Des.
									LGD Construction
									CMO Construction
Figs. 2-3; 2:60-3:10; 3:22-4:12	E.g.,	Intrinsic Support	to partially define the boundary for the removal or formation process	Figs. 2-3; 2:60-3:10; 3:22-4:12	E.g.	Intrinsic Support	formation process	to partially define the boundary for the removal or	AUO Construction

					(
	surface passivation film				mask	Claim Terms
	C				A	Des.
						LGD Construction
						CMO Construction
E.g., Figs. 2-3; 3:11-21; 3:22-4:12	Plain meaning Intrinsic Support	Figs. 2-3; 2:60-3:10; 3:22-4:12	E go	Intrinsic Support	A pattern above a surface from which material is to be selectively removed or formed, and the pattern protects against removal or formation from above. The pattern is made of material that is resistive to the removal or formation technique relative to the material to be removed or formed.	AUO Construction

exposing a part of each of said source electrode, drain electrode and gate electrode to be exposed to the atmosphere [E.g., Figs. 2-3; 3:11-21; 3:22-4:12] exposing A M Uncovering [E.g., Figs. 2-3; 3:11-21; 3:21-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21; 3:11-21;	Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
exposing A	source electrode, drain electrode and gate electrode	A			electrode, drain electrod and gate electrode to be exposed to the atmosphe
					Intrinsic Support
		,			Ή ġġ
A		,			Figs. 2-3; 3:11-21; 3:22-4:12
E.g., Figs. 2-3; 3:11-21;	exposing	Α			Uncovering
E.g., Figs. 2-3; 3:11-21;					Intrinsic Support
Figs. 2-3; 3:11-21;					E.g.,
					Figs. 2-3; 3:11-21;

A-3

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insulating substrate	C	the material (such as glass, quartz, ceramic, insulator-coated silicon or insulator-coated
		metal) upon which the transistor is fabricated to provide mechanical support and electrical
		insulation

Disputed Constructions

			_	The state of the s
••	"thin-film transistor"			
	construction below for			transistor
-	plain meaning in light of the		C	a process for producing a thin-film
AUO Construction	CMO Construction	LGD Construction	Des.	Claim Terms

																	Claim Terms Des.
see also 5/5/05 Order re Claim Construction, Case No. 02-6775, at 13; Second Revised Joint Claim Construction Statement, Case No. 02-6775, at 89-93	1:8-31; 1:47-53; 4:3-12	Intrinsic Support	substrate rather than in a single crystal silicon wafer.	formed using thin-film techniques on an insulating	thin-film transistor is	from the semi-conductor by	the gate, which is separated	applied at the third terminal,	semiconductor; this field is	modulated by an electric	drain, is controlled or	terminals, the source and	through one pair of	which the current flow	semiconductor device in	A th	LGD Construction CMO Construction
nd 93			91.	18		by _	ed	1al,	is								AUO Construction

		,			
		insulating film, a high-resistivity semiconductor film and a conducting film	continuously depositing on said gate electrode and substrate a gate	forming on	Claim Terms forming a gate electrode on an insulating substrate
			С	С	Des.
(6)	LI S e C	. a a	C	đ	LGD Construction p
1:17-38; 3:28-35; 3:53-4:2; 4:17-23; Figs. 1a-1d, 2b, 3b (e.g., elements 1, 2, 3)	depositing above and in contact with the gate electrode and the insulating substrate Intrinsic Support	"depositing on said gate electrode and substrate" as:	construe the term:	plain meaning	CMO Construction plain meaning
-					AUO Construction

depositing	depositing on					continuously depositing	Claim Terms
A	С				A C	ם כ	Des.
							LGD Construction
plain meaning	this term should be construed as part of the larger term "depositing on said gate electrode and substrate"	see also 5/5/05 Order re Claim Construction, Case No. 02-6775, at 8-9; Second Revised Joint Claim Construction Statement, Case No. 02-6775, at 95-101.	1:17-38; 3:28-35; 3:53-4:2; 4:17-23; Figs. 1a-1d, 2b, 3b (e.g., elements 3, 4, 20 and 30)	Intrinsic Support	resistivity semiconductor film and conducting film without intervening films	the formation of the gate	CMO Construction
		-					AUO Construction

				gate insulating film	Claim Terms
				C	Des.
					LGD Construction
1:17-21; 4:17-23; 1:32-40; 4:47-53 (Claim 2); 4:26-46 (Claim 1); 3:53-4:2; Figs 2a-2e, 3	Intrinsic Support	the gate electrode to the high resistivity semiconductor layer, for insulating the gate electrode from the channel	layer film made of such materials) with a high electrical resistance, spanning the region from	a thickness of material (such as SiNx, SiOx, or a multi-	CMO Construction
					AUO Construction

conducting film			high-resistivity semiconductor film	Claim Terms 1
C			С	Des.
				LGD Construction
a thickness of electrically conductive material that lies adjacent to the channel layer Intrinsic Support 2:17-21; 2:46-3:10; 3:53-4:2; Figs. 2b-2e, 3b-3d (e.g., elements 20, 30)	Intrinsic Support 1:32-51; 2:8-10; 2:38-43; 2:60-3:4; Figs. 2b-2e, 3b-3d (e.g., element 4)	hydrogenated amorphous silicon, hydrogenated amorphous silicon-fluorine alloy, amorphous silicon-hydrogen-fluorine alloy, or a microcrystalline amorphous silicon) that has a high resistance to current flow and acts as the channel of the transistor	a thickness of semiconductor material	CMO Construction
				AUO Construction

low-resistivity semiconductor film	Claim Terms [a] conducting film containing at least a low-resistivity semiconductor film A*
	Des. LGD Construction L C A*
a thickness of semiconductor material (such as amorphous silicon, hydrogenated amorphous silicon, amorphous silicon- fluorine alloy, amorphous silicon-hydrogen-fluorine alloy, or a microcrystalline amorphous silicon) that has a low resistance to current flow Intrinsic Support 1:32-51; 2:17-21; 2:38-44; 3:53-4:2; Figs. 2b-2e, 3b-3d (e.g., element 20)	plain meaning the terms "conducting film" and "low-resistivity semiconductor film" should be construed separately from this term
	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction
without exposing them to an oxidizing atmosphere	С		without permitting the gate insulating film, high-
			resistivity semiconductor
			film, low-resistivity semiconductor film, or
:			conducting film to come
			into contact with an
			uncontrolled ambient
	*****		oxidizing agents
			Intrinsic Support
			1:32-51; 2:17-53; 3:28-35; Figs. 2b-2e, 3b-3d
them	С		the gate insulating film, the high-resistivity
Committee Pales			semiconductor film, and the
			at least the low-resistivity
			semiconductor IIIm
oxidizing atmosphere	C		an uncontrolled ambient atmosphere which contains oxidizing agents
			Intrinsic Support
			1:32-51; 2:17-53; 3:28-35;
and the second s			To see to the

	plain meaning		C	selectively forming	[
	plain meaning		A C	a fourth step for selectively forming a source electrode and drain electrode	
	see 5/5/05 Order re Claim Construction, Case No. 02- 6775, at 7-8; Second Revised Joint Claim Construction Statement, Case No. 02-6775 at 93-95				
	a patterned electrically conductive material that controls current flow through the channel between the source electrode and drain electrode	-	A C	gate electrode	
	plain meaning		С	island region on said gate electrode	· · · · · · · · · · · · · · · · · · ·
	plain meaning		L	they are partly left as an island region on said gate electrode	T
AUO Construction	CMO Construction plain meaning	LGD Construction	Des.	Claim Terms selectively etched	[888]

				100000000
drain electrode			source electrode	Claim Terms
≯ C			A C	Des.
				LGD Construction
this term should be construed as part of the larger term "a source electrode and a drain electrode"	1:32-51; 2:60-66; 3:4-7; 3:36-41; 3: 59-4:6; Figs. 2d- 2e, 3c-3d (e.g., elements 5, 6)	Intrinsic Support	"a source electrode and a drain electrode" as: Patterned, electrically conductive material formed over the source region and drain region, respectively, of a transistor. Current flows through the channel between the source electrode and the drain electrode of the transistor under control of the gate electrode of the transistor.	CMO Construction
				AUO Construction

	1:8-31; 1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 1b – 1d, 2c-2e, 3b-3d			
	Intrinsic Support			
	eliminating all the conducting film in the space between the edges of the source and drain electrodes		С	selectively removing said conducting film exposed on said island region
-	1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 2c- 2e, 3b-3d		··	
	Intrinsic Support			mask
	eliminating all the conducting film in the space between the edges of the source and drain electrodes		A	a fifth step for selectively removing said conducting film exposed on said island region with said source and drain electrodes serving as at least a part of the
	2:60-66; 3:4-7; 3:36-41; Figs. 2d-2e, 3c-3d			
	Intrinsic Support		;	
	touching a part of the surface of the island region		A C L	contacting a part of the surface of said island region
AUO Construction	CMO Construction	LGD Construction	Des.	Claim Terms

Claim Terms	selectively removing				exposed on said island	region					
Des.	C				\						
LGD Construction											
CMO Construction	this term should be construed as part of the	larger term, "selectively removing said conducting	film exposed on said island	G	film on top of the island	region is exposed to the	atmosphere	Intrinsic Support	1:8-31; 1:32-51; 2:60-66;	3:8-10; 3:36-41; 3:59-4:6;	Higs. 1b-1a, 2c-2e, 3b-3a
AUO Construction	-				-	-					

serving as at least a part of the mask	[said] source and drain electrodes serving as at least a part of the mask
Г	Des. C*
	LGD Construction
this term should be construed as part of the term "said source and drain electrodes serving as at least a part of the mask" see also construction of "mask" below Intrinsic Support 1:8-31; 1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 1b-1d, 2c-2e, 3b-3d	the source and drain electrodes are part of the pattern on the top surface that protects underlying layer from being removed while allowing the portion of the layer exposed between the source and drain electrodes to be removed Intrinsic Support 1:8-31; 1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 1b – 1d, 2c-2e, 3b-3d
-	AUO Construction

mask	a part of the mask	Claim Terms at least a part of the mask
Α	A	Des. C
A top surface pattern above one or more layers of material that will be selectively removed according to the shape of th mask. The mask is made of material that is resistive to the removal technique and defines by its edges the boundaries of the material selected for removal. Intrinsic Support 1:8-31; 1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 1b – 1d, 2c-2e, 3b-3d	this term should be construed as part of the "said source and drain electrodes serving as at a part of the mask"	LGD Construction this term should be construed as part of the "said source and drain electrodes serving as a a part of the mask"
A top surface pattern above one or more layers of material that will be selectively removed according to the shape of the mask. The mask is made of material that is resistive to the removal technique and defines by its edges the boundaries of the material selected for removal. Intrinsic Support 1:8-31; 1:32-51; 2:60-66; 3:8-10; 3:36-41; 3:59-4:6; Figs. 1b – 1d, 2c-2e, 3b-3d	this term should be construed as part of the term said source and drain electrodes serving as at least a part of the mask"	CMO Construction this term should be construed as part of the term "said source and drain electrodes serving as at least a part of the mask"
		AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
surface passivation film	С		plain meaning	
exposing a part of each of said source electrode, drain electrode	A C		plain meaning	
and gate electrode				

B-1

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Disputed Constructions

forming a pattern of pixels on said substrate	substrate	Claim Terms
Q	O	Des.
depositing and etching a matrix of transparent electrically conductive material to form pixel electrodes above and supported by or in contact with the substrate Intrinsic Support 1:38-2:6; 2:45-68; 3:3-21; 3:25-36; 3:47-59; 4:4-22, 4:42-45; 4:61-5:6, 5:24-32; 5:42-5:57; 6:46-6:50; 6:60-7:18; 7:47-7:60; 8:49-62; Figs. 1, 4-7; Figs. 1-6; Abstract.	ss) or [-7;	LGD Construction CMO Const.
		truction
-		AUO Construction

		said row lines to one another and substantially all of said column lines to one another	interconnecting substantially all of	forming a plurality of row and column intersecting pixel activation lines
			of A	C C
1:34-35; 5:65-68; 6:6-17; 6:26-32; 6:38-60; 8:1-37; 8:49-62, Fig. 4-7.	Intrinsic Support	conductive material all or nearly all row lines to at least one other row line and electrically connecting with conductive material all or nearly all of the column lines to at least one other column line	electrically connecting with	depositing and etching electrically conductive material patterned in rows and columns that control pixels Intrinsic Support 1:38-42; 1:56-59-2:6; 2:54-62; 3:33-54, 3:60-63; 4:45-58; 5:58-6:17; 6:25-59; 7:3-15; 7:23-29; Figs. 1, 4-7; Abstract.
				truction
				AUO Construction

		row lines			substantially all			interconnecting	Claim Tarms
		C		Α	• C			L C	ב. האנד
1:38-42; 1:56-59-2:6; 2:54-62; 3:33-54, 3:60-63; 4:45-58; 5:58-6:17; 6:25-59; 7:3-15; 7:23-29; Figs. 1, 4-7; Abstract.	Intrinsic Support	electrically conductive material patterned in rows that control pixels	1:34-35; 5:65-68; 6:6-17; 6:26-32; 6:38-60; 8:1-37; 8:49-62; Fig. 4-7.	Intrinsic Support	all or nearly all	1:34-35; 5:65-68; 6:6-17; 6:26-32; 6:38-60; 8:1-37; 8:49-62, Fig. 4-7.	Intrinsic Support	electrically connecting with conductive material	I CD Construction
								CMO Construction	
		-						AUO Construction	ATIO Constmution

·		row and column lines			Claim Terms column lines
		C			Des.
1:38-42; 1:56-59-2:6; 2:54-62; 3:33-54, 3:60-63; 4:45-58; 5:58-6:17; 6:25-59; 7:3-15; 7:23-29; Figs. 1, 4-7; Abstract.	Intrinsic Support	electrically conductive material patterned in rows and columns that control pixels	1:38-42; 1:56-59-2:6; 2:54-62; 3:33-54, 3:60-63; 4:45-58; 5:58-6:17; 6:25-59; 7:3-15; 7:23-29; Figs. 1, 4-7; Abstract.	columns that control pixels Intrinsic Support	LGD Construction CMO electrically conductive material patterned in
					CMO Construction
	-	·	• .		AUO Construction

		Claim Terms outer electrostatic discharge guard ring
		Des. L C A
1:8-14; 2:37-68; 3:20-21; 4:22-31; 4:46-60; 7:11-22; 7:30-34; 8:1-17; 8:24- 37.8:40-44; 8:49-62; Abstract; Figs. 5-7; App 07/218,312, 3/31/1989, Office Action, pages 2-4; App 07/218,312, 7/12/1990, Proposed Response, page 2-3.	Intrinsic Support	a closed or open ring, or open L or C-shaped line, outside the active matrix display to provide protection from electrostatic discharge
		CMO Construction
		AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction A	AUO Construction
resistance	C	a circuit component designed to provide		
	A	opposition to electric current		
		minimize current surge in		
		the TFT array from electrostatic discharge		
		Intrinsic Support		•
		1:8-14; 2:45-68; 4:46-60;		
		7:61-68; 8:18-39; 8:49-62;		
		Abstract; App 07/218,312, 3/31/1989, Office Action,		
		pages 2-4; App 07/218,312, 7/12/1990, Response, pages 2-3.		-
to provide protection from electrostatic discharges between said row and column activation	A	to minimize current surge in the TFT array from electrostatic discharge		
lines during manufacture of the displays		during manufacture of the display		
		Intrinsic Support		
		1:8-14; 2:45-68; 4:46-60; 5:32-43; 7:14-18:7:35-46; 7:61-68; 8:23-39; 8:49-62; Abstract; Fig. 5, 7.		
			-	

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		row and column activation lines			Claim Terms protection from electrostatic discharges
		C			Des.
1:38-42; 1:56-59-2:6; 2:54-62; 3:33-54, 3:60-63; 4:45-58; 5:58-6:17; 6:25-59; 7:3-15; 7:23-29; Figs. 1, 4-7; Abstract.	Intrinsic Support	electrically conductive material patterned in rows and columns that control pixels	1:8-14; 2:45-68; 4:46-60; 5:32-43; 7:14-18:7:35-46; 7:61-68; 8:23-39; 8:49-62; Abstract; Fig. 5, 7.	Intrinsic Support	to minimize current surge in the TFT array from electrostatic discharge during manufacture of the display
	-				AUO Construction

	removing			removing said outer guard ring L and row and column C interconnections	Claim Terms Des.
2:45-68; 8:11-17; 8:26-30; 8:40-62; Abstract; App 07/218,312, 3/31/1989, Office Action, pages 2-4; App 07/218,312, 7/12/1990, Response, pages 2-3.	physically disconnecting said guard ring and row and column interconnections	2:45-68; 8:11-17; 8:26-30; 8:40-62; Abstract; App 07/218,312, 3/31/1989, Office Action, pages 2-4; App 07/218,312, 7/12/1990, Response, pages 2-3.	Intrinsic Support	physically disconnecting said guard ring and row and column interconnections	LGD Construction CMO Const
					ruction AUO Construction

	shunt switching elements				inner electrostatic discharge guard ring	Claim Terms 1
	A C				CL	Des.
Intrinsic Support 7:22-50; 7:61-68; 8:49-62; Abstract.	shunt transistors, including floating gate, no gate, an oxide below to form a spark gap, or other active switching elements such as diodes	1:8-14; 2:45-68; 4:46-60; 5:32-43; 6:60-72; 7:14-68; 8:49-62, Abstract.	Intrinsic Support	inside the source and/or gate pads to provide protection from electrostatic discharge	a closed or open ring, or open L or C-shaped line,	LGD Construction
						CMO Construction
	-	<u>-</u>		·		AUO Construction

B-2

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Disputed Constructions

			column intersecting pixel activation lines	Claim Terms
				Des.
				LGD Construction CMO Construction
Figs. 1, 4, 5, & 6; 3:25-4:3; 5:44-7:10	E.g.,	Intrinsic Support	forming a plurality of row intersecting pixel activation lines and a plurality of column intersecting pixel activation lines	AUO Construction

								substantially all of said column lines to one another	said row lines to one another and	Claim Terms Des.
										LGD Construction CMO Cons
A, Re	A ₁	A ₁ P _r 2-	A _A	7:	8. 5. 3. <u>H</u>	Ĕ.	<u> </u>		Jio Lii	truction
App 06/948224, 9/16/88 Response, Pages 7-9	App 06/948224, 3/16/88 Office Action, Pages 3-4;	App 07/218312, 6/25/90 Proposed Response, Pages 2-3	App 07/218312, 3/31/89 OA, Pages 2-3;	U.S. Pat. No. 4,820,222: Figs. 1, 6, 7, & 8; 7: 39-8:34	Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48;		Intrinsic Support	almost all of the column lines together	joining almost all of the row lines together and joining	AUO Construction

				ţ			interconnecting	Claim Terms
						(ם כ	Des.
								LGD Construction CMO Construction
App 06/948224, 3/16/88 Office Action, Pages 3-4; App 06/948224, 9/16/88 Response, Pages 7-9	App 07/218312, 6/25/90 Proposed Response, Pages 2-3	App 07/218312, 3/31/89 OA, Pages 2-3	U.S. Pat. No. 4,820,222: Figs. 1, 6, 7, & 8; 7: 39-8:34	Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48	E.g.,	Intrinsic Support	Joining together	AUO Construction

				Claim Terms substantially all
			A	Des.
				LGD Construction CMO Construction
U.S. Pat. No. 4,820,222: Figs. 1, 6, 7, & 8; 7:39-8:34	Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48	E go	Intrinsic Support	AUO Construction Almost all

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
row lines	С			Indefinite;
				or
				Lines connecting all pixels in a row
				Intrinsic Support
		·		E.g.,
				Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48
				U.S. Pat. No. 4,820,222: Figs. 1, 6, 7, & 8; 7: 39-8:34

Claim Terms	Des.	LGD Construction	CMO Construction
column lines	C		
	····		
	. 117 67 9444		Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48
	(1-1-1-1-1-1-1-1-1-1-1-1-1-1-1-1-1-1-1-		

						row and column lines
				411,000,000,000		Des.
						LGD Construction
						CMO Construction
U.S. Pat. No. 4,820,222: Figs. 1, 6, 7, & 8; 7:39-8:34	Figs. 1, 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48	E ĠĢ	Intrinsic Support	The row lines and the column lines	or	AUO Construction Indefinite;

AUO Construction A surrounding structure outside the active matrix display to provide protection from electrostatic discharges Intrinsic Support E.g., Figs. 4, 5, 6 & 7; 3:25-4:3; 5:44-7:10; 8:1-48 A circuit component that has a specified ratio between voltage and the flow of electric current, and used to minimize the current surge from electrostatic discharge. Intrinsic Support E.g., Figs. 4, 5, 6 & 7; 3:25-4:3; Figs. 4, 5, 6 & 7; 3:25-4:3;	resistance C A A
	A circuit component that has a specified ratio between voltage and the flow of electric current, and used to minimize the current surge from electrostatic discharge. Intrinsic Support E.g., Figs. 4, 5, 6 & 7; 3.75.4.3.

	protection from electrostatic C discharges		displays	to provide protection from electrostatic discharges between said row and column activation lines during manufacture of the
Intrinsic Support E.g., 4:9-6:59; 8:1-48	Plain meaning; or Guarding against	E.g., 4:9-6:59; 9:1-48	lines during the manufacturing of the displays Intrinsic Support	To guard against electrostatic discharges between the row activation lines and column activation

				illes	row and column activation	Claim Terms
					a	Des.
						LGD Construction CMO Construction
4:9-6:59; 8:1-48	E.g.,	Intrinsic Support	Control lines activating all pixels in rows and control lines activating all pixels in columns.	or	Indefinite;	AUO Construction

						interconnections	removing said outer guard ring	Claim Terms
		P. C., Alle VI.				C	Ţ	Des.
							-	LGD Construction CMO Construction
	U.S. Pat. No. 4,820,222: Figs. 6 & 8; 6: 42-7:38	App 07/218312, 3/31/89 OA, Pages 2-3 App 07/218312, 6/25/90 Proposed Response, Pages 2-3	Fig. 7; 2:45-68; 8:1-48	Intrinsic Support E.g.,	the row and column intersecting pixel activation lines from the substrate	ring and lines connecting	Indefinite; physically	AUO Construction

J								ı.	e) En
								removing	Claim Terms
and the second s						<u> </u>		A	Des.
									LGD Construction
							J		CMO Construction
U.S. Pat. No. 4,820,222: Figs. 6 & 8; 6: 42-7:38	App 07/218312, 7/22/90 Proposed Response, Pages 2-3	App 07/218312, 2/31/89 OA, Pages 2-3	Fig. 7; 2:45-68; 8:1-48	E.gg.	Intrinsic Support	Alternate 2: physically disconnecting	Alternate 1: separating or breaking off	Taking away	AUO Construction

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
inner electrostatic discharge guard	L		Ring structure inside the
ring	C		active matrix display to
			provide protection from
			electrostatic discharges
			Intrinsic Support
			E.g.,
			Fig. 5; 2:45-68;
		•	6:60-7:68
shunt switching elements	A C		A switching circuit for shunting electrostatic discharges
			Intrinsic Support
,			E.g.,
			Fig. 5; 2:45-68; 6:60-7:68

B-3

Disputed Constructions

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
substrate			plain meaning	
forming a pattern of pixels on said substrate	С		forming a repeating configuration of redundant subpixels	
			Intrinsic Support	
			7:46-60; 4:58-60; 5:44-57; 6:19-25; 6:26-36; and figures referenced therein	
forming a plurality of row and column intersecting pixel activation lines	C		forming a plurality of row intersecting pixel activation lines and column intersecting pixel activation lines	
			Intrinsic Support	
			6:1-18; 6:26-36; 5:58-68; 6:38-50; 7:3-10; and figures referenced therein	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
substantially all	> C	-	nearly all, but not all	
	<u>}</u>		Intrinsic Support	
			1:15-35; 1:56-2:10; 2:45-51; 4:9-31; and figures referenced therein	
row lines	С	-	indefinite	-
			or	
			lines connecting all pixels in a row	
			Intrinsic Support	
			1:38-42; 3:37-46; and figures referenced therein	-
column lines	С		indefinite	
			or	
			lines connecting all pixels in a column	
			Intrinsic Support	
			1:38-42; 3:37-46; and figures referenced therein	

			(outer electrostatic discharge guard ring					row and column lines	Claim Terms 1
			>	C					С	Des.
										LGD Construction
see also June 13, 2006 Memorandum Opinion 7-10	Abstract; 2:61-62; 8:27-29; and figures referenced therein	Intrinsic Support	outside the active matrix display to provide protection from electrostatic discharges	a closed or open ring, or open L or C-shaped line.	1:38-42; 3:37-46; and figures referenced therein	Intrinsic Support	the row lines and the column lines	or	indefinite	CMO Construction
		-								AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
resistance	D T		a circuit component that has a specified resistance to the	
	A		flow of electric current and	
			is used to minimize the	-
		-	current surge from an	
			electrostatic discharge	ü
			Intrinsic Support	
			8:23-34; and figures referenced therein	
	1440		see also June 13, 2006 Memorandum Opinion 10-	
			13	
to provide protection from	Α		indefinite	
electrostatic discharges between said row and column activation				-
lines during manufacture of the				
displays				7. 14.11.1
protection from electrostatic	С		indefinite	
discharges				

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
row and column activation lines	C		indefinite	
			or	
			control lines activating all pixels in rows and control lines activating all pixels in columns	
			Intrinsic Support	
			1:38-42; 2:4-7; 3:37-46; and figures referenced therein	
removing said outer guard ring and row and column interconnections	CL		physically disconnecting said guard ring and row and column interconnections	
			Intrinsic Support	-
			Abstract; 2:64-65; 8:27-30; and figures referenced therein	
removing	A		physically disconnecting	
			Intrinsic Support	
			Abstract; 2:64-65; 8:27-30; and figures referenced therein	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
inner electrostatic discharge guard ring	C		a closed or open ring, or open L or C-shaped conductive line, inside the	
			active matrix display to provide protection from electrostatic discharges	
			Intrinsic Support	
			7:14-21; 7:22-68; and figures referenced therein	
			see also June 13, 2006 Memorandum Opinion 7-	
			10; LGD's Mar. 8, 2006 Plaintiff's Memorandum in	
			Claim Constructions 15-17	

Claim Terms	I	s. LGD Construction	CMO Construction
shunt switching elements	nents C		an active switching element like a shunt transistor or diode
			Intrinsic Support
			8:57-59; 8:18-27; 8:34-39; and figures referenced therein
			see also LGD's Mar. 8, 2006 Plaintiff's Memorandum in Support of Its Proposed Claim Constructions 19-20.

C-1

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Claim Terms	Des.	Agreed Constructions
substrate	С	the material (such as glass) upon which a transistor or integrated circuit is fabricated to
		provide mechanical support.
indium tin oxide layer	С	a thickness of indium tin oxide (ITO)

Disputed Constructions

	THE STREET S			
		1:34-38; 2:31-3:15; 3:44-50; 4:50-53; 4:65-5:22; Fig 1-3.		
		Intrinsic Support		
		a thickness of material	С	layer
		1:34-38; 2:31-3:15; 3:44-50; 4:50-53; 4:65-5:22; Fig 1-3.		
		Intrinsic Support		
		thickness of electrically conductive material	CL	conductive layer
		4:24-27; Figs. 1-3.		
		Intrinsic Support		
		connecting at least two points		
1		a structure electrically	C	wiring structure
AUO Construction	CMO Construction	LGD Construction	Des.	Claim Terms

		(
		1:31-48, 56-64: 2:37-46: 3:44-62; 4:19-23; 4:39-41; 4:65-5:8; Figs 2-3; App. No. 08/781,188, 8/1/97, Office Action, page 2.		
		Intrinsic Support		
		above and in contact with a second part of the substrate	С	formed on a second portion of said substrate
		1:31-48, 56-64: 2:37-46: 3:44-62; 4:19-23; 4:39-41; 4:65-5:8; Figs 2-3; App. No. 08/781,188, 8/1/97, Office Action, page 2.		
		Intrinsic Support	Α	
		above and in contact with	> C	formed on
		1:31-48; 1:56-64; 2:37-46: 3:44-62; 4:19-23; 4:39-41; 4:65-5:8; Figs 2-3; App. No. 08/781,188, 8/1/97, Office Action, page 2.		
		Intrinsic Support		
		above and in contact with a first part of the substrate	· Q	formed on a first portion of said substrate
AUO Construction	CMO Construction	LGD Construction	Des.	Claim Terms

		ŧ		
	insulative layer			Claim Terms formed on a first portion of said first insulative layer
	C			Des.
Intrinsic Support 1:40-42; 2:5-9, 2:40-41, 45- 51, 61-62; 3:1-8, 50-54; 4:6-12, 27-34, 47-50; 5:1-2, 8-15; Figs. 1-3.	a thickness of non- conductive material (such as SiNx) that has high electrical resistance	1:31-48, 56-64: 2:37-46: 3:44-62; 4:19-23; 4:39-41; 4:65-5:8; Figs 2-3; App. No. 08/781,188, 8/1/97, Office Action, page 2.	Intrinsic Support	LGD Construction above and in contact with a first part of the first insulative layer CMO Construction CMO Construction
				ion
·			-	AUO Construction

	·	contact hole is provided through layers		overlying	,		Claim Terms formed on said second conductive layer and on a second portion of said first insulative layer overlying said first conductive layer
		A C		С	,		Des.
1:51-2:10; 2:31-3:14; 3:50- 4:41; 4:47-5:47; Figs. 1-3.	Intrinsic Support	the contact hole is formed in the layer	Intrinsic Support 1:40-44; 2:37-55; 3:63-4:15; 5:16-22; Figs 1-3.	above	1:31-48, 56-64: 2:37-46: 3:44-62; 4:19-23; 4:39-41; 4:65-5:8; Figs 2-3; App. No. 08/781,188, 8/1/97, Office Action, page 2.	Intrinsic Support	above and in contact with the second conductive layer and above and in contact with a second part of the first insulative layer above the first conductive layer
							On.
	,					-	AUO Construction

expose part of said layer		provided through		contact hole
C		C		C
removing portions of one or more layers to uncover at least part of another layer Intrinsic Support 1:52-60; 2:5-10, 17-28, 45-55; 3:1-14, 3:66-4:15; 4:35-39, 46-50; 5:8-22; Figs. 1-3; Abstract.	Intrinsic Support 1:51-2:10; 2:31-3:14; 3:50-4:41; 4:47-5:47; Figs. 1-3.	1:51-2:10; 2:31-3:14; 3:50- 4:41; 4:47-5:47; Figs. 1-3. the contact hole is formed in	for purposes of forming an electrical connection. Intrinsic Support	an opening in one or more insulative layers to expose a portion of a conductive layer
				CMO Construction AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
extends through	С	is disposed in		
		Intrinsic Support		
		1:50-60; 2:36-3:15; 4:16-34;		
		4:47-64; 5:5-23; Figs 1-3.		
one of said first and second conductive layers is connected to	A C	one, but not both, of the first and second conductive		
one of a plurality of terminals of a		layers is directly connected		-
thin film transistor		to one terminal of a thin film transistor		
		Intrinsic Support		
		1:24-30; 2:31-3:15; 3:63- 4:5; 4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997,		
one of said first and second conductive layers	С	one, but not both, of the first and second conductive layers		
		Intrinsic Support		
		4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997, Amendment, at p. 5-7.		

			*	
·	one of a plurality of terminals of a thin film transistor	connected to		Claim Terms one
	Г	A C		Des.
4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997, Amendment, at p. 5-7.	one of the terminals (i.e., source, drain, or gate) of a thin film transistor	Intrinsic Support 1:24-30; 2:31-3:15; 3:63- 4:5; 4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997, Amendment, at p. 5-7.	Intrinsic Support 4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997, Amendment, at p. 5-7.	a single layer CMO Construction
·	-	-		AUO Construction

		Claim Terms Des. a plurality of terminals of C a thin film transistor
4 0 4		
4:46-5:23; Fig 3; App. No. 08/781,188, 12/1/1997, Amendment, at p. 5-7.	Intrinsic Support	the terminals (i.e., source, drain, or gate) of a thin film transistor
		CMO Construction
-		AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
liquid crystal display device	C	a type of display that generates an image by		
		directing light through an array of liquid crystal pixels,		
		where the amount of light effused by each pixel is controlled via an electric		
	·	field varying the orientation of the liquid crystal		-
		the pixel		
		Intrinsic Support		
		1:8-25; 1:31-34; Fig. 1-3.		
gate electrode	C A	a patterned electrically conductive material that controls current flow		
	***************************************	through the channel between the source electrode and drain electrode		
		Intrinsic Support		
		1:22-38; 56-60; 2:37-44; 2:56-61; 3:44-49; 4:47-53; 4:65-5:1; 5:29-38; Figs. 1-3.		

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
gate pad	A C	a portion of patterned electrically conductive		
		material that is provided		
		near the periphery of the		_
		thin film transistor array to receive a gate signal		
		Intrinsic Support		
		1:22-38; 1:52-60; 2:8-10; 2:19-26: 3:44-49: 4:6-15:		
		4:21-27; 4:35-41; 4:47-53; 4:65-5:1; 5:19-23; Figs. 1, 3.		
source pad	C	a portion of patterned, electrically conductive	TO CONTRACT	
	A	material that is provided		
		near the periphery of the		
		thin film transistor array to receive a data signal		
		Intrinsic Support		
		1:8-12; 1:22-38; 1:52-64; 2:8-10: 2:17-22: 3:66-4:5:		
		4:6-14; 4:24-27; 4:35-61;		
		4:65-5:1; 5:19-23; 5:48-51; Figs. 1-3.		

Claim Terms	a gate insulating film on said	surface of said substrate											
Des.	С												
LGD Construction	a thickness of non-	conductive material (such as	SiNx) that has high	electrical resistance and	insulates the transistor gate	from the semiconductor	above and in contact with at	least part of the surface of	the substrate	Intrinsic Support	1:52-55; 2:11-13; 2:19-26; 2:34-36; 2:40-44; 3:50-53;	4:1-15; 4:35-39; 4:47-50;	4:65-5:4; 5:12-15; 5:19-23; 5:40-46; Figs. 1-3.
CMO Construction													
AUO Construction			_~ .	_	e e e e e e e e e e e e e e e e e e e	,			-				

		insulating film											gate insulating film	Claim Terms
	T-M-S-S	C											C	Des.
1:52-55; 2:11-13; 2:19-26; 2:34-36; 2:40-44; 3:50-53; 4:1-15; 4:35-39; 4:47-50; 4:65-5:4; 5:12-15; 5:19-23; 5:40-46; Figs. 1-3.	Intrinsic Support	a thickness of non- conductive material (such as SiNx) that has high electrical resistance	5:40-46; Hgs. 1-3.	4:65-5:4; 5:12-15; 5:19-23;	4:1-15; 4:35-39; 4:47-50;	2:34-36; 2:40-44; 3:50-53;	1:52-55; 2:11-13; 2:19-26;	Intrinsic Support	from the semiconductor	insulates the transistor gate	SiNx) that has high	conductive material (such as	a thickness of non-	LGD Construction CMO Construction
								-		-				AUO Construction

		semiconductor layer			Claim Terms a semiconductor layer on said portion of said gate insulating film
		С			C C
1:40-51; 1:61-2:4; 2:37- 3:15; 3:50-4:5; 4:65-5:5; Figs 1-3.	Intrinsic Support	a thickness of semiconductor material, such as amorphous silicon	1:40-51; 1:61-2:4; 2:37- 3:15; 3:50-4:5; 4:65-5:5; Figs 1-3.	Intrinsic Support	a thickness of semiconductor material above and in contact with a part of the gate insulating film
					AUO Construction

impurity-doped semiconductor layer	C		CMO Construction
		to which impurities (such as phosphorous atoms) have been added to enhance electrical conductivity	
		Intrinsic Support 1:40-51; 1:61-2:4; 2:37-	
		Figs 1-3.	
a source electrode and a drain electrode on said semiconductor layer	A	a source electrode and a drain electrode above and in contact with the	
		Intrinsic Support	
		1:40-51; 1:61-2:4; 2:37- 3:15; 3:50-4:5; 4:65-5:15; Figs 1-3.	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
source electrode	A C	a patterned, electrically conductive material formed		
		over the source region.		
		Current flows through the channel between the source		
		electrode and drain electrode		
	W. C. A.	under control of the gate electrode		
		Intrinsic Support		
		1:8-12; 1:22-30; 1:61-2:4; 2:11-27; 2:37-3:15; 3:63-		
		4:5; 4:47-64; 5:6-22; 5:29- 39; 5:48-54; Figs. 1e-1f; 2c- e, 3.		
drain electrode	A C	a patterned, electrically conductive material formed over the drain region.		
		over the drain region. Current flows through the channel between the source		
		the control of the gate electrode		
		Intrinsic Support		
		1:8-12; 1:22-30; 1:61-2:4; 2:11-27; 2:37-3:15; 3:63-		
		4:5; 4:47-64; 5:6-22; Figs.		

1: 55 63 3.		exposing said gate pad portion A r		Claim Terms passivation layer C I I S
1:52-60; 2:5-10, 17-28, 45- 55; 3:1-14, 3:66-4:15; 4:35- 65; 5:6-22; Abstract; Figs 1- 3.	Intrinsic Support	removing portions of one or more layers to uncover at least part of a gate pad [portion]	Intrinsic Support 2:5-10; 2:19-26; 2:34-36; 2:40-46; 3:50-53; 4:1-15; 4:35-39; 4:47-50; 4:65-5:4; 5:12-15; 5:19-23; 5:40-46; Figs. 1-3.	a thickness of insulative material that provides protection such as electrical stability and chemical isolation
				CMO Construction
				AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
transparent conductive layer	C	a thickness of transparent electrically conductive material		<u> </u>
		Intrinsic Support		
		1:55-60; 4:16-19; 4:39-41; 5:15-22; Figs 1-3.		-
a method of manufacturing a liquid crystal display device	С	a process for producing a liquid crystal display device		-
		Intrinsic Support		
		1:8-25; 1:31-34; Fig. 103.		
patterning to form an active layer	С	the removal of selected portions of the impurity-doped semiconductor layer and the semiconductor layer using etching techniques in order to form an active layer	`	
		Intrinsic Support		
		1:34-37; 1:44-50; 1:55-67; 2:16-28; 2:56-3:14; 3:44- 4:5; 4:16-24; 4:47-5:22; Figs 1-3.		

	ac				pa	
	active layer	-			patterning	Claim Terms
	> C				C	Des.
located at least in part above the gate electrode. In operation, the discrete portion is penetrated, at least in part, by the electric field introduced by the gate electrode. Intrinsic Support 1:34-51; 1:61-2:4; 2:11-27;	a discrete portion of semiconductor layer that is formed by patterning and	1:34-3/; 1:44-50; 1:55-6/; 2:16-28; 2:56-3:14; 3:44- 4:5; 4:16-24; 4:47-5:22; Figs 1-3.	Intrinsic Support	etching techniques in order to produce a pattern in the remaining material	the removal of selected portions of a surface using	LGD Construction
					6	CMO Construction
						AUO Construction

	ţ	TOP COMMUNICATION	CALC CONSTITUTION	THE COMMENSATION
selectively etching	С	the removing selected		
		portions of a surface using		
		etching techniques (such as		
		wet etching, plasma etching,		-
		reactive ion etching, and ion		
		etching) in order to produce		
		surface		
		Intrinsic Support		
		1:47-55; 2:8-10; 2:31-36:		
		2:50-51; 3:59-61; 3:67-4:1;		
		4:8-19; 4:35-39; 4:47-50;		
		5:1-15; 5:40-47; Figs 1-3.		
patterning a pixel electrode	C	the removal of selected		
electrically connected to said		portions of a pattern of		
drain electrode		transparent electrically		
		conductive material to form	- Notes and	
		a pixel electrode that has an		
		electrical conduction path		
		with the drain electrode		
		Intrinsic Support		
		1:34-37; 1:44-50; 1:55-67;		
		4:5; 4:16-24; 4:47-5:22; Figs		
		1-3.		

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
electrically connect/electrically connected	V	provide an electrical		
0		7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7 7		~ .
	- 444	Intrinsic Support		
		1:24-30; 2:31-3:15; 4:56-64; 5:8-22; Figs 1-3.		

C-2

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Claim Terms	Des.	Agreed Constructions
substrate	С	the material (such as glass) upon which a transistor or integrated circuit is fabricated to
	,	provide mechanical support.
indium tin oxide layer	C	a thickness of indium tin oxide (ITO)

Disputed Constructions

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
wiring structure	С			A structure made by wires
				Intrinsic Support
				E.g.,
				Figs. 2-5; 2:31-3:14
	:			
conductive layer	L C			Plain meaning
layer	С			Plain meaning

Claim Terms	Des.	LGD Construction CM	CMO Construction	AUO Construction
formed on a first portion of said	C			Produced above, supported by and in contact with a
				first portion of the substrate
				Intrinsic Support
				E.g.,
		-		Figs. 3, 4, & 5;
				4:65-5:5;
				5:23-38;
				5:39-54
formed on	A A			Produced above, supported by, and in contact with Intrinsic Support
				E.g.,
				Fig. 3, 4, & 5; 4:46-4:64:
				4:65-5:5;
				5:23-38; 5:39-54

Produced above, supported by, and in contact with a second portion of the substrate Intrinsic Support E.g., Figs. 3, 4, & 5; 4.46-4.64; 4:65-5.5; 5:23-38; 5:39-54 Produced above, supported by, and in contact with a first portion of the first insulative layer Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54
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		forme layer said f overly layer
	overlying	ed on and of irst in the ying
	ng	Claim Terms said second c on a second ponsulative layer said first cond
		cond cc cond por e layer t condu
		nductive ctive
	С	Des.
		\ \frac{1}{2}
		Const
		LGD Construction
AND THE PROPERTY OF THE PROPER		
		CMO Cons
		nstruction
		tion
E.g., Figs. 4:46- 5:6-5 5:23- 5:39-	Cov	Produby, au secor a secor insulation top su conduction E.g., Figs. 4:46-5:6-55:39-
Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54	ering t	AUO Constructio Produced above, suppo by, and in contact with second conductive layer a second portion of the insulative layer coverin top surface of the first conductive layer Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54
<u>apport</u> & 5;	he top :	Construction of the layer of the layer sport
•	Covering the top surface of	Produced above, supported by, and in contact with the second conductive layer and a second portion of the insulative layer covering the top surface of the first conductive layer Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54
	of	the

extends through C	expose part of said layer C	provided through C	contact hole C						 layers A	contact hole is provided through C	Claim Terms Des.
					-						LGD Construction
											CMO Construction
Plain meaning	Plain meaning	See above	Plain meaning	5.23-53	4:46-5:53;	Fig. 3, 4, & 5;	E. GO.	Intrinsic Support	 in the layers	The contact hole is formed	AUO Construction

				one of said first and second conductive layers						one of a plurality of terminals of a thin film transistor	conductive layers is connected to	one of said first and second	Claim Terms
				econd		7.00 The Case Selection of the Case Selectio		w		nals of a	ected to	nd br	
	,,		······································	С				, , , , , , , , , , , , , , , , , , , 			A	С	Des.
			- Carrollens										LGD Construction
													CMO Construction
App 08/781,188, 12/01/97 Response, pg. 1-7	Fig. 3, 4, & 5; 4:46-5:53; 5:23-53	E.g.,	Intrinsic Support	At least one of the first and second conductive layers.	App 08/781,188, 12/01/97 Response, pg. 1-7	Figs. 3, 4, & 5; 4:46-5:53; 5:23-53	E.g.	Intrinsic Support	drain, and gate electrodes of a thin film transistor.	least one of the source	second conductive layers is	At least one of the first and	AUO Construction

LGD Construction CMO Construction AUO Construction Intrinsic Suppo E.g., Figs. 3, 4, & 5; 4:46-5:53; 5:23-53 App 08/781,18 Response, pg. Intrinsic Suppo E.g., Figs. 3, 4, & 5; 4:46-5:53; 5:23-53;	connected to C A	OILC	Jaim Terms
	Electrically connected to Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-5:53; 5:23-53	Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-5:53; 5:23-53 App 08/781,188, 12/01/97 Response, pg. 1-7	

			·						- E
			a plurality of terminals of a thin film transistor					of a thin film transistor	Claim Terms
			C					7	Des.
									LGD Construction
									CMO Construction
App 08/781,188, 12/01/97 Response, pg. 1-7	Figs. 3, 4, & 5; 4:46-5:53; 5:23-53	Eg	Source, drain, and gate electrodes of a thin film transistor	App 08/781,188, 12/01/97 Response, pg. 1-7	Figs. 3, 4, & 5; 4:46-5:53; 5:23-53	E. 69	Intrinsic Support	gate, and drain electrodes of a thin film transistor	AUO Construction

liquid crystal display device C																					thin film transistor C	Claim Terms Des.
																				-		s. LGD Construction
Plain meaning	silicon wafer	rather th	on an in	using th	film trai	insulati	semicor	which is	electrod	applied	introduc	semicor	field tha	modulat	electrod	electrod	electrod	through	which the	semicor	A three-	CMO Construction AU
neaning	wafer.	rather than a single crystal	on an insulating substrate	using thin-film techniques	film transistor is formed	insulating layer. The thin-	semiconductor by an	which is separated from the	electrode, the gate electrode,	applied at the third	introduced by a voltage	semiconductor; this field is	field that penetrates the	modulated by an electric	electrode, is controlled or	electrode and drain	electrodes, the source	through one pair of	which the current flow	semiconductor device in	A three-terminal	AUO Construction

						and the And				gate electrode	Claim Terms
									Α	C	Des.
											LGD Construction
											CMO Construction
Fig. 3; 2:37-3;14 (Summary of the Invention)	E.g.,	Intrinsic Support	electrode	under control of the gate	and the drain electrode	between the source electrode	flows through the channel	in the gate region. Current	conductive material formed	A patterned, electrically	AUO Construction

cate and	כ	The second secon
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	A patterned, electrically conductive material that is
	conductive material that is
	provided near the periphery
	of the thin film transistor
,	array to receive a data signal
	from a data driving circuit
	Intrinsic Support
	1
	ţ;
	Figs. 3, 4, & 5;
	2:37-3;14 (Summary of the
-	Invention)
	4:46-4:64;
	4:65-5:5;
	5:23-38;
	5:39-54

				a gate insulating film on said surface of said substrate	
	ŕ			<u>م</u>	Des.
					LGD Construction
					CMO Construction
Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-4:64; 4:65-5:5; 5:23-38; 5:39-54	E.g.	Intrinsic Support	contact with the surface of the substrate	A gate insulating film	AUO Construction

insulating film		gate insulating film	Claim Terms
С		0	Dec
		LGD Construction	I CD Construction
		CMO Construction	CMO Construction
Plain meaning	E.g., Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-4:64; 4:65-5:5; 5:23-38; 5:39-54	Plain meaning; or Insulating film formed over the gate region Intrinsic Support	AIIO Construction

CMO Construction

		,			
			,	impurity-doped semiconductor laver	Claim Terms
				C	Des.
					LGD Construction
					CMO Construction
Figs. 3, 4, & 5; 4:46-4:64; 4:65-5:5; 5:23-38; 5:39-54	Intrinsic Support	Semiconductor layer doped with impurities	or	Plain meaning;	AUO Construction

												layer	electrode on said semiconductor	a source electrode and a drain	Claim Terms
														A	Des.
							-								LGD Construction
															CMO Construction
5:39-54	5:23-38;	5:6-5:15;	4:46-4:64;	Invention)	2:37-3;14 (Summary of the	Figs. 3, 4, & 5;	E.g.,	-	Intrinsic Support	 layer	with the semiconductor	supported by, and in contact	drain electrode above,	The source electrode and the	AUO Construction

·			Source electrode C	rms
				nstruction CMO Construction
Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54	E.g.	Intrinsic Support	A patterned, electrically conductive material formed over the source region. Current flows through the channel between the source electrode and the drain electrode under control of the gate electrode.	AUO Construction

			drain electrode
			Des. A
			LGD Construction
	e.		struction
			CMO Construction
Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54	E.g.,	Intrinsic Support	A patterned, electrically conductive material formed over the drain region. Current flows through the channel between the source electrode and the drain electrode under control of the gate electrode.
the			med he urce

			exposing said gate pad portion	passivation tayor	Claim Terms I
			A		Des. LGD Construction CMO Construction
Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-5:22	E.g.,	Intrinsic Support	Causing the gate pad to be exposed to the atmosphere	Intrinsic Support E.g., Figs. 3, 4, & 5; 2:37-3;14 (Summary of the Invention) 4:46-4:64; 5:6-5:15; 5:23-38; 5:39-54	AUO Construction Plain meaning

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
exposing	С		Laying open or causing to be exposed from above
			Intrinsic Support
			E GO
		-	Figs. 3, 4, & 5; 4:46-5:53; 5:23-53
pixel electrode	С		Electrode controlling the brightness of a pixel
			Intrinsic Support
			E.g.,
			Figs. 3, 4, & 5; 4:46-4:64;
	,		5:16-23; 5:39-54
transparent conductive layer	С		Plain meaning
a method of manufacturing a	С		Plain meaning
liquid crystal display device			

	patterning					layer	patterning to form an active C
to produce a pattern in the remaining material Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-4:64; 4:65-5:5 5:23-53	selectively removing portions of a surface using etching techniques in order	4:65-5:5 5:23-53	Figs. 3, 4, & 5; 4:46-4:64;	E.g.,	an acuve region Intrinsic Support	portions of using etching techniques in order to form	selectively removing

selectively removing portions of a pixel electrode using etching techniques in order to electrode to the pixel electrode drain electrode Intrinsic Support E.g., Figs. 3, 4, & 5; 4:46-5:53 Plain meaning
B S S C S C S C S C S C S C S C S C S C

C-3

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Claim Terms 1	Des.	Agreed Constructions
substrate		the material (such as glass) upon which a transistor or integrated circuit is fabricated to
		provide mechanical support
indium tin oxide layer		a thickness of indium tin oxide (ITO)
contact hole is provided through		the contact hole is formed in the layer
layer[s]		

Disputed Constructions

conductive layer L C		
	conductive material that	
	may include one or more patterned features, all of a single material	
	Intrinsic Support	
	1:34-37; 1:56-60; 1:61-64;	-
	2:37-46; 3:44-47; 4:61 - 5:22; 7:36-39 (claim 10);	-
	Figs. 1a, 1e, 2a, 2e, 3	
	'449 File history, 8/1/97 Office Action, para. 2.	
layer C	plain meaning	
formed on a first portion of said C substrate	above and in contact with a first part of the substrate	
	Intrinsic Support	
	1:56-60; Figs. Ia, 1e, 2a, 2e,	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
formed on	A C		above and in contact with	
			Intrinsic Support	
			1:35-38, 1:42-44, 1:44-48,	
			2:37-40, 2:42-44, 3:44-47,	
			3:56-60; Figs. 1a-1f, 2a-2e,	
formed on a second portion of	C		above and in contact with a	
said substrate			second part of the substrate	
			Intrinsic Support	
			1:35-38, 3:44-47; Figs. 2b, 3	
formed on a first portion of said first insulative layer	C		bove and in contact with a first part of the first insulative layer	-
			Intrinsic Support	
			1:42-44; Figs. 2b, 3, 5	
insulative layer	C		plain meaning	
***************************************				The state of the s

one of said first and second Conductive layers							thin film transistor	one of a plurality of terminals of a	one of said first and second C	Claim Terms Des. LGD Construction
this term should be construed as part of the larger term "one of said first and second conductive layers is connected to one of a plurality of terminals of a thin film transistor"	Claims 2, 6	'449 File history, 11/17/97 Amendment & Response, pages 1-7	'449 File history, 8/1/97 Office Action, para. 6	2:16-28, 4:65-5:13; 5:16-22; 5:23-39; 5:40-51, Figs. 3, 4, 5	Intrinsic Support	connected to the gate, source or drain of the thin film transistor	transistor, and/or the second conductive layer is	or drain of a thin film	the first conductive layer is	CMO Construction
					-					AUO Construction

one of a plurality of terminals of a thin film transistor	connected to	one	Claim Terms
	C A	Г	Des.
			LGD Construction
this term should be construed as part of the larger term "one of said first and second conductive layers is connected to one of a plurality of terminals of a thin film transistor"	plain meaning	this term should be construed as part of the larger term "one of said first and second conductive layers is connected to one of a plurality of terminals of a thin film transistor"	CMO Construction
	-		AUO Construction

						 			
							film transistor	a plurality of terminals of a thin	Claim Terms
								С	Des.
				-					LGD Construction
'449 File history, 11/17/97 Amendment & Response, page 5	the gate, source, and drain of a thin film transistor	proposes the following construction:	embedded term "terminals of a thin film transistor"	to the extent that the	a plurality of terminals of a thin film transistor"	and second conductive layers is connected to one of	construed as part of the larger term "one of said first	this term should be	CMO Construction
				-		-			AUO Construction

							•		thin film transistor	Claim Terms
									C	Des.
LGD-9										LGD Construction
	'449 Prosecution History, 11/17/97 Amendment & Response, page 5	5/5/05 Order re Claim Construction, Case No. 02- 6775, at 13; Second Revised Joint Claim Construction Statement, Case No. 02- 6775, at 157-159	1:13-30; Figs. 1f, 2e, 3, 4	on an insulating substrate rather than in a single crystal silicon wafer.	from the semi-conductor by an insulating layer. The thin- film transistor is formed using thin-film techniques	semiconductor; this field is introduced by a voltage applied at the third terminal, the gate, which is separated		the current flow through one pair of terminals, the source	A three terminal semi- conductor device in which	CMO Construction
										AUO Construction

gate electrode C A	liquid crystal display device C	Claim Terms Des. LGD Construction
a patterned, electrically conductive material that controls current flow through the channel between the source electrode and drain electrode Intrinsic Support Figs. 1a, 1e, 2a, 2e, 3 (e.g., element 2); 3:44-49; see also 1:34-37; 2:37-44; 2:56 – 3:1; 5:29-38.	a type of display that generates an image by directing light through an array of liquid crystal pixels, where the amount of light effused by each pixel is controlled via an electric field varying the orientation of the liquid crystal molecules contained within the pixel Intrinsic Support 1:13-30; Fig. 6	tion CMO Construction AUO Construction

Claim Lerms	Des.	TAD COUST ICHOR	CIATO COTISTI ACTION
gate pad	С		a portion of patterned,
1	Α		electrically conductive
			material that is provided
			near the periphery of the
			thin film transistor array to
			gate driving circuit
			(
	······································		Intrinsic Support
			Figs. 1a–1e, 2a–2e (e.,g., element 2C). 3 (e.g., element
			2B), 6
			1:27-30; 1:34-38; 1:52-55;
			2:39-40; 2:59-61; 4:8-15;
			4:4/-53; 4:65 – 5:1.
			5/5/05 Order re Claim
			Construction, Case No. 02-
			Joint Claim Construction
	1071 11 11		Statement, Case No. 02-
			6775, at 162-165.

	C			,
	plain meaning		C	gate insulating film
	plain meaning		C	a gate insulating film on said surface of said substrate
	6775, at 165-168			
	Joint Claim Construction			
	Construction, Case No. 02-			
	5/5/05 Order re Claim			
	1:27-30; 1:34-38; 1:52-55; 1:67 – 2:4; 4:8-15.		,	
•				
- -	Figs. 1a-1e, 2a-2e, 3 (e.g., element 2A), 6			
	Intrinsic Support			
	data driving circuit			
	thin film transistor array to		······	
	near the periphery of the		Α	
de la companya de la	electrically conductive		- a	
	a portion of patterned,		Ţ	source pad
AUO Construction	CMO Construction	s. LGD Construction	Des.	Claim Terms

Claim Terms	Des.	LGD Construction CM	CMO Construction	AUO Construction
a semiconductor layer on said portion of said gate insulating film	С	a thickness of semiconductor above and in c part of the gate film	a thickness of semiconductor material above and in contact with a part of the gate insulating film	
		Intrinsic	Intrinsic Support	
		Figs. 1b	Figs. 1b – 1f, 2b – 2e, 3	-
		1:53-54, 2:42-4 3:50-62; 5:1-5	1:53-54, 2:42-44; 2:61-64; 3:50-62; 5:1-5	
semiconductor layer	С	a thickn semicor such as	a thickness of a semiconductor material, such as amorphous silicon	
		Intrinsic	Intrinsic Support	
		1:53-54 Figs. 1b	1:53-54, 2:42-44; 5:1-5; Figs. 1b – 1f, 2b – 2e, 3	
		The state of the s		

			a source electrode and a drain electrode on said semiconductor layer					layer	impurity-doped semiconductor C
1:44-50; 1:61-67; 3:56-60; 3:63-66; 4:27-34; 5:6-8	Figs. 1e – 1f, 2c – 2e, 3 (e.g., source electrode 7 and drain electrode 8)	Intrinsic Support	a source electrode and a drain electrode above and in contact with the semiconductor layer	1:43-48, 3:52-63; 5:1-5; Figs. 2b – 2e, 3 (e.g., element 5)	Intrinsic Support	been added to enhance electrical conductivity	to which impurities (such as	semiconductor material,	a thickness of

					Claim Terms source electrode
					Des. C A
					LGD Construction
drain electrode 8) 1:44-50; 1:61-67; 3:56-60; 3:63-66; 4:27-34; 5:6-8	Intrinsic Support Figs. 1e – 1f, 2c – 2e, 3 (e.g., source electrode 7 and	the source electrode and the drain electrode of the transistor under control of the gate electrode of the transistor.	Patterned, electrically conductive material formed over the source region and drain region, respectively, of a transistor. Current flows	drain electrode" as:	CMO Construction Construe term: "a source electrode and a
				· -	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
drain electrode	С		this term should be	
	Α		construed as part of the	
			larger term "a source	
			electrode and a drain	-
			electrode" (see above)	
passivation layer	С		a thickness of insulative	
			material that provides	
			protection such as electrical	-
			stability and chemical	
			Intrinsic Support	
			Figs. 1f, 2d – 2e, 3 (e.g.,	
			5:6-15	
exposing said gate pad [portion]	\triangleright		plain meaning	
exposing	С		plain meaning	
pixel electrode	С		electrode controlling the brightness of a pixel	
			Intrinsic Support	
			1:15-19, 1:26-30, 1:56-59, 1:67 – 2:4	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
transparent conductive layer	С		plain meaning	
a method of manufacturing a liquid crystal display device	С		plain meaning	
patterning to form an active layer	С		plain meaning	
patterning	С		plain meaning	

plain meaning plain meaning		A C	patterning a pixel electrode electrically connected to said drain electrode electrically connect/electrically
plain meaning		С	selectively etching
Statement, Case No. 02-6775, at 176-177.			
 Construction, Case No. 02-6775, at 18; Second Revised			
5/5/05 Order re Claim		-	
1:42-44; 3:47-49; 3:50-62; 5:1-5			
 Intrinsic Support			
electrode of the thin film transistor.			
by the electric field	-		
penetrated, at least in part,			
transistor. In operation, the			
electrode of a thin film			
located along the gate			
semiconductor layer that is formed by patterning and		A	
A discrete portion of the		- C	active layer

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Claim Terms	Des.	Agreed Constructions
drain electrode	Α	A patterned, electrically conductive material formed over the drain region. Current flows
		through the channel between the source electrode and drain electrode under control of the
		gate electrode.
source electrode	Α	A patterned, electrically conductive material formed over the source region. Current flows
		through the channel between the source electrode and drain electrode under control of the
		gate electrode.

sputed Construction

	Claim Terms the gate line having an opening therein
	A A
Intrinsic Support 1:13-16; 1:67-2:11; 2:23-67; 3:2-6; 3:30-48; 4:6-11; 4:20- 40; 4:47-5:2; 5:41-6:17; 6:21-41; 7:40-57; 7:60-8:28; 8:36-9:17; Abstract; Figs. 4- 9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	the gate line has a space in its pattern to reduce gatedrain capacitance and compensate for gate-drain layer misalignment
	AUO Construction

			Claim Terms a gate line
			Des.
1:67-2:11; 2:23-35; 2:63-67; 3:2-6; 3:30-48; 5:41-6:17; 6:21-41; 7:60-8:4; 8:36-42; 8:63-9:17; Abstract; Figs. 4- 9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	Intrinsic Support	conductive material that conveys gate signals to transistors, a portion of which controls current flow through the channel between the source and drain electrodes	a pattern of electrically CMO Construction
			AUO Construction

	Claim Terms having an opening therein
70 8 5 A C 7 A 5 5 4 1	Des. L h r c fi n l l
1:13-16; 2:23-3:67; 4:6-11; 4:20-40; 4:47-5:2; 5:47-57; 5:66- 6:17; 6:28-41; 7:40- 57; 8:2-28; 8:41-9:17; Abstract; Figs. 5-9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	has a space in its pattern to reduce gate-drain capacitance and compensate for gate-drain layer misalignment Intrinsic Support
	CMO Construction
	AUO Construction

	· ·
a drain electrode on the semiconductor layer over at least a portion of the opening	a semiconductor layer on the first insulating layer over at least a portion of the opening
>	A A
a drain electrode, above and supported by or in contact with the semiconductor layer, a portion of which overlaps part of the space in the gate line Intrinsic Support 2:6-11; 2:24-3:29; 3:36-40; 3:48-67; 4:9-11; 4:32-40; 4:48-65; 5:54-6:17; 6:64-7:23; 7:41-8:28; 8:37-9:17; Figs. 4, 6b, 6c-9; Abstract.	a layer of semiconductor material, above and supported by or in contact with the first insulating layer, a portion of which overlaps part of the space in the gate line Intrinsic Support 4:30-40; 6:29-58; 7:6-24; 8:1-13; Fig. 4-9; Abstract.
	AUO Construction

Claim Terms	Des.	LGD Construction CMO Construction AUO	AUO Construction
pixel electrode	A		
		material that stores charge to drive the liquid crystal	
		material within an individual element of the liquid crystal display device	<u>-</u>
		Intrinsic Support	-
		1:37-65; 2:13-22; 7:33-39; Fig 1, 2, 9.	
substantially surrounds the drain electrode	A	extending considerably around a portion of the drain electrode	
		Intrinsic Support	
		4:20-40; 5:59-65; 6:66-7:7:5; 8:5-10; Abstract; Fig. 5, 6B, 6C, 7, 8.	
substantially	Α	considerably	
		Intrinsic Support	
		4:20-40; 5:59-65; 6:66- 7:7:5; 8:5-10; Abstract; Fig. 5, 6B, 6C, 7, 8.	

			the gate electrode having an opening therein	Claim Terms
117.07.00.00			Þ	Des.
1:13-16; 1:67-2:11; 2:23-67; 3:2-6; 3:30-48; 4:6-11; 4:20-40; 4:47-5:2; 5:41-6:17; 6:21-41; 7:40-57; 7:60-8:28; 8:36-9:17; Abstract; Figs. 4-9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	Intrinsic Support	gate-drain capacitance and compensate for gate-drain layer misalignment	the gate electrode has a space in its pattern to reduce	LGD Construction
				CMO Construction
				AUO Construction

						gaic electione	Claim Terms
						≯ t	Des.
pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	6:21-41; 7:60-8:4; 8:36-42; 8:63-9:17; Abstract; Figs. 4- 9; App. No. 09/867,484, 03/13/3003, Office Action;	1:67-2:11; 2:23-35; 2:63-67; 3:2-6; 3:30-48; 5:41-6:17;	Intrinsic Support	the source electrode and drain electrode	includes a portion that controls current flow	conductive material that	ion
							CMO Construction A
, -		-	_				AUO Construction

		the opening includes a first opening portion and a second opening portion	Claim Terms
		A	Des.
1:13-16; 2:23-3:67; 4:6-11; 4:20-40; 4:47-5:2; 5:47-57; 5:66-6:17; 6:28-41; 7:40- 57; 8:2-28; 8:41-9:17; Abstract; Figs. 5-9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	Intrinsic Support	n S a	LGD Construction CMO Construction
-			AUO Construction

		a first opening portion	Claim Terms
		٢	Des.
1:13-16; 2:23-3:67; 4:6-11; 4:20-40; 4:47-5:2; 5:47-57; 5:66-6:17; 6:28-41; 7:40- 57; 8:2-28; 8:41-9:17; Abstract; Figs. 5-9; App. No. 09/867,484, 03/13/3003, Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.	Intrinsic Support	a first part to primarily compensate for gate-drain layer misalignment	LGD Construction
			CMO Construction
			AUO Construction

	reduce gate-drain	e	
	capacitance Intrinsic Support		· · ·
	1:13-16; 2:23-3:67; 4:6-11; 4:20-40; 4:47-5:2; 5:47-57; 5:66-6:17; 6:28-41; 7:40-		-
	57; 8:2-28; 8:41-9:17; Abstract; Figs. 5-9; App. No. 09/867,484, 03/13/3003,		-
	Office Action; pages 3-4; App. No. 09/867,484, 5/6/2003, Interview		
	Summary; App. No. 09/867,484, 5/8/2002, Response, page 10-11.		
a first electrode L	a first portion of the drain electrode to primarily compensate for gate-drain		
	layer misalignment Intrinsic Support		
	4:48-5:2; 5:4-6:17; 7:6-23; 7:41-59; 8:7-28; 8:34-9:17; Abstract; Figs. 2-925-31,		

Claim Lerms	Des.	LGD Construction	CIVIO Construction	ACC Construction
a second electrode	L	a second portion of the drain electrode to primarily reduce		
		gate-drain capacitance		
		Intrinsic Support		
		4:48-5:2; 5:4-6:17; 7:6-23;		
		7:41-59; 8:7-28; 8:34-9:17;		
		Abstract; Figs. 2-925-31,		-
		1,001,000	The state of the s	
a third electrode	ŀ	a third portion of the drain electrode to primarily connect to the pixel electrode		
		Intrinsic Support		
		2:13-22; 4:41-47; 7:24-39; Abstract; Figs. 2-5, 6B, 6C, 7-9.		
connects	Т	joins		
	•	Intrinsic Support		
		2:13-22; 4:41-47; 5:61-65; 7:24-39; Figs. 2-5, 6B, 6C, 7-8		

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Claim Terms	Des.	Agreed Constructions
drain electrode	Α	A patterned, electrically conductive material formed over the drain region. Current flows
		through the channel between the source electrode and drain electrode under control of the
		gate electrode.
source electrode	Α	A patterned, electrically conductive material formed over the source region. Current flows
		through the channel between the source electrode and drain electrode under control of the
		gate electrode.

Disputed Constructions

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							PILATATI	the gate line having an opening A	Claim Terms Des.
									LGD Construction CMO Const
App 09/867484, 5/12/03 Response, pages 10-11	7:6-17; 7:41-43;	6:31-41; 8:7-10; 8:37-42:	Abstract; 4:63-65; 6:13-15:	Figs. 5-8;	E.g.	Intrinsic Support	periphery of the gate line to the interior of the gate line	Gate line with a cut out	nstruction AUO Construction

										
		having an opening therein							a gate line	Claim Terms
		٢							Ţ	Des.
										LGD Construction CMO Construction
See support for limitation "the gate line having an opening therein"	Intrinsic Support	Having a cut out extending from the periphery to a point within	1:65-2:8; 2:63-65	5:40-53; 8:37-42;	Figs. 1, 2, 7, 8; 2:23-25;	E.g.	Intrinsic Support	signals to gate electrodes	An elongated directional	ion AUO Construction

			n the first east a	Claim Terms
			A	Des.
			CONST. ROBOT.	LGD Construction
			CHACTOR	CMO Construction
Figs. 6A, 8 and 9 6:47-54	E.g.,	Intrinsic Support	A semiconductor layer above, supported by, and in contact with the first insulating layer, the semiconductor layer being over at least a portion of the opening in the gate line	AIIO Construction

		pixel electrode A					a portion of the opening	a drain electrode on the A
								LOD COMSK HORION
								CITA O COMOU MCCHOM
Figs. 1-5, 6B-6C, 7-9; 1:38-48; 2:13-22; 2:24-39; 4:43-36; 6:61-63; 7:34-40	Intrinsic Support E.g.,	Electrode controlling the brightness of a pixel	7:48-51; 7:6-20	Figs. 6A, 8 and 9	Intrinsic Support E.g.,	being over at least a portion of the opening in the gate line	supported by, and in contact with the semiconductor layer, the drain electrode	A drain electrode above,

Claim Terms substantially surrounds the drain electrode	Des.	LGD Construction CMO Construction	AUO Construction Surrounds almost all the drain electrode portion Intrinsic Support E.g.,
			E.g., Figs. 5 6B, 6C 4:37-40; 5:53-61; 6:66-7:2; 7:18-23; 8:5-7.
substantially	⊳		Almost all Intrinsic Support
			E.g.,
			Figs. 5 6B, 6C 4:37-40; 5:53-61; 6:66-7:2; 7:18-23; 8:5-7.

						gate electrode	Claim Terms
					*****	A	Des.
							LGD Construction
							CMO Construction
App 09/867484, 5/12/03 Response, pages 10-11	Figs. 2-5; 8:64-65; 3:30-40; 4:27-31; 6:27-32.	E.g.,	Intrinsic Support	and the drain electrode under control of the gate electrode.	in the gate region. Current flows through the channel between the source electrode	A patterned, electrically conductive material formed	AUO Construction

Claim Terms the opening includes a first opening portion and a second	Des.	LGD Construction	CMO Construction	Non-rectangular-shaped opening having two distinct
opening portion				opening portions Intrinsic Support
				F.g.
		-		Figs. 6A, 6B, 9. Abstract;
				6:32-41; 7:17-18
a first opening portion	Г			One distinct opening portion
				Intrinsic Support
				See above
a second opening portion	T			Another distinct opening portion
				Intrinsic Support
				See above

<u>α</u> ω	af
a second electrode	a first electrode
L	L L
	LGD Construction
	CMO Construction
Another distinct portion of the single electrode Intrinsic Support E.g., Figs. 5, 6B, 6C, 7-9 4:53-60; 7:6-17; 6:6-12	AUO Construction One distinct portion of a single electrode Intrinsic Support E.g., Figs. 5, 6B, 6C, 7-9 4:53-60; 7:6-17; 6:6-12

Claim Terms	Des.	LGD Construction CM	CMO Construction AUO	AUO Construction
a third electrode	T	-		The third distinct portion of
			the single electrode	electrode
			Intrinsic Support	Support
			E.g.,	
			Figs. 5, 6B 5:61-65; 7:29-32	Figs. 5, 6B, 6C, 7, 8 5:61-65; 7:29-32
connects	I		Physically attached	y attached
			Intrinsic Support	Support
			E.g.,	
			Figs. 5, 6B 5:57-65	Figs. 5, 6B, 6C, 7, 8 5:57-65

E-1

Disputed Constructions

	Г	11.75.WT.				
	a first substrate				a liquid crystal display device	Claim Terms
	C				С	Des.
Intrinsic Support 5:11-22; 7:9-13; Figs. 2, 3, and 4.	one of a TFT or color filter substrate	Intrinsic Support 1:23-48.	a type of display that generates an image by directing light through an array of liquid crystal pixels, where the amount of light effused by each pixel is controlled via an electric field varying the orientation of the liquid crystal molecules contained within the pixel	or	plain meaning	LGD Construction
						CMO Construction
			·			AUO Construction

	on a single production process line	a second substrate	Claim Terms
	Ţ	C	Des.
Intrinsic Support 3:25-42; 5:23-30; 7:9-13, 35-41; Figs. 2, 3, and 4; App 10/124,452, 6/17/04 Notice of Allowability, pages 2-3.	on a production line where the processing equipment is arranged along a common path for performing the liquid crystal cell processes	the other of the TFT or color filter substrate Intrinsic Support 5:11-22; 7:9-13; Figs. 2, 3, and 4.	LGD Construction
			CMO Construction
			AUO Construction

					*		
	in serial order		a sealing material coating portion of the single production process line		material coating portion of the single production process line in serial order	passing the first and second substrates through a sealing	Claim Terms
	Α		Α			C	Des.
Intrinsic Support 5: 39-50, 55-66; 6:27-46, 62-7; 7:1-13, 21-3.	one after the other	Intrinsic Support 3:25-42; 5:11-30; 5:39-50; 5:62-66; 6:27-34; 6:42-6; 7:1-13; 7:35-41; Figs. 2, 3, and 4.	a portion of the single production process line where the sealing material is selectively applied	Intrinsic Support 3:25-42; 5:11-30, 39-50, 62- 6; 6:27-34, 42-6; 7:1-13, 35- 41; Figs. 2, 3, and 4; App 10/124,452, 6/17/04 Notice of Allowability, pages 2-3.	other, along a portion of the single production process line where the scaling material is selectively applied	ond T	LGD Construction CMO Construction
				-		AUO Consu action	AUO Construction

	· ·
a liquid crystal dispensing portion of the single production process line	passing the first and second substrates through a liquid crystal dispensing portion of the single production process line in serial order
Α	C C
a portion of the single production process line where liquid crystal is selectively dispensed Intrinsic Support 3:25-42; 5:11-30; 5:55-66; 6:35-46; 6:62-67; 7:9-13; 7:35-41; Figs. 2, 3, and 4; App 10/124,452, 6/17/04 Notice of Allowability, pages 2-3.	passing the first and second substrates, one after the other, along a portion of the single production process line where liquid crystal is selectively dispensed Intrinsic Support 3:25-42; 5:11-30, 55-66 6:35-46; 6:62-67; 7:9-13; 7:35-41; Figs. 2, 3, and 4; App 10/124,452, 6/17/04 Notice of Allowability, pages 2-3.
	CMO Construction
-	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
in serial order in a same cleaning	Ţ	one after the other in the		
unit		same cleaning equipment		-
		Intrinsic Support		
	·	3:25-42; 3:36-43; 5:26-30;		
		5:11-30, 55-66 6:35-46;		
		6:62-67; 7:9-13; 7:35-41;		
		Figs. 2, 3, and 4.		
				-

E-2

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Disputed Constructions

					a first substrate				a liquid crystal display device C	Claim Terms Des.
										s. LGD Construction
										CMO Construction
1:38-39; 1:59-61; 7:25-33; Claim 5 and 9	E.g.,	Intrinsic Support	one of the two opposing substrates of the liquid crystal cell	OR	Plain meaning;	1:21-27; 1:31-37	E.g.,	Intrinsic Support	Plain meaning	AUO Construction

				······································						T STORAGE
				on a single production process line					a second substrate	Claim Terms
				T					С	Des.
										LGD Construction
										CMO Construction
App 10/128452, 1/8/04 Amendment	Figs. 2-4; 5:23-27; 7:35-43; Claim 1	E.g.	Intrinsic Support	On a production line for processing liquid crystal displays in a single, linear arrangement	See above	Intrinsic Support	the other of the two opposing substrates of the liquid crystal cell	OR	Plain meaning	AUO Construction

					single production process line in serial order	substrates through a sealing	passing the first and second	Claim Terms
						· · · · · · · · · · · · · · · · · · ·	С	Des.
								LGD Construction CMO Construction
App 10/128452, 1/8/04 Amendment, pages 1-6; App 10/128452, 6/23/04	5:23-30; 6:19-53; 6:54 - 7:20;	Figs. 2-4; 4:20-25	E G	Intrinsic Support	in between; in at one end, and out at the other end in the same order of a machine for coating sealing material on a substrate	second substrate one after	providing the first and	AUO Construction

		in serial order	production process line	Claim Terms a sealing material coating portion of the single
		A	V	Des.
		-		LGD Construction
·				CMO Construction
Figs. 2-4; 5:23-27; 7:25-33; 6:19-53 & Fig. 3; 6:54-7:20 & Fig. 4	anything in between Intrinsic Support E.g.,	See above One after the other without	production process line. Intrinsic Support	AUO Construction A machine for coating sealing material in the single

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
passing the first and second	С		providing the first and
substrates through a liquid crystal			second substrate one after
dispensing portion of the single			the other, without anything
production process line in serial			in between; in at one end,
order			and out at the other end in
			the same order of the liquid
			crystal dispensing machine
			•
			Intrinsic Support
			T.J.
			,
			Figs. 2-4; 4:26-30
			6:19-53:
			6:54 – 7:20;
			App 10/128452, 1/8/04
			Amendment, pages 1-6
			App 10/128452, 6/23/04
			pages 1-4

<u>a</u>				ا دع		•				
assembling				a pixel region			production process line	portion of the single	a liquid crystal dispensing	Claim Terms
С		× 18 30 30 30 30 30 30 30 30 30 30 30 30 30		C			318 (21 WALL)		Α	Des.
										LGD Construction
										CMO Construction
Indefinite	2:48-40; 5:16-18; Claim 7	E ig.	Intrinsic Support	Area with pixel	See above	Intrinsic Support	in the single production process line	liquid crystal on a substrate	a machine for dispensing	AUO Construction

			ŧ
	in serial order in a same cleaning unit		Claim Terms the liquid crystal is dispensed onto the first substrate at the same time that the second substrate is disposed in the sealing material coating portion
	L		Des. A
			LGD Construction
			CMO Construction
E.g. Figs. 2-4; 5:23-36; 6:19-21; 6:54-56	cleaning the first substrate and the second substrate one after the other without anything in between in the same cleaning machine	Intrinsic Support E.g. 7:22-33	when the liquid crystal is dispensed onto the first substrate in the liquid crystal dispensing machine, the second substrate is located in the sealant coating machine

E-3

Disputed Constructions

	I () (cases, see ex.	(HIN) (CALCAN MORACES	THE COMPANY STATES
a liquid crystal display device C		a liquid crystal device operable as a display, such	
		as a PC monitor or a TV monitor	
	-	Intrinsic Support 1:31-37	-
a first substrate C		plain meaning	· · · · · · · · · · · · · · · · · · ·
		Intrinsic Support	
		Abstract, 3:61-66, 5:11-25, 7:17-34, Figs. 2-4	
a second substrate C		the substrate immediately following the first substrate	
		Intrinsic Support	
		Abstract, 3:61-66, 5:11-25, 7:17-34, Figs. 2-4	

	•		
		line	Claim Terms on a single production process
			Des.
			LGD Construction
Abstract, 3,22-53, 3:61-4:13, 5:23-30, 7:17-43, Figs. 1-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5	Intrinsic Support	processing the substrates in only one direction without branching	CMO Construction on a line structure for
-			AUO Construction

		passing the first and second substrates through a sealing material coating portion of the single production process line in serial order	
		Jes. ad C ng f the line in	
		LGD Construction	
Abstract, 2:28-38, 2:54-59, 3:61-4:13, 5:11-30, 5:39-50, 6:27-34, 7:1-8, 7:17-44, Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5	Intrinsic Support	providing the first and second substrates, one after the other without anything in between, in at one end, and out at the other end, of a machine for coating sealing material in the single production process line in which the same order of the first and second substrates is maintained throughout the seal dispensing process	
		AUO Construction	

portion of the single production process line Intrinsic Support	Claim Terms a sealing material coating	Des.	LGD Construction	CMO Construction a machine for coating	AUO Construction
in serial order A	portion of the single production process line			sealing material in the single production process line	
in serial order A				Intrinsic Support	
A				Abstract, 2:28-38, 2:54-59, 3:61-4:13, 5:11-30, 5:39-50.	
				6:27-34, 7:1-8, 7:17-44,	-
				Figs. 2-4, App. No.	=
A				10/128,452, January 6, 2004 Amendment at 4-5	
A one after the othe without anything without anything Intrinsic Support Abstract, 3:61-4: 25, 5:41-49, 5:56 41, 6:62-67, 7:1-8 Figs. 2-4, App. N 10/128,452, Janua Amendment at 4-	•	•	TOTAL STREET,		
Intrinsic Support Abstract, 3:61-4:13, 5:11- 25, 5:41-49, 5:56-61, 6:27- 41, 6:62-67, 7:1-8, 7:17-34, Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5	in serial order	Α			
Abstract, 3:61-4:13, 5:11-25, 5:41-49, 5:56-61, 6:27-41, 6:62-67, 7:1-8, 7:17-34, Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5				Intrinsic Support	
25, 5:41-49, 5:50-01, 0:27- 41, 6:62-67, 7:1-8, 7:17-34, Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5				Abstract, 3:61-4:13, 5:11-	
Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5				41, 6:62-67, 7:1-8, 7:17-34,	
10/128,452, January 6, 2004 Amendment at 4-5				Figs. 2-4, App. No.	
				10/128,452, January 6, 2004	

		passing the first and second C substrates through a liquid crystal dispensing portion of the single production process line in serial order
7 7 7	Ш	LGD Construction P tl a ii s s s s s s s d d
Abstract, 2:28-38, 2:63-3:12, 3:61-4:13, 5:11-30, 5:56-61, 6:36-41, 6:62-67, 7:17-34, Figs. 2-4, App. No. 10/128,452, January 6, 2004 Amendment at 4-5	Intrinsic Support	providing the first and second substrates, one after the other without anything in between, in at one end, and out at the other end, of a machine for dispensing liquid crystal material in the single production process line in which the same order of the first and second substrates is maintained throughout the liquid crystal dispensing process
		AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
a liquid crystal dispensing portion of the single	A		a machine for dispensing liquid crystal in the single	
production process line			production process line	
			Intrinsic Support	
			Abstract, 2:28-38, 2:63-3:12, 3:61-4:13, 5:11-30,	
			5:56-61, 6:36-41, 6:62-67,	-
			7:17-34, Figs. 2-4, App. No.	
			Amendment at 4-5	
a pixel region	С		an area with pixels	
			Intrinsic Support	
			2:45-53, 3:6-12, 4:7-11, 5:39-47, 6:27-33, 7:1-5	
assembling	О		indefinite	

in serial order in a same cleaning L one after the other without anything in between, in a same cleaning machine Intrinsic Support 3:22-42, 5:26-30, 5:33-38,

F-1

Disputed Constructions

transistor	C	
		introduced by a voltage applied at the third terminal, the gate, which is separated from the semiconductor by an insulating layer, and the
		thin film transistor is formed using thin-film techniques on a substrate Intrinsic Support
		1:5-20; 1:44-46; 2:49-51; 3:21-63; 5:38-41; Figs 1-4; Abstract.

			gate				substrate	Claim Terms
			П			, www.		Des.
1:5-39; 3:21-29; 3:41-64; 4:26-34; 4:40-5:7; 5:21-37; 5:63-6:7; 6:15-48; 7:7-52; Figs 1-4; Abstract.	Intrinsic Support	includes a portion that controls current flow through the channel between the source electrode and drain electrode	patterned electrically conductive material that	2:49-54; 3:40-59; 5:40-54; Figs 1-4; Abstract.	Intrinsic Support:	fabricated to provide mechanical support	the material (such as glass) upon which a transistor or	LGD Construction
								CMO Construction
								AUO Construction

	a second metal layer disposed on the first metal layer			a double lavered structure
	C T		\triangleright	Des.
Intrinsic Support 1:20-27; 2:49-3:20; 3:27-40; 3:45-58; 4:26-39; 4:53-59; 5:21-38; 5:42-54; 7:32-59; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment.	sequentially depositing the second metal layer above and in contact with the first metal layer	1:5-10; 1:20-43; 2:55-3:19; 3:27-64; 4:24-34; 4:40-62; 5:22-38; 5:42-62; 6:27-49; 7:32-52; Figs. 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment.	conductive material that includes two sequentially deposited metal layers Intrinsic Support	a structure of an electrically CMO Cons
				struction
-				AUO Construction

	•
the second metal layer being arranged on the first metal layer to prevent hillock at the sides of the aluminum first metal layer	the first metal layer including aluminum
C	C
the second metal layer is patterned to prevent hillock on the side surfaces of the first metal layer that are exposed to a subsequently deposited gate insulating layer Intrinsic Support 1:17-43; 2:49-65; 3:21-29; 3:34-40; 5:21-38; 6:37-48; 7:47-52; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment.	the first metal layer containing aluminum and possibly other materials Intrinsic Support 1:6-10; 1:17-26; 1:40-43; 1:51-55; 3:22-26; 4:32-38; 5:42-54; 7:47-52, App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment.
·	AUO Construction

							first metal layer	at the sides of the aluminum	Claim Terms
						Α	C	L	Des.
Office Action; App 08/918,119, 11/25/1998, Amendment.	7:47-52; Figs 1-4; Abstract; App 08/918,119, 8/20/1998,	3:34-40; 5:21-38; 6:37-48;	1:17-43; 2:49-65; 3:21-29;	Intrinsic Support	gate insulating layer	to a subsequently deposited	metal layer that are exposed	the side surfaces of the first	LGD Construction CMO Construction AUO Construction

1:51-2:21; 3:41-64; 4:32-52; 5:21-38; 5:55-62; 5:67-6:48; 7:47-52; Abstract; Figs. 1-4; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment.	Intrinsic Support	g wider L the width of the first metal yer by C layer, determined by the portion of the first metal layer in contact with the second metal layer together with the portions exposed to the subsequently deposited gate insulating layer, is more than 1 µm and less than 4µm greater than the width of the second metal layer	I CD Construction CMO Const
-		ACCONSTRUCTION	

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
two side portions of the first metal	С	the side surfaces of the first		
layer having no second layer		metal layer that are exposed		-
thereon		to the subsequently		
		layer		· -
		Intrinsic Support		
		2:5-26; 2:49-60; 3:21-29;		-
		4:40-63; 5:21-38; 6:7-15;		
		6:27-49; 7:24-28; 7:47-52;		
		Figs. 1-4; Abstract; App 08/918.119, 8/20/1998.		
		Office Action; App		
		08/918,119, 11/25/1998,		
		Amenament.		

					disposed thereon	layer having no second layer A	two side portions of the first metal C	Claim Terms Des.
Office Action; App 08/918,119, 11/25/1998, Amendment.	6:27-49; 7:24-28; 7:47-52; Figs. 1-4; Abstract; App 08/918,119, 8/20/1998,	2:5-26; 2:49-60; 3:21-29; 4:40-63; 5:21-38; 6:7-15;	Intrinsic Support	layer	to the subsequently	metal layer that are exposed	the side surfaces of the first	LGD Construction CMO Construction AUO Construction

F-2

Disputed Constructions

																										transistor	· Cimilia I vi ilia
																								. 15		C	1 63.
																					-						EGE Comon action
																											Ciri Compan nemon
Claim 4	6:55-61;	4:39-44;	4:23-31;	Intrinsic Support	on an insulating substrate	using thin-film techniques	film transistor is formed	insulating layer. The thin-	semiconductor by an	which is separated from the	electrode, the gate electrode,	applied at the third	introduced by a voltage	semiconductor; this field is	field that penetrates the	modulated by an electric	electrode, is controlled or	electrode and drain	electrodes, the source	through one pair of	which the current flow	semiconductor device in	A three-terminal		Or -	Plain meaning	TAO O COMPENSATION

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
substrate	С			the material (such as glass) upon which a transistor or integrated circuit is
				fabricated to provide mechanical support.
gate	T			same as gate electrode; a patterned, electrically conductive material formed
				in the gate region. Current flows through the channel between the source electrode
				and drain electrode under control of the gate electrode
				Intrinsic Support
				E.g.,
				4:26-5:3
a double layered structure	> O			a two-layered step structure
	>			Intrinsic Support
				E.g.,
	,			Figs. 3-4;
				3:27-58;
				4:23-59; 5:21-38;

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction 6:27-48
a second metal layer disposed on the first metal layer	CL			a second metal layer precipitated above, supported by and in contact with the first metal layer
				Intrinsic Support
				E,g.,
				5:41-54
the first metal layer including	С			Plain meaning
				Intrinsic Support
				E.G.,
				4:34-36; 5:42-43;
the second metal layer being	C			the second metal layer being
arranged on the first metal layer to				arranged on the first metal
prevent hillock at the sides of the				layer to prevent hillocks
aluminum first metal layer				from forming on the side portions of the aluminum
				first metal layer
				Intrinsic Support
				E.g.,

							Claim Terms Des. LGD Construction CM
Office Action, pages 5-6; App 09/983629, 1/14/03	App 09/983629, 8/14/02 Office Action, pages 4-11; App 09/983629, 11/13/02	App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7;	App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;	App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06	Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages	3:21-25; 4:46-55; 5:21-38; 6:27-48; App 08/918119, 11/17/98	CMO Construction AUO Construction Figs. 3-4; 1:20-2:65;

																												Science of
	at the sides of the aluminum first metal layer																											Claim Terms
Α	CL									**																		Des.
																												LGD Construction CMO Construction
layer not covered by the second metal layer	at the portions on the top surface of the first metal	Notice of Allowance, page 2	App 09/983629, 8/8/01	10;	Response, pages 4-7 and 9-	App 08/918462, 4/4/01	Office Action, pages 2-4;	App 08/918462, 1/23/01	Interview Summary;	App 08/918462, 12/5/00	Response, pages 4-10;	App 08/918462, 11/7/00	Office Action, pages 2-5;	App 08/918462, 07/7/00	Response, pages 4-8;	App 08/918462, 4/13/00	Office Action, pages 3-6;	App 08/918462, 12/14/99	Response, Remark Section;	App 08/918462, 9/27/99	1-2;	Interview Summary, pages	App 08/918462, 9/10/99	Office Action, pages, 1-2;	App 08/918462, 4/26/99	2;	Notice of Allowance, page	AUO Construction

	· · · · · · · · · · · · · · · · · · ·	
		Claim Terms
		Des.
		LGD Construction
		CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 8/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7; App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7; App 09/243556, 8/3/01 Office Action, pages 4-1; App 09/983629, 8/14/02 Office Action, pages 4-11;	Intrinsic Support E.g., Figs. 3-4; 4:23-59; 5:21-38; 6:45-47	AUO Construction

	,	
the first metal layer being wider than the second metal layer by about 1 to 4 μm		Claim Terms
A C L		Des.
		LGD Construction CMO
		CMO Construction
Indefinite; or	App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages 1-2; App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01 Response, pages 4-7 and 9-10; App 09/983629, 8/8/01 Notice of Allowance, page 2	AUO Construction Office Action, pages 5-6; App 09/983629, 1/14/03 Notice of Allowance, page

		*		
				Claim Terms
				Des.
				LGD
				Cons
				LGD Construction
				on
				CMO Consti
				Const
				ruction
				n
App App Offic App 1-2; App Offic App Offic App App Offic App App Resp	Figs. 3-4; 1:20-2:65 4:23-59; 5:21-38; 5:57-6:7; 6:27-48;	Intrir	1 to 4 width layer defin first 1	the fi
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;	Figs. 3-4; 1:20-2:65; 4:23-59; 5:21-38; 5:57-6:7; 6:27-48;	Intrinsic Support	I to 4 um greater than the width of the second metal layer measured from a level defined by the top of the first metal layer	AUO Construction the first metal layer is about
3119, 1 pages (27,732, 77,732, 77,732, 77,732, 77,732, 77,132,		pport	reater secon reader in the top ayer	onstr fal lav
11/17/5 3-4; 3-4; 5/27/0 5/27/0 ner, pa 9/30/0 ges 2-: ges 2-: ge 2; ge 2; ge 2; 8/29/0		-	than the defined met om a less of the	uction er is al
6 6 6 6 6 6 6 6 6 6 6 6 6 6 6 6 6 6 6		CANADA V	al evel) III

	Claim Terms
	S. Des.
	LGD Const
	Construction
	CMO Construction
App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01	AUO Construction App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7; App 09/983629, 8/14/02 Office Action, pages 4-11; App 09/983629, 11/13/02 Office Action, pages 5-6; App 09/983629, 1/14/03 Notice of Allowance, page 2; App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages

		two side portions of the first metal layer having no second layer thereon	Claim Terms
		C	Des.
			LGD Construction
			CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01	Intrinsic Support Figs. 3-4; 1:20-2:65; 4:23-59; 5:21-38; 5:57-6:7; 6:27-48	the two side portions on the top surface of the first metal layer not covered by the second layer	AUO Construction 10; App 09/983629, 8/8/01 Notice of Allowance, page 2

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																													Claim Terms
																													Des.
																													LGD Construction
																													CMO Construction
Office Action, pages 2-4; App 08/918462, 4/4/01	App 08/918462, 1/23/01	App 08/918462, 12/5/00	Response, pages 4-10;	Office Action, pages 2-5; App 08/918462, 11/7/00	App 08/918462, 07/7/00	Response, pages 4-8;	App 08/918462, 4/13/00	Office Action, pages 3-6;	App 08/918462, 12/14/99	Response, Remark Section;	App 08/918462, 9/27/99	1-2;	Interview Summary, pages	App 08/918462, 9/10/99	Office Action, pages 1-2;	App 08/918462, 4/26/99	2;	Notice of Allowance, page	App 09/983629, 1/14/03	Office Action, pages 5-6;	App 09/983629, 11/13/02	Office Action, pages 4-11;	App 09/983629, 8/14/02	Response, pages 4-7;	App 09/243556, 8/3/01	Office Action, pages 2-5;	App 09/243556, 3/29/01	Resnonse nage 7:	AUO Construction

*	
two side portions of the first metal layer having no second layer disposed thereon	Claim Terms
A C	Des.
	LGD Construction
	CMO Construction
The two side portions on the top surface of the first metal layer not covered by the second layer Intrinsic Support See above	AUO Construction Response, pages 4-7 and 9- 10; App 09/983629, 8/8/01 Notice of Allowance, page 2

F-3

Disputed Constructions

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
transistor	С		a device that includes a semiconductor material and three electrodes	
			Intrinsic Support	
		·	1:15-16; 4:26-31; Fig. 2; Fig. 3	
substrate	С		plain meaning	
gate	T		a region of a transistor	
			Intrinsic Support	
			4:26-31; Fig. 2; Fig. 3	-
a double layered structure	A C		a structure having only two metal layers.	
			Intrinsic Support	
		-	1:17-23; 3:27-29; 4:32-34; 5:21-25; 6:27-29; Fig. 2; Fig. 3; Figs. 4A-F; Application, 08/918.119.	
			Kesponse, November 17, 1998	

	indefinite		ACL	at the sides of the aluminum first metal layer
	1:20-38; 3:20-26; 6:40-47			
	Intrinsic Support			
	the second metal layer prevents roughness on the sides of the aluminum first metal layer		С	the second metal layer being arranged on the first metal layer to prevent hillock at the sides of the aluminum first metal layer
	4:34-36; 5:41-42			
	Intrinsic Support			
	a first metal layer that includes pure aluminum		С	the first metal layer including aluminum
-	3:49-51; Abstract; Fig. 3; Figs. 4A-F	·	WAS BUILD ON THE STATE OF THE S	
	Intrinsic Support			
	layer			
	the second metal layer is in contact with the first metal		CL	a second metal layer disposed on the first metal layer
AUO Construction	CMO Construction	LGD Construction	Des.	Claim Terms

two side portions of the first metal C layer having no second layer thereon																			than the second metal layer by C	
plain meaning	Application, 9804417.5, Response, March 4, 1999	Office Action, May 21, 1998; United Kingdom	Application, 9804417.5,	Request for Patent Drawing Revision, December 16,	Application, 918,119,	August 27, 1997;	Figs 4A-F; Application,	6:15-26; 6:40-47; Fig. 3;	1:23-2:65; 4:39-51; 5:25-37;	Intrinsic Support	second metal layer.	layer is covered by the	surface of the first metal	where not all of the top	layer to form a double step.	surface of the second metal	than a width of the top	is about 1 to 4 µm wider	metal layer has a width that	The ten confidence of the first
						-							-				-			

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
two side portions of the first metal	С	plain meaning	
layer having no second layer	A		
disposed thereon			

Case 1:06-cv-00726-JJF Document 363-4 Filed 07/29/2008 Page 28 of 114

G-1

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Disputed Constructions

																			transistor	Claim Terms
	•		-											,				•	C	Des.
1:20-40; 1:61-64; 2:64-68; 3:39-4:14; 5:56-58; Abstract.	Intrinsic Support	rather than a single crystal silicon wafer.	on an insulating substrate	using thin-film techniques	thin-film transistor is formed	an insulating layer. The	from the semiconductor by	the gate, which is separated	applied at the third terminal,	introduced by a voltage	semiconductor; this field is	field that penetrates the	modulated by an electric	drain, is controlled or	terminals, the source and	through one pair of	which the current flow	semiconductor device in	A three-terminal	LGD Construction
																				CMO Construction
			-															-		AUO Construction

1:37-44; 2:65-3:37; 3:44- 4:15; 4:44-56; 5:3-9; 5:39- 55; 5:59-6:5; 7:47-67; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 4; App 09/243,556, 8/3/2001, Amendment; USP 6,340,610, Claims 1, 4.	Intrinsic Support	forming a second metal layer on the first metal layer C second metal layer above and in contact with the first metal layer	2:65-3:5; 3:59-4:10; 5:59-64; Figs 1-4; Abstract.	Intrinsic Support	integrated circuit is fabricated to provide mechanical support	substrate C the material (such as glass) upon which a transistor or	Claim Terms Des. LGD Construction
							CMO Construction AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction
depositing a second metal layer on the first metal layer	C	sequentially depositing the second metal layer above and in contact with the first	
		metal layer Intrinsic Support	
		1:37-44; 2:65-3:37; 3:44-	
		55; 5:59-6:5; 7:47-67; Figs	
		1-4; Abstract; App 08/918,119, 8/20/1998,	
		Office Action; App	
		Amendment; USP	
	-	5,905,274, Claims 1, 4; App	
		09/243,556, 8/3/2001,	
		Amendment; USP	
		6,340,610, Claims 1, 4.	

			A	[a] double layered metal gate C
Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance; USP 6,548,829, Claim 1.	Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 4; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001,	Intrinsic Support 1:20-56; 1:37-60; 3:4-36; 3:39-4:14; 4:40-52; 4:57-5:24; 5:39-55; 5:59- 6:25;6:33-65; 7:23-67; Figs 1-4; Abstract; App 08/018 110 8/20/1008	material that includes two sequentially deposited metal layers and includes a portion that controls current flow through the channel between the source electrode and drain electrode	[a] patterned structure of an
				CMO Construction
			·	AUO Construction

																	gate	Claim Lerms
																	L	Des.
09/243,556, 9/10/2001, Notice of Allowance; USP 6,548,829, Claim 1.	Office Action; App 09/243,556, 8/3/2001, Amendment; App	Amendment; App 09/243,556, 3/29/2001,	5,905,274, Claims 1, 4; App 09/243,556, 1/8/2001,	08/918,119, 11/25/1998,	Office Action; App	1-4; Abstract; App 08/918,119, 8/20/1998,	6:25;6:33-65; 7:23-67; Figs	4:57-5:24; 5:39-55; 5:59-	3:39-4:14: 4:40-52:	1.20_56: 1.37_60: 3.4_36:	Intrinsic Support	drain electrode	the source electrode and	controls current flow	includes a portion that	conductive material that	patterned electrically	LGD Construction
																		CMO Construction
											-			· -				AUU Construction

		•
		Claim Terms a total width of the first metal layer is greater than a total width of the second metal layer by about 1 to 4 μm
		Des. C A
09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance; USP 6,340,610, Claim 1; USP 6,548,829, Claims 1 and 6.	Intrinsic Support 2:1-39; 3:59-4:15; 4:50-5:2; 5:38-55; 6:5-13; 6:18-65; 7:40-43; 7:62-67; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 9/6/2000, Office Action; App 09/243,556, 1/8/2001, Amendment; App	the width of the first metal layer, determined by the portion of the first metal layer in contact with the second metal layer together with the portions exposed to the subsequently deposited gate insulating layer, is more than 1µm and less than 4µm greater than the width of the second metal layer
		CMO Construction
		AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
first etching layer	T	the first metal layer		
		Intrinsic Support		
		Claims 1-22; See Specification Generally.		. <u>-</u>
waking	Ţ	making		1
		Intrinsic Support		
		Claims 1-22; See Specification Generally; App 10/377,732, 3/4/2003, Application as filed; App 10/377,732, 5/27/2004, Terminal Disclaimer Transmittal.		

	photoresist C	Claim Terms forming a single photoresist having a predetermined width on the second metal layer Des. C having a single photoresist C having a predetermined width on the second metal layer
Intrinsic Support 1:40-60; 2:1-29; 2:65-36; 3:44-51; 3:66-4:9; 4:50-56; 5:58-6:44; 7:23-67; Figs. 1- 4; Abstract.	pattern of a photosensitive material	forming a pattern of single photosensitive material that has a specified width on the second metal layer Intrinsic Support 1:40-60; 2:1-29; 2:65-36; 3:44-51; 3:66-4:9; 4:50-56; 5:58-6:44; 7:23-67; Figs. 1-4; Abstract; App 09/243,556, 9/6/2000, Office Action; App 09/243,556, 3/29/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; USP 6,340,610 Claims 1, 2.
		CMO Construction
		AUO Construction

	Claim Terms Dess. simultaneously in a single etching L step using the single photoresist as a mask
1:40-60; 2:1-29; 2:65-36; 3:44-51; 3:66-4:9; 4:50-56; 5:58-6:44; 7:23-67; Abstract; App 09/243,556, 9/6/2000, Office Action; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; USP 6,340,610, Claims 1, 2.	LGD Construction CMO Construction during a single etching process with a common mask Intrinsic Support
	AUO Construction

Claim Terms	Des.	I.G.D. Construction	CMO Construction	AIIO Construction
simultaneously	Α	removing part of the first		
patterning/patterning		and second metal layers		
SITIULIMITATIVO		process		
		Intrinsic Support:		
		Abstract; 1:40-60; 2:1-29;		
		2:65-36; 3:44-51; 3:66-4:9;		-
		4:50-56; 5:58-6:44; /:23-6/; Figs. 1. 4: USP 6.340.610.		
		Claims 1, 2; App		
		09/243,556, 9/6/2000 Office Action: App 09/243,556,		
		1/8/2001, Amendment; App		
		Office Action; App		
		09/243,556, 8/3/2001		
		Amendment.		
the first metal layer being etched	L	the first and second metal		
to have a width greater than a	C	layers are etched such that		
width of the second metal layer	Α	the width of the first metal		
oy acour I to T him		portion of the first metal		
		layer in contact with the		
		second metal layer together		
CALCINO TO SERVICE OF THE SERVICE OF		the subsequently deposited		
		gate insulating layer, is more		
		than 1 µm and less than 4 µm		
		greater than the width of the		

								*						Claim Terms Des.
09/243,556, 9/10/2001, Notice of Allowance; USP 6,340,610, Claim 1; USP 6,548,829, Claims 1 and 6.	Office Action; App 09/243,556, 8/3/2001,	Amendment; App 09/243,556, 3/29/2001,	9/6/2000, Office Action; App 09/243,556, 1/8/2001,	4, 5; App 09/243,556,	USP 5,905,274 Claims 1, 2,	App 08/918,119, 11/25/1998, Amendment;	8/20/1998, Office Action;	Abstract; App 08/918,119,	7:40-43; 7:62-67; Figs. 1-4;	5:38-55; 6:5-13; 6:18-65;	2:1-39; 3:59-4:15; 4:50-5:2;	Intrinsic Support	second metal layer	
											-			AUO Construction

	a first and a second side portion being exposed from the second metal layer
	C
1:34-60; 2:65-3:14; 3:39-47; 3:52-57; 5:38-55; 6:55-65; 7:62-67; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance.	first and second side surfaces of the first metal layer that are exposed to the subsequently deposited gate insulating layer Intrinsic Support
	AUU Construction

	two side portions of the first metal Clayer having no second metal A layer deposited thereon
1:34-60; 2:65-3:14; 3:39-47; 3:52-57; 5:38-55; 6:55-65; 7:62-67; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance	the side surfaces of the first metal layer that are exposed to the subsequently deposited gate insulating layer Intrinsic Support
-	AUO Construction

		the first metal layer including aluminum	Claim Terms
		C	Des.
1:20-28; 1:34-44; 1:56-60; 2:1-5; 3:39-44; 4:50-56; 5:59-6:5; 7:62-67; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 4; App 09/243,556, 3/11/1999, Preliminary Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment.	Intrinsic Support	the first metal layer containing aluminum and possibly other materials	LGD Construction
			CMO Construction
			AUO Construction

G-2

Disputed Constructions

		transistor
		C
		LGD Construction CMO Co
Intrinsic Support 4:40-49; 4:57-62; 7:5-11	A three-terminal semiconductor device in which the current flow through one pair of electrodes, the source electrode and drain electrode, is controlled or modulated by an electric field that penetrates the semiconductor; this field is introduced by a voltage applied at the third electrode, the gate electrode, which is separated from the semiconductor by an insulating layer. The thinfilm transistor is formed using thin-film techniques on an insulating substrate	Plain meaning Or

Claim Terms Des.	substrate C	forming a second metal layer on L	the first metal layer C				depositing a second metal layer C on the first metal layer					[a] double layered metal gate C	
LGD Construction (
CMO Construction AUO Construction	Plain meaning	forming a second metal	layer above, supported by, and in contact with the first	metal layer	Intrinsic Support	Fig. 4; 5:59-6:5	Precipitating a second metal layer above, supported by, and in contact with the first	metal layer	Intrinsic Support	E.g.,	Fig. 4; 5:59-6:5	a gate electrode having a two-layered step structure	Intrinsic Support

Claim Terms Des. LGD Construction E.g Figs. 3-4; 1:29-3:14; 3:44-15.9; 4:41-5.9; 4:41-5.9; 5:38-55; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-47; 6:44-17; 6:44-					
L L L I width of the first metal ris greater than a total width C e second metal layer by about A 4 µm L		Des.	LGD Construction	CMO Construction	AUO Construction
L L L I width of the first metal r is greater than a total width C e second metal layer by about A μm					E.g.,
L L L L I system than a total width C c e second metal layer by about A 4 µm L L A					Figs. 3-4;
L L I width of the first metal L is greater than a total width C e second metal layer by about A 4 µm					1:29-3:14;
L L I descend metal layer by about A L C C C C C C C C C C C C					3:44-4:9;
L L I L I A I A A L C c e second metal layer by about A μm					4:41-5:9;
L L I L I A I A I A I A I A I A					5:38-55;
L L I I I I I I I I I			-		6:44-47;
L L al width of the first metal r is greater than a total width c e second metal layer by about 4 μm L			-		6:58-62
L I width of the first metal I is greater than a total width C e second metal layer by about A 4 μm	1			Control of the Contro	
bout A		t			notterned electrically
dth C hbout A					conductive material formed
bout A					in the gate region. Current
dth C bout A					flows through the channel
dth C hout A					electrode and drain
dth C hbout A					electrode under control of
dth C bout A					the gate electrode.
th C hout A					Intrinsic Support
dth C hbout A					E.io;
dth C lbout A					l
dth C bout A					4:41-5:20
A	a total width of the first metal	L			Indefinite;
	ayer is greater than a total width of the second metal layer by about	A C			or
the width of the first metal layer is about 1 to 4 um	l to 4 μm				
					the width of the first metal layer is about 1 to 4 um

			Cath	Claim
			Š	Claim Terms
			2003	Des
				I.GD Construction
			,	structio
				n
				2
			COL	OCons
				CMO Construction
O	6,5,4,2,5,H E	<u></u>		
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, page 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2;	E.g., Indefinite: Figs. 3-4; 2:29-3:14; 4:40-5:9; 5:38-55; 6:14-25; 6:45-54	Intrinsic Support	greater than the width of second metal layer when measured from a level defined by the top of the first metal layer	ОПО
[8119, 1], pages 3, pages 3, pages 3, pages 3, pages 3, 77,732, 2, tion, pag 77,527, 9, tion, pag 72,527, 3, tion, pages 72,527, 3, tion, pages 72,527, 3		upport	an the we etal layer from a ly the top	ATO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2;		-	greater than the width of the second metal layer when measured from a level defined by the top of the first metal layer	ction
vs.			<u>ō</u>	

	Claim Terms
	Des. LGD Construction
	CMO Construction
Response, page 7; App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7; App 09/983629, 8/14/02 Office Action, pages 5-6; App 09/983629, 11/13/02 Office Action, pages 5-6; App 09/983629, 11/13/02 Office Action, pages 1-2; App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages 1-2; App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 17/7/00 Response, pages 4-8; App 08/918462, 17/7/00 Office Action, pages 2-5; App 08/918462, 17/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4;	AUO Construction Ann 09/243556 1/8/01

													, ,				
							as a mask	simultaneously in a single etching	photoresist	the second metal layer	forming a single photoresist	waking	first etching layer				Claim Terms
								L	С		C	T	T				Des.
																	LGD Construction CMO Construction
Fig. 4;	F.g.,	Intrinsic Support	Forming the patterned first and second metal layers in one chemical etching step using one photoresist mask	as	etching step using the single photoresist as a mask"	second metal layers simultaneously in a single	"patterning the first and	construe term:	Plain meaning		Plain meaning	Non-sensical; Indefinite	Indefinite	App 09/983629, 8/8/01 Notice of Allowance, page 2	10;	Response, pages 4-7 and 9-	AUO Construction Ann 08/918462 4/4/01

A Form and the scher cher cher fig. 5.39 E.g., Fig. 5.39 App App Offin App Offin App Offin App Offin App Resg App Offin App Offin App Resg App Offin App Resg App Offin App Resg App Offin App Offin App Offin App Resg App Resg App App App App App App App App App Offin App Resg App App App App App App App App App Ap	Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
ming A					5:39-43; 6:6-12
E.g., Fig. 4; 5:39-43; 6:6-12; App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 2/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 3/29/06 Office Action, page 2; App 09/243556, 1/8/01 Response, page 2; App 09/243556, 1/8/01	simultaneously patterning/patterning simultaneously	A			Forming the patterned first and second metal layers at the same time in one chemical etching step
E.g., Fig. 4; 5:39-43; 6:6-12; App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;					Intrinsic Support
Fig. 4; 5:39-43; 6:6-12; App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/24356, 1/8/01 Response, page 7;					E.g.,
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;					Fig. 4; 5:39-43; 6:6-12;
Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;					App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377.732, 5/27/04
App 10/8/2,327, 7/30/03 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;					Terminal Disclaimer, pages 1-2;
Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7;					App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872 527 3/29/06
App 10/6/2,327, 6/29/00 Response, page 2; App 09/243556, 1/8/01 Response, page 7;	r				Office Action, page 2;
Response, page 7;					Response, page 2;
\mathreal \tau \tau \tau \tau \tau \tau \tau \tau					Response, page 7;

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																															Claim Terms Des.
																															LGD Construction
																															CMO Construction
10;	Response pages 4-7 and 9-	Ann 08/918462 4/4/01	App 08/918462, 1/23/01	Interview Summary;	App 08/918462, 12/5/00	Response, pages 4-10;	App 08/918462, 11/7/00	Office Action, pages 2-5;	App 08/918462, 07/7/00	Response, pages 4-8;	App 08/918462, 4/13/00	Office Action, pages 3-6;	App 08/918462, 12/14/99	Response, Remark Section;	App 08/918462, 9/27/99	1-2;	Interview Summary, pages	App 08/918462, 9/10/99	Office Action, pages 1-2;	App 08/918462, 4/26/99	2;	Notice of Allowance, page	App 09/983629, 1/14/03	Office Action, pages 5-6;	App 09/983629, 11/13/02	Office Action, pages 4-11;	App 09/983629, 8/14/02	Response, pages 4-7;	App 09/243556, 8/3/01	Office Action, pages 2-5;	AUO Construction

Claim Lerms	Des.	LGD Construction	CIVIO Construction	App 00/083630 8/8/01
				App 09/983629, 8/8/01 Notice of Allowance, page 2
the first metal layer being etched to have a width greater than a	CL			indefinite;
width of the second metal layer by about 1 to 4 um	> C			or
of account to 1 parts				the first metal layers being etched so that the width of
		-		the first metal layer is about
				1 to 4 um greater than the width of the second metal
				layer when measured from a level defined by the top of
				the first metal layer
,				Intrinsic Support
				E.g.,
				Indefinite:
				Figs. 3-4; 2:29-3:14;
				4:40-5:9;
				5:38-55;
				6:45-54
				App 08/918119, 11/17/98
				Response, pages 3-4;

,	
	Claim Terms
	Des.
	. LGD Construction
	CMO
	CMO Const
	truction
	Ĕ
Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, page 2; App 10/872,527, 8/29/06 Office Action, page 2; App 09/243556, 1/8/01 Response, page 7; App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7; App 09/983629, 8/14/02 Office Action, pages 4-11; App 09/983629, 11/13/02 Office Action, pages 5-6; App 09/983629, 11/13/02 Office Action, pages 5-6; App 09/983629, 1/14/03 Notice of Allowance, page 2; App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages 1-2; App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99	AUO Construction

a first and a second side portion being exposed from the second metal layer	Claim Terms
C	Jes.
	LGD Construction
	CMO Construction
A first side portion and a second side portion on the top surface of the first metal layer not covered by the second layer Intrinsic Support E.g., Indefinite: Figs. 3-4; 4:40-5:9; 5:38-55; 6:45-54; 6:58-62	AUD Construction App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01 Response, pages 4-7 and 9-10; App 09/983629, 8/8/01 Notice of Allowance, page 2

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																				Claim
																				Claim Terms
	, , , , , , , , , , , , , , , , , , , ,													***************************************					*	Des.
٠													-							LGD Construction
																				CMO Construction
Interview Summary, pages 1-2;	App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99	Notice of Allowance, page 2;	App 05/363025, 11/13/02 Office Action, pages 5-6; App 09/983679 1/14/03	Office Action, pages 4-11;	Response, pages 4-7; App 09/983629, 8/14/02	App 09/243556, 8/3/01	App 09/243556, 3/29/01	Response, page 7;	Response, page 2;	App 10/872,527, 8/29/06	App 10/8/2,32/, 3/29/06 Office Action, page 2;	Office Action, pages 2-3;	App 10/872,527, 9/30/05	1-2;	App 10/377,732, 5/27/04	Office Action, pages 2-5;	App 10/377,732, 2/27/04	Response, pages 3-4;	App 08/918119, 11/17/98	AUO Construction

	two side portions of the first metal layer having no second metal layer deposited thereon		Claim Terms
	A C	Des	Dec
			I GD Construction
			CMO Construction
E.g., Figs. 3-4; 4:40-5:9; 5:38-55;	The two portions on the top surface of the first metal layer not covered by the second metal layer Intrinsic Support	App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01 Response, pages 4-7 and 9-10; App 09/983629, 8/8/01 Notice of Allowance, page 2	AIIO Construction

· ·	10-2330)
	Claim Terms
	Des.
	LGD Construction
	CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7; App 09/243556, 3/29/01 Office Action, pages 4-7; App 09/983629, 8/14/02 Office Action, pages 4-11; App 09/983629, 1/13/02 Office Action, pages 5-6; App 09/983629, 1/14/03 Notice of Allowance, page 2; App 08/918462, 4/26/99 Office Action, pages 1-2;	AUO Construction 6:45-55

the first metal layer including aluminum		Claim Terms
С		Des.
		LGD Construction CMO Construction
		struction
Plain meaning	Interview Summary, pages 1-2; App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01 Response, pages 4-7 and 9-10; App 08/918462, 8/8/01 Notice of Allowance, page 2	AUO Construction

G-3

Disputed Constructions

transistor	С	a device that includes a
		semiconductor material and three electrodes
•		Intrinsic Support
,	-	1:15-15; 4:26-31; Fig. 2; Fig. 3
substrate	С	plain meaning
forming a second metal layer on the first metal layer	C	the second metal layer is formed in direct contact with the first metal layer
		Intrinsic Support
		3:49-51; Abstract; Fig. 3; Figs. 4A-F

Claim Terms	Des.	LGD Construction	CMO Construction ¹	AUO Construction
depositing a second metal layer on the first metal layer	C		the second metal layer is deposited in direct contact with the first metal layer	
			Intrinsic Support	· -
			3:49-51; Abstract; Fig. 3; Figs. 4A-F	-
[a] double layered metal gate	A C		a double-layered metal gate is a gate having only two metal layers	
			Intrinsic Support	
			1:17-23; 3:27-29; 4:32-34; 5:21-25; 6:27-29; Fig. 2; Fig. 3; Figs. 4A-F; Application, 08/918,119, Response, November 17, 1998	
gate	T		a region of a transistor	
			Intrinsic Support	
			4:26-31; Fig. 2; Fig. 3	

	a total width of the first metal layer is greater than a total width of the second metal layer by about 1 to 4 μm
	Des. L C A
F 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1 1	LGD Construction T S S S S S S S S S S S S
1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999	The top surface of the first metal layer has a width that is about 1 to 4 µm wider than a width of the top surface of the second metal layer to form a double step. A double step is a structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support
· ·	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction 1	AUO Construction
first etching layer	Ţ		indefinite	
waking	L		indefinite	
forming a single photoresist having a predetermined width on the second metal layer	C		the photoresist is deposited in direct contact with the second metal layer	
			Intrinsic Support	-
			3:41-58; 6:15-18; Figs. 4A- F	
photoresist	C		an etching mask	
			Intrinsic Support	
			3:41-58; 6:15-18; Figs. 4A- F	-
simultaneously in a single etching step using the single photoresist as a mask	L		the first and second metal layers are simultaneously etched in a single step using the photoresist as a mask	
			Intrinsic Support	
			5:55-62; 7:15-30	
simultaneously patterning/patterning simultaneously	Α		plain meaning	

the first metal layer being etched to have a width greater than a width of the second metal layer by about 1 to 4 µm A The first metal layer heing C of the first metal layer as a width of the second metal layer by about 1 to 4 µm width that is	Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
A C	the first metal layer being etched	Л		The first metal layer being	
	to have a width greater than a	a		etched so that a top surface	
	width of the second metal layer	A			
wider than a width of the top surface of the second metal layer to form a double step. A double step is a structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 198,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, 9804417.5, Application, 9804417.5, Response, March 4, 1999	by about 1 to 4 μm			width that is about 1 to 4 µm	-
top surface of the second metal layer to form a double step. A double step is a structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 198,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999			· ·	wider than a width of the	
metal layer to form a double step. A double step is a structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999			-	top surface of the second	
step. A double step is a structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998; United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				metal layer to form a double	
structure where not all of the top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				step. A double step is a	
top surface of the first metal layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999			-	structure where not all of the	-
layer is covered by the second metal layer. Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998; United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999			· · · · · · · · · · · · · · · · · · ·	top surface of the first metal	_
Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				layer is covered by the	
Intrinsic Support 1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				second metal layer.	
1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				Intrinsic Support	
6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				1:23-2:65; 4:39-51; 5:25-37;	
Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				6:15-26; 6:40-47; Fig. 3;	
918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				Figs 4A-F; Application,	-
August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999			Patricipa	918,119, Original Drawings;	
Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				August 27, 1997;	
Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				Request for Patent Drawing	
1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999		*************		Revision, December 16,	
Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				1998, United Kingdom	
Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999		******		Application, 9804417.5,	
1998; United Kingdom Application, 9804417.5, Response, March 4, 1999				Office Action, May 21,	
Application, 9804417.5, Response, March 4, 1999				1998; United Kingdom	
Response, March 4, 1999				Application, 9804417.5,	
				Response, March 4, 1999	

		the first metal layer including C aluminum	layer having no second metal A layer deposited thereon	two side portions of the first metal C	being exposed from the second metal layer	a first and a second side portion C	Claim Terms Des.
4:34-36; 5:41-42	Intrinsic Support	A first metal layer that includes pure aluminu		plain meaning		plain meaning	LGD Construction CMO Construc
		nat num					uction AUO Construction

H-1

Disputed Constructions

																						100000
																					Transistor	Claim Terms
																					C	rms Des.
Abstract.	1:20-40; 1:61-64; 2:64-68; 3:39-4:14: 5:56-58:	Intrinsic Support	crystal silicon wafer.	substrate rather than a single	techniques on an insulating	formed using thin-film	thin-film transistor is	an insulating layer. The	from the semiconductor by	the gate, which is separated	applied at the third terminal,	introduced by a voltage	semiconductor; this field is	field that penetrates the	modulated by an electric	drain, is controlled or	terminals, the source and	through one pair of	which the current flow	semiconductor device in	A three-terminal	. LGD Construction
																						CMO Construction
					-										-					-		AUO Construction

Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
substrate	С	the material (such as glass)	
	**************************************	upon which a transistor or	
		integrated circuit is	
		fabricated to provide	_
		mechanical support	
•		Intrinsic Support:	
		2:64-3:3; 3:59-4:8; 5:59-64; Figs 1-4; Abstract.	

Claim Terms	Des.	LGD Construction	CMO Construction	AUU Construction
a double layered metal gate	С	a patterned structure of an		
	A	electrically conductive		
		material that includes two		
		sequentially deposited metal		-
		layers and includes a portion		
		that controls current flow		
		through the channel between		
		the source electrode and		
		drain electrode		-
		Intrinsic Support		
		1.01 56. 1.30 60. 3.4 34.		
		3:39-4:13; 4:41-53; 4:58-		
		5:25; 5:39-55; 5:59-6:25;	n garagean	
		6:33-65; 7:24-8:26;		
		Abstract; App 08/918,119,		
		8/20/1998, Office Action;		
		App 08/918,119,		
		11/25/1998, Amendment;		
		USP 5,905,274, Claims 1, 4;		
		App 09/243,556, 1/8/2001,		
		Amendment; App		
	•	Office Action: App		
		09/243,556, 8/3/2001,	not entered	
		Amendment; App		
		09/243,556, 9/10/2001,		
		Notice of Allowance; USP		
		6,548,829, Claim 1.		

	gate gate
	Des.
1:21-56; 1:38-60; 3:3-35; 3:39-4:13; 4:41-53; 4:58-5:25; 5:39-55; 5:59-6:25; 6:33-65; 7:24-8:26; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 4; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance; USP 6,548,829, Claim 1.	patterned electrically conductive material that includes a portion that controls current flow through the channel between the source electrode and drain electrode Intrinsic Support
	AUO Construction

	Claim Terms having a first metal layer and a second metal layer thereon
	Des. L C
1:38-44; 2:64-3:37; 3:44-4:13; 4:44-57; 5:4-10; 5:39-55; 5:59-6:5; 8:6-26; Figs 1-4; Abstract; App 8/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 4; App 09/243,556, 8/3/2001, Amendment; USP 6,340,610, Claims 1, 4.	sequentially depositing the second metal layer above and in contact with the first metal layer
	CMO Construction
	AUO Construction

	1		
a total width of the first metal	L	the width of the first metal	Construction ACO Construction
layer being greater than a total	С	layer, determined by the	
width of the second metal layer by	Α	portion of the first metal	~ -
about 1 to 4 µm		layer in contact with the	
		second metal layer together	
		with the portions exposed to	
		the subsequently deposited	
		gate insulating layer, is	
		more than 1 µm and less	-
		than 4µm greater than the	-
		width of the second metal	
-		layer	
		Intrinsic Support 2:1-38: 3:58-4:13: 4:51-5:3:	
		5:39-55; 6:6-13; 6:18-65;	
		7:41-8:2; 8:21-26; Figs. 1-4;	
		Abstract; App 08/918,119,	
		8/20/1998, Office Action;	-
		App 08/918,119,	
		11/25/1998, Amendment;	
		USP 5,905,274, Claims 1, 2,	
		4, 5; App 09/243,556,	
		9/6/2000, Office Action;	
		App 09/243,556, 1/8/2001,	
		Amendment; App	
		09/243,330, 3/29/2001,	
		09/243 556 8/3/2001	
		Amendment: Ann	
		09/243,556, 9/10/2001,	
		Notice of Allowance; USP	
		6,340,610, Claim 1; USP	
		6,548,829, Claims 1 and 6.	

			,	metal layer	a first and second side portion being exposed from the second	Claim Terms
						Des
Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance.	App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001,	3:39-46; 3:51-57; 5:39-55; 6:55-65; 8:21-26-; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action;	Intrinsic Support 1:35-60; 2:64-3:13;	layer that are exposed to the subsequently deposited gate insulating layer	first and second side surfaces of the first metal	LGD Construction
					CMAC CONSTRUCTION	CMO Construction
			<u>-</u>		AUO Consuluction	AIIO Construction

side surface of the first metal layer exposed to the subsequently deposited gate insulating layer Intrinsic Support 1:35-60; 2:64-3:13; 3:39-50; 3:51-57; 5:39-55; 6:55-65; 8:21-26; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action; App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001, Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance.							Claim Terms Des. side portion of the first metal layer A
AUO	Office Action; App 09/243,556, 8/3/2001, Amendment; App 09/243,556, 9/10/2001, Notice of Allowance.	App 08/918,119, 11/25/1998, Amendment; USP 5,905,274, Claims 1, 2, 4, 5; App 09/243,556, 1/8/2001, Amendment; App 09/243,556, 3/29/2001,	6:55-65; 8:21-26; Figs 1-4; Abstract; App 08/918,119, 8/20/1998, Office Action;	1:35-60; 2:64-3:13; 3:39-50; 3:51-57; 5:39-55;	Intrinsic Support	metal layer exposed to the subsequently deposited gate insulating layer	side surface of the first
							ruction

H-2

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Disputed Constructions

					F
					Transistor
					C Jes.
					LGD Construction CMO Construction
4:41-50; 4:58-63;	E.g.,	Intrinsic Support	A three-terminal semiconductor device in which the current flow through one pair of electrodes, the source electrode and drain electrode and drain electrode, is controlled or modulated by an electric field that penetrates the semiconductor; this field is introduced by a voltage applied at the third electrode, the gate electrode, which is separated from the semiconductor by an insulating layer. The thinfilm transistor is formed using thin-film techniques on an insulating substrate	Or .	Plain meaning

A gate electrode naving a two-layered step structure Intrinsic Support E.g., Figs. 3-4; 1:29-3:14; 3:44-4:9; 4:41-5:9; 5:38-55; 6:44-47;	□ > C	Gate
OR The material (such as glass) upon which a transistor or integrated circuit is fabricated to provide mechanical support.		Substrate
7:5-11	Σ	2

E.g., Figs. 3-4; 5:59-6:5 Indefinite;	CL	a total width of the first metal
E.g., Figs. 3-4; 5:59-6:5		
E.g.,		
AND		
Intrinsic Support		
The double layered metal gate having a first metal layer and a second metal layer formed on the top surface of the first metal layer	C	having a first metal layer and a second metal layer thereon
E.g., 3:44-50; 4:41-5:21		
Intrinsic Support		
the gate electrode		
between the source electrode and drain		

			Claim Terms
	·		Des. LGD Construction
			CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01 Response, page 7; App 09/243556, 3/29/01	Figs. 3-4; 2:29-3:14; 4:40-5:9; 5:38-55; 6:14-25; 6:45-54;	Intrinsic Support Indefinite:	AUO Construction greater than the width of the second metal measured from a level defined by the top of the first metal layer

				Claim Terms
 				
				Des.
		•		
				Con
				LGD Construction
				tion
				CMO Const
				Istru
				ruction
App Res App Off App Res App	1-2; App App Res App Off	2; Apr Off Apr	App Office Not	Offi App Res App
pons 5 08/9 5 08/9 6 08/9 5 08/9	pons 5 08/9 5 08/9 5 08/9	08/9 ice A	ice A 09/9 ice A 09/9	AUX ice A ice A 09/2 pons pons 09/9
e, pag 91840 ction 91840 e, pag 91840	91840 e, Re 91840 ction)184(ction	ction 98362 ction ction 98362	ction 24355 e, pag 98362
ges 4- 52, 07, pag 52, 111 ges 4- 52, 12	nimar 52, 9/ mark 52, 12	52, 4/ , pag 52, 9/	, pag 29, 11 , pag , pag 29, 1/	AUC Construction Office Action, pages 2-5; App 09/243556, 8/3/01 Response, pages 4-7; App 09/983629, 8/14/02
-8; 7/7/0(es 2 1/7/0(-10; 2/5/0(y, pa 27/99 Sect 2/14/9 es 3-	26/99 26/99 es 1-2	es 4- 1/13/(es 5- 14/03	es 2-: 3/01 -7; 14/02
5;5	;5; 66 66 66 68	25. A &	11 5; 5;	5;
	App 08/918462, 4/15/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00	Interview Summary, pages 1-2; App 08/918462, 9/27/99 App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 07/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00	2; App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages 1-2; App 08/918462, 9/27/99 App 08/918462, 9/27/99 Response, Remark Section App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 11/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00	

		ť	
		a first and second side portion being exposed from the second metal layer	Claim Terms
		A C	Des.
			LGD Construction CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05 Office Action, pages 2-3; App 10/872,527, 3/29/06 Office Action, page 2; App 10/872,527, 8/29/06 Response, page 2; App 09/243556, 1/8/01	Intrinsic Support E.g., Figs. 3-4; 4:40-5:9; 5:38-55; 6:45-55 6:58-63;	The two side portions on the top surface of the first metal layer not covered by the second metal layer	AUO Construction App 09/983629, 8/8/01 Notice of Allowance, page 2

,		
		Claim Terms
		Des.
,		LGD C
		Construction
		tion
		-
		СМО
		Const
		CMO Construction
Kesponse, pages 4-/; App 09/983629, 8/14 Office Action, pages App 09/983629, 11/1 Office Action, pages App 09/983629, 11/1 Office Action, pages App 09/983629, 1/14 Notice of Allowance, 2; App 08/918462, 4/26 Office Action, pages App 08/918462, 9/10 Interview Summary, 1 1-2; App 08/918462, 12/1 Office Action, pages App 08/918462, 12/1 Office Action, pages App 08/918462, 11/7 Response, pages 4-8; App 08/918462, 11/7 Office Action, pages App 08/918462, 11/7 Response, pages 4-10 App 08/918462, 12/5 Interview Summary; App 08/918462, 12/5 Interview Summary; App 08/918462, 1/23 Office Action, pages App 08/918462, 1/23 Office Action, pages App 08/918462, 1/23 Office Action, pages App 08/918462, 1/23	App 09, Office / App 09,	AUO Constr Response page 7:
se, pag /98362! Action, /98362! Action, /98362! /91846: Action, /91846: W Sum /91846: /91846: Action, /91846: /91846: /91846: /91846: /91846: /91846: /91846: /91846: /91846: /91846: /91846: /91846:	Action, 124355	O Con
Response, pages 4-7; App 09/983629, 8/14/02 Office Action, pages 4-1; App 09/983629, 11/13/02 Office Action, pages 5-6; App 09/983629, 1/14/03 Notice of Allowance, page 2; App 08/918462, 4/26/99 Office Action, pages 1-2; App 08/918462, 9/10/99 Interview Summary, pages 1-2; App 08/918462, 9/27/99 Response, Remark Section; App 08/918462, 12/14/99 Office Action, pages 3-6; App 08/918462, 4/13/00 Response, pages 4-8; App 08/918462, 11/7/00 Office Action, pages 2-5; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 11/7/00 Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01	App 09/243556, 3/29/01 Office Action, pages 2-5; App 09/243556, 8/3/01	AUO Construction
/02 /02 /4-11; 3/02 5-6; /03 page page /99 yages /99 ction; //99 3-6; /00 00 2-5; /00	'01 2-5;	on
		

					side nortion of the first metal laver	Claim Terms
				*	>	Des.
						LGD Construction CMO Construction
App 08/918119, 11/17/98 Response, pages 3-4; App 10/377,732, 2/27/04 Office Action, pages 2-5; App 10/377,732, 5/27/04 Terminal Disclaimer, pages 1-2; App 10/872,527, 9/30/05	Figs. 3-4; 4:40-5:9; 5:38-55; 6:45-55 6:58-62;	E.g.	surface of the first metal layer not covered by the second metal layer Intrinsic Support	front: Each of the first and second side portions on the top	Notice of Allowance, page 2 Construed with "each" in	AUO Construction Response, pages 4-7 and 9- 10; App 09/983629, 8/8/01

	Claim Terms
	Des.
	LGD Construction
	CMO Construction
Response, pages 4-10; App 08/918462, 12/5/00 Interview Summary; App 08/918462, 1/23/01 Office Action, pages 2-4; App 08/918462, 4/4/01 Response, pages 4-7 and 9-10; App 09/983629, 8/8/01 Notice of Allowance, page 2	AUO Construction

H-3

Disputed Constructions

a double layered metal gate	Substrate		Transistor
metal gate			Claim Terms
A C	С		C C
		. •	LGD Construction
a gate having only two metal layers Intrinsic Support 1:17-23; 3:27-29; 4:32-34; 5:21-25; 6:27-29; Fig. 2; Fig. 3; Figs. 4A-F; Application, 08/918,119, Response, November 17, 1998	plain meaning	Intrinsic Support 1:15-16; 4:26-31; Fig. 2; Fig. 3	a device that includes a semiconductor material and three electrodes
		- -	AUU Construction

The citations to the patent specification are to the colum and line numbers in the grand-parent patent U.S. Pat. No. 5,905,274.

		having a first metal layer and a second metal layer thereon			Gate Claim Terms
		CL			Des.
					LGD Construction
3:49-51; Abstract; Fig. 3; Figs. 4A-F	Intrinsic Support	the second metal layer is in contact with the first metal layer	4:26-31; Fig. 2; Fig. 3	Intrinsic Support	a region of a transistor
		-	· •		AUO Construction

	a total width of the first metal layer being greater than a total width of the second metal layer by about 1 to 4 µm
	A C
*	LGD Construction
1:23-2:65; 4:39-51; 5:25-37; 6:15-26; 6:40-47; Fig. 3; Figs 4A-F; Application, 918,119, Original Drawings; August 27, 1997; Application, 918,119, Request for Patent Drawing Revision, December 16, 1998, United Kingdom Application, 9804417.5, Office Action, May 21, 1998; United Kingdom Application, 9804417.5, Response, March 4, 1999	The top surface of the first metal layer has a width that is about 1 to 4 µm wider than a width of the top surface of the second metal layer to form a double step. A double step is a gate where not all of the top surface of the first metal layer is covered by the second metal layer.
-	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction 1	AUO Construction
a first and second side portion	С		plain meaning	
being exposed from the second	Α			
metal layer				
side portion of the first metal layer A	A		plain meaning	

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Claim Terms	Des.	Agreed Constructions
UV sealant	С	sealant material that is at least partially curable by UV light
forming a main UV sealant	L	The combination of the construction for "forming a main sealant" with the agreed
		construction of "UV sealant"
auxiliary UV sealant	С	The combination of the construction for "auxiliary sealant" with the agreed construction of
	A	"UV sealant"
main UV sealant	С	The combination of the construction for "main sealant" with the agreed construction of
	A	"UV sealant"

Disputed Constructions

					
	a dummy region		auxiliary sealant		Claim Terms main sealant
	A		A C		Des. C A
Intrinsic Support 5:7-20; 7:63-8:2; Figs. 3B, 4A, and 5A.	an area outside of the main sealant	Intrinsic Support 5:7-20; 7:63-8:2; Figs. 3B, 4A, and 5A.	sealant deposited in an area outside of the main sealant	Intrinsic Support 2:36-40; 3:20-25, 5:5-20; 7:63-8:2; Figs. 2B, 3B, 4A, and 5A.	LGD Construction C sealant material that encloses the display region
					CMO Construction
					AUO Construction

	connects to the main sealant	Claim Terms Des.
Intrinsic Support 2:41-55; 5:7-20; 7:63-8:2; Figs. 3B, 4A, and 5A; App 10/184,118, 7/16/04, Response, pagse 2; App 10/184,118, 2/16/05 Response, pages 2-3; App 10/184,118, 4/18/05 Response, pages 6-7; App 10/184,118, 11/27/06 Response, page 2.	joined to the main sealant	LGD Construction CMO Construction
		AUO Construction

	Claim Terms Wherein the auxiliary UV sealant is formed in a dummy region and extends outside from the main UV sealant
	Des. L A
Intrinsic Support 2:41-55; 5:7-20; 7:63-8:2; Figs. 3B, 4A, and 5A; App 10/184,118, 7/16/04, Response, page 2; App 10/184,118, 2/16/05 Response, pages 2-3; App 10/184,118, 4/18/05 Response, pages 6-7 App 10/184,118, 11/27/06 Response, page 2.	LGD Construction CMO Construction wherein the auxiliary UV sealant is deposited in an area that is outside of the main UV sealant and is joined to the main UV sealant area that is outside of the main UV sealant and is
	astruction
	AUO Construction

, , , , , , , , , , , , , , , , , , ,	wherein the auxiliary UV sealant C wherein the auxiliary UV sealant A sealant touches the main UV	Response, pages 6-7; App 10/184,118, 11/27/06	Response, pages 2-3; App 10/184,118, 4/18/05	Response, page 2; App 10/184,118, 2/16/05	Figs. 3B, 4A, and 5A; App	<u>Intrinsic Support</u> 2:41-55; 5:7-20; 7:63-8:2;	Α	the main sealant are contiguous C main sealants are deposited	Des.
				-		· -			AUO Collstruction

	Claim Terms	Des.	LGD Construction CMO Construction	AUO Construction
	applying a liquid crystal on one of	ם ב	depositing the liquid crystal	
	ere to net my abber propries	> (substrates	
•			Intrinsic Support 5:65 - 6:9; Fig. 3B.	· -
	attaching the lower and upper substrates	Α	pressing the lower and upper substrates together	-
			Intrinsic Support 6:4-6; Figs. 1C and 2C.	

I-2

Claim Terms	Des.	Agreed Constructions
UV sealant	С	sealant material that is at least partially curable by UV light
forming a main UV sealant	T	The combination of the construction for "forming a main sealant" with the agreed
		construction of "UV sealant"
main UV sealant	С	The combination of the construction for "main sealant" with the agreed construction of
	A	"UV sealant"
auxiliary UV sealant	С	The combination of the construction for "auxiliary sealant" with the agreed construction of
	A	"UV sealant"

Disputed Constructions

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
preparing a lower substrate and an	С			Indefinite
upper substrate				
	-			Intrinsic Support
				E.g.,
				Figs. 3, 4, 5, & 6;
				4:23-67;
	······································			6:40-67;
				7:27-58;
				7:64-34
forming a main sealant	T			forming a segment of
				sealant that encloses the liquid crystal in the LCD
				panel
				Intrinsic Support
				E.g.,

Claim Terms Des JGD Construction AUO Construction Figs. 3, 4, 5, & 6; 339-40; 539-40; 539-40; 539-40; 539-40; 539-40; 539-40; 640-67 App 10/184118, 12/1/03 OA, pages 2-7; App 10/184118, 12/1/03 OA, pages 2-7; App 10/184118, 7/15/2004 Reply Under 37 C.F.R. Section 1.111, pages 2-6 App 10/184118, 12/18/2004 OA, pages 2-7; App 10/184118, 12/18/2004 OA, pages 2-7; App 10/184118, 02/16/2005 Response after Office Action, pages 2-7; App 10/184118, 02/16/2005 Response as Submission under 37 C.F.R. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-7; App 10/184118, 06/15/2005 Office Action, pages 6-7; App 10/184118, 06/15/2005 Office Action, pages 6-7; App 10/184118, 06/15/2005 Office Action, pages 6-7; App 10/184118, 06/15/2005		- Indiana
LGD Construction CMO Construction		Claim Terms
CMO Construction		Des.
CMO Construction		
CMO Construction		LGDC
CMO Construction		onstru
		ection
		CM
		O Con
		structi
Figs. 3, 4, 5, & 6; 3:9-40; 5:1-64; 6:40-67 App 10/184118, 12/1/03 OA, pages 2-7; App 10/184118, 2/4/04 Amendment in Response to Non-Final Office Action, pages 7-9; App 10/184118, 7/15/2004 Reply Under 37 C.F.R. Section 1.111, pages 2-6 App 10/184118, 11/18/2004 OA, pages 2-8; App 10/184118, 02/16/2005 Response after Office Action, pages 2-7; App 10/184118, 04/18/2005 Response as Submission under 37 C.F.R. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005		On .
WO Construction 3, 4, 5, & 6; 0; 4; 67 10/184118, 12/1/03 2 ages 2-7; 10/184118, 2/4/04 2 indment in Response to Final Office Action, 7-9; 10/184118, 7/15/2004 2 Under 37 C.F.R. 2 in 1.111, pages 2-6 10/184118, 11/18/2004 2 ages 2-8; 2 in 1.114, 02/16/2005 2 inse after Office 2 in, pages 2-7; 10/184118, 04/18/2005 2 inse as Submission 2 in 2 i	Figs. 3:9-4 5:1-6 6:40- App OA, I App OA, I Amer Non- pages App O4/26 App O4/26 App Respo OA, I App I App I App I App I App I App I Respo Actio App I Respo Office App I Respo Office App I	A
onstruction & 6; & 6; 18, 12/1/03	3, 4, 5, 0; 0; 4; 67 10/184] pages 2 10/184] riman of Final O; 7-9; 10/184] riman of The final O; 10/184]	O OU
ction /1/03 /1/04 /1/04 /1/04 /1/04 /1/04 /1/0005 /1/0004 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005 /1/0005	& 6; & 6; 118, 12 -7; in Res effice A pages: 118, 7/: 118, 7/: 118, 11 1, page 118, 02 ter Offi s 2-7; s 2-7; r. R. 1.1 18, 04 Submi R. 1.1 18, 06 n, page 118, 09 non-fin n, page	onstru
	/1/03 1/04 ponse t ction, 2-7; 15/2004 F.R. % 2-6 /18/200 ce ce /18/200 ssion 14, /15/200 ss 2-4; /15/200 is 6-7; /01/200	ction
	<u>σ σ σ σ σ σ σ σ σ σ σ σ σ σ σ σ σ σ σ </u>	

				1									[25057]
			auxiliary sealant			main sealant							Claim Terms
	· · · · · · · · · · · · · · · · · · ·		≯ C			> C							Des.
													LGD Construction
													CMO Construction
Fig. 4, 5, & 6; 3:9-40;	E.g.,	Intrinsic Support	A segment of sealant that extends from the main sealant and is outside the enclosure of the main sealant	See above	Intrinsic Support	a segment of sealant for enclosing the liquid crystal in the LCD panel	App 10/184118, 10/11/2006 Notice of Allowability, page 2	Response to Non-final Office Action, page 5;	App 10/184118, 09/15/2006	App 10/184118, 06/19/2006	Response to Final Office	App 10/184118, 03/01/2006	AUO Construction

Claim Terms	Des.	LGD Construction	CMO Construction	AUO Construction
				5:1-64; 6:40-67
a dummy region	A			An area outside the enclosure of the main sealant
				Intrinsic Support
				E.g.,
				Figs. 2, 3, 4, 5, & 6;
				3:9-40;
				5:1-64; 6:40-67
connects to the main sealant	T			Physically attached to the main sealant
				Intrinsic Support
				E.g.,
				Figs. 3, 4, 5, & 6; 5:1-64; 6:40-67
wherein the auxiliary UV sealant	T			Wherein the auxiliary UV
extends outside from the main UV sealant	Α			outside the enclosure of the main UV sealant

				wherein the auxiliary sealant and the main sealant are contiguous				Claim Terms
				A C L				Des.
								LGD Construction CMO Construction
App 10/184118, 12/1/03 OA, pages 2-7; App 10/184118, 2/4/04 Amendment in Response to Non-Final Office Action, pages 7-9; App 10/184118, 04/26/2004, pages 2-7; App 10/184118, 7/15/2004 Reply Under 37 C.F.R.	Figs. 3, 4, 5, & 6; 5:1-64; 6:40-67	E.g.,	Intrinsic Support	Wherein the auxiliary sealant and the main sealant are physically connected to each other	Figs. 3, 4, 5, & 6; 5:1-6:9; 6:40-67	E.g.	Intrinsic Support	AUO Construction

	,	
wherein the auxiliary UV sealant contacts the main UV sealant		Claim Terms
≯ C		Dec
		I.GD Construction
		CMO Construction
wherein the auxiliary sealant and the main sealant are physically connected	Section 1.111, pages 2-6 App 10/184118, 11/18/2004 OA, pages 2-8; App 10/184118, 02/16/2005 Response after Office Action, pages 2-7; App 10/184118, 04/18/2005 Response as Submission under 37 C.F.R. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final Office Action, pages 5; App 10/184118, 09/15/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Notice of Allowability, page	ATIO Construction

				the lower and upper substrates	and time a liquid exected on one of			Claim Terms
				A C t	-			Des.
								LGD Construction CMO Construction
App 10/184118, 04/26/2004, pages 2-7; App 10/184118, 7/15/2004 Reply Under 37 C.F.R. Section 1.111, pages 2-6 App 10/184118, 11/18/2004 OA, pages 2-8;	App 10/184118, 12/1/03 OA, pages 2-7; App 10/184118, 2/4/04 Amendment in Response to Non-Final Office Action, pages 7-9;	Figs. 3, 4, 5, & 6; 5:65-6:9; 6:40-67	E.g.,	Intrinsic Support	Figs. 3, 4, 5, & 6; 5:1-6:9; 6:40-67	E.g.,	Intrinsic Support	AUO Construction together

under 3 / C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2.4; App 10/184118, 09/15/2005 Response to mon-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Notice of Allowability, page Putting the lower and upper substrates together as one single piece Intrinsic Support	attaching the lower and upper substrates
	taching the lower and upper ubstrates
under 37 C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Notice of Allowability, page	
under 3 / C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006 Notice of Allowability, page	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final Office Action, page 5; App 10/184118, 10/11/2006	
under 37 C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 09/15/2006 Response to Non-final	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8; App 10/184118, 06/19/2006	
pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006 Office Action, pages 2-8;	
under 3 / C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7; App 10/184118, 06/19/2006	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office Action, pages 7;	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006 Response to Final Office	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4; App 10/184118, 03/01/2006	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005 Office Action, pages 2-4;	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7; App 10/184118, 12/01/2005	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final Office Action, pages 6-7;	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005 Response to non-final	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4; App 10/184118, 09/15/2005	
under 3/ C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005 Office Action, pages 2-4;	
under 3 / C.F.K. 1.114, pages 6-11; App 10/184118, 06/15/2005	
pages 6-11;	
under 3/ C.r.K. 1.114,	
Response as Submission	
App 10/184118, 04/18/2005	
Action, pages 2-7;	
Response after Office	
App 10/184118, 02/16/2005	

· · · · · · · · · · · · · · · · · · ·	10000
	Claim Terms
	Des.
	LGD Construction
	CMO Construction
Figs. 3, 4, 5, & 6; 5:65-6:9; 6:40-67	AUO Construction

Case 1:06-cv-00726-JJF Document 363-4 Filed 07/29/2008 Page 108 of 114

I-3

auxiliary UV sealant	forming a main UV sealant	main UV sealant	Claim Terms UV sealant
A C	Ц	AC	Des.
The combination of the construction for "auxiliary sealant" with the agreed construction for "UV sealant"	The combination of the construction for "forming a main sealant" with the agreed construction for "UV sealant"	The combination of the construction for "main sealant" with the agreed construction for "UV sealant"	Agreed Constructions sealant material that is at least partially curable by UV light

Disputed Constructions

		forming a main sealant L	preparing a lower substrate and an C upper substrate	Claim Terms Des.
Abstract; 3:20-24; 3:35-41; 3:55-4:11; 5:3-30; 6:34-39; 7:11-16; 7:63-8:2; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6	Intrinsic Support	forming sealant material necessary for confining liquid crystal from leaking out from between the substrates	indefinite	LGD Construction CMO Construction
35-41; 34-39; gs. 1A- IA-4D,		rial ng aking	-	ion AUO Construction

auxiliary sealant	Claim Terms main sealant
A C	Des. A
	LGD Construction
sealant material that is not necessary for confining liquid crystal from leaking out from between the substrates Intrinsic Support Abstract; 1:20-23; 3:20-24; 3:35-41; 3:55-4:11; 5:3-20; 6:34-39; 7:11-16; 7:63-8:2; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6	sealant material necessary for confining liquid crystal from leaking out from between the substrates Intrinsic Support Abstract; 3:20-24; 3:35-41; 3:55-4:11; 5:3-30; 6:34-39; 7:11-16; 7:63-8:2; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6
·	AUO Construction

	connects to the main sealant		a dummy region	Claim Terms
	L		ΔL	Des.
				LGD Construction
Intrinsic Support Abstract; 1:20-23; 2:5-55; 3:9-40; 3:55-4:11; 5:3-20; 5:27-51; 6:34-39; 7:63-8:2; 8:14-17; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6; App. 10/184,118, 11/18/04 Office Action, page 2-3; 2/16/05 Amendment at page 2	physically attached to the	Intrinsic Support Abstract; 1:20-23; 2:5-55; 3:9-40; 3:55-4:11; 5:3-20; 5:27-51; 6:34-39; 7:63-8:2; 8:14-17; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6; App. 10/184,118, 11/18/04 Office Action, page 2-3; 2/16/05 Amendment at page 2	an area outside the boundary of the main sealant	CMO Construction
.÷ -		-		AUO Construction

JOINT CLAIM CONSTRUCTION STATEMENT - EXHIBIT I LG DISPLAY USP 7,218,374

	ŧ	
	wherein the auxiliary UV sealant is formed in a dummy region and extends outside from the main UV sealant	Claim Terms
	A C	Des.
		LGD Construction
Intrinsic Support Abstract; 1:20-23; 2:5-55; 3:9-40; 3:55-4:11; 5:3-20; 5:27-51; 6:34-39; 7:63-8:2; 8:14-17; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6; App. 10/184,118, 3/1/06 Response, pages 5, 7	wherein the auxiliary UV sealant is formed in an area outside the boundary of the main UV sealant beginning from the main UV sealant and moving outward	CMO Construction
		AUO Construction

JOINT CLAIM CONSTRUCTION STATEMENT - EXHIBIT I LG DISPLAY USP 7,218,374

Abstract; 1:20-23 3:9-40; 3:55-4:11 5:27-51; 6:34-39; 8:14-17; Figs. 1A 2C, 3A-3D, 4A-4 6; App. 10/184,1 Office Action, pa 9/15/06 Amendm 4, 5	wherein the auxiliary UV sealant C contacts the main UV sealant A sealant ouche sealant	Intrinsic Support Abstract; 1:20-23 3:9-40; 3:55-4:11 5:27-51; 6:34-39; 8:14-17; Figs. 1A 2C, 3A-3D, 4A-4 6; App. 10/184,1 Office Action, pa 9/15/06 Amendm 2, 5	wherein the auxiliary sealant and the main sealant are contiguous A LGD Construction wherein the auxiliary sealant and the main sealant are contiguous A CNO Construction wherein the auxiliary touches but does the main sealant
Abstract; 1:20-23; 2:5-55; 3:9-40; 3:55-4:11; 5:3-20; 5:27-51; 6:34-39; 7:63-8:2; 8:14-17; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6; App. 10/184,118, 6/19/06 Office Action, page 3, 4; 9/15/06 Amendment, page 4, 5	wherein the auxiliary UV sealant touches the main UV sealant	Intrinsic Support Abstract; 1:20-23; 2:5-55; 3:9-40; 3:55-4:11; 5:3-20; 5:27-51; 6:34-39; 7:63-8:2; 8:14-17; Figs. 1A-1D, 2A-2C, 3A-3D, 4A-4D, 5A-5B, 6; App. 10/184,118, 6/19/06 Office Action, page 3, 4; 9/15/06 Amendment, page 2, 5	wherein the auxiliary sealant touches but does not overlap the main sealant
			AUU Construction

JOINT CLAIM CONSTRUCTION STATEMENT - EXHIBIT I LG DISPLAY USP 7,218,374

attaching the lower and upper A substrates	applying a liquid crystal on one of the lower and upper substrates A	
	S. LGD Construction	
putting the lower and upper substrates together as one single piece Intrinsic Support Abstract; 1:27-28; 3:25-34; 5:65-6:15; Figs. 1A-1D; 3A-3D	plain meaning Intrinsic Support Abstract; 1:31-55; 2:5-15; 2:34-40; 3:25-34; 5:27-5:51; Figs. 1A-1D; 3A-3D	
	AUU Construction	ATTO Construction

J-1

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Claim Terms	Des.	Agreed Constructions
color filter	L	a filter that modifies light from a source so as to allow one or more selected colors to pass
		through to the viewer side of the display. A color filter is formed on the color filter
		substrate
color filter substrate	Α	the structure on which the color filter is formed that faces the TFT substrate
active element	Α	an element that controls voltage or current, typically one or more transistors located at each
		pixel location

Disputed Constructions

the pillars are formed higher than the highest portions of the color filter.	Г	pillars formed higher than other portions of the color filter
Abstract; 1:57-60, Figs. 1 and 2; 2:1-12; 2:25-3:29, esp. 2:29-42, and Figs. 3 and 4; 3:35-38, and Fig. 2; 4:65-5:44, esp. 4:67-5:6, and Fig 8; 6:26-43, 6:47-51, and Figs. 6-11, esp. element 30; 6:52-7:32, esp. 7:8-19; 8:24-25; claims 1, 3, 6, and 7.		
Intrinsic Support '266 Specification		
a conductor, typically made of a transparent material, on the color filter substrate that receives a reference voltage relative to which the pixel electrode voltages can be measured	L	common electrode

	6:47-51, and Figs. 6-11, esp. elements 78 and 30; 7:4-13, and Fig. 8; 8:24-25; 8:28-		
	Abstract; 4:65-5:6, and Fig. 8; 6:26-43,		
	'266 Specification		
	Intrinsic Support		
	Plain meaning	L	the pillars are covered with the common electrode
	7266 Prosecution History March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.		
-	Abstract; 4:65-5:6, and Fig. 8; 5:57-6:5; 6:26-43, 6:47-51, and Figs. 6-11; 7:4-31, and Fig. 8; 8:28-34; claims 1, 3, 6 and 7.	1112	
	'266 Specification		
	Intrinsic Support		
	Plain meaning	L	objects formed on the array substrate
	266 Prosecution History March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.		
	Abstract; 4:65-5:6, and Fig. 8; 5:57-6:5; 6:26-43, 6:47-51, and Figs. 6-11, esp. elements 78 and 32; 7:4-31, and Fig. 8; 8:20-23; claims 1-5, 7, 9 and 10.		
	'266 Specification		
	Intrinsic Support		
Lest construction	ACO Construction	2000	

	5		
Claim I Villis	Deg.	34; claims 1, 3 and 7.	EXT CONSTITUTION
		266 Prosecution History	-
		March 5, 1997 Office Action, esp. at 2-3;	
		July 7, 1997 Response, esp. at 6-7.	-
pillars being formed higher than	L	the pillars are formed higher than the	, and the second
other portions of the facing		highest portions of the color filter substrate.	
onconunc			
		Intrinsic Support	
		'266 Specification	
		Abstract; 4:65-5:6, and Fig. 8; 5:57-6:5; 6:26-43, 6:47-51, and Figs. 6-11, esp. elements 78 and 32; 7:4-31, and Fig. 8;	
		7766 Prosecution History	
		March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.	
common electrode for all pixels covering at least some of the	Ц	Plain meaning	
pillars		Intrinsic Support	
		'266 Specification	
		Abstract; 4:65-5:6, and Fig. 8; 6:26-43, 6:47-51, and Figs. 6-11, esp. elements 78 and 30; 7:4-13, and Fig. 8; 8:24-25; 8:28-	
		'266 Prosecution History	
		March 5, 1997 Office Action, esp. at 2-3;	

storage capacitance line A a li typ: stor	Ma	Ab: 40, 6:2. elet		Intr	storage capacitance line for L the outputting the reference potential of the storage capacitance reference	Ma Jul		ode	the common electrode being L Pla electrically connected to the storage capacitance line at the		Ciaim Terms Des.
a line or wire of conductive material, typically metal, connected to one or more storage capacitors of the TFT array	'266 Prosecution History March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.	Abstract; 1:45-48, and Figs. 1 and 2; 2:31-40, and Figs. 3 and 4; 4:65-5:44, and Fig. 8; 6:26-43, 6:47-51, and Figs. 6-11, esp. element 28; claims 3, 6, 7, and 9.	'266 Specification	Intrinsic Support	the storage capacitance line is connected to the capacitor(s), and therefore outputs the reference potential of the storage capacitance	'266 Prosecution History March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.	Abstract; 4:65-5:44, and Fig. 8; 6:26-43, 6:47-51, and Figs. 6-11; 7:4-43, and Fig. 8; 8:24-25; 8:28-34; claims 1, 3 and 7.	'266 Specification	Plain meaning Intrinsic Support	July 7, 1997 Response, esp. at 6-7.	AUU Construction
											LGD Construction

A CONTROL OF THE CONT			
Caim Terms	Des.	Intrinsic Support	LGD Construction
		'266 Specification	•
		Abstract; 1:45-48, and Figs. 1 and 2; 2:31-40, and Figs. 3-4; 4:67-5:44, esp. 5:14-18, and Fig. 8; 6:26-43, 6:47-51, and Figs. 6-11, esp. element 28; claims 3, 6, 7, and 9.	
		7266 Prosecution History March 5, 1997 Office Action, esp. at 2-3; July 7, 1997 Response, esp. at 6-7.	
pillars of a color filter		pillars associated with and constructed on the color filter, for maintaining separation between the array substrate and the color filter substrate	
		Intincio Cumpost	
		'266 Specification	
		Abstract; 4:65-5:6, and Fig. 8; 5:57-6:5; 6:26-43, 6:47-51, and Figs. 6-11, esp. element 78; 7:4-32, and Fig. 8; 8:20-23; claims 1-5, 7, 9, and 10.	
injecting liquid crystal between the array substrate and the color	I	Introducing liquid crystal into the space between the array substrate and the color	
		Intrinsic Support	

266 Specification 266 Specification ; 2:17-18, and Fig. 2; 6:26-43, 6:47- igs. 6-11; 7:51-8:39, esp. 8:35-39; 266 Prosecution History ent No. 5,181,132 (Shindo et al.) in esp.: 2:9-18 and Fig. 2; 2:19-37 and 0:39-49 and Fig. 10; 11:15-22 and 13:27-32 and Fig. 16. ent No. 5,338,240 (Kim) in general,	U.S. Patent No. 5,181,132 (St general, esp.: 2:9-18 and Fig. Fig. 3; 10:39-49 and Fig. 10; Fig. 12; 13:27-32 and Fig. 16. U.S. Patent No. 5,338,240 (K.	266 Abstract; 2:17-18 51, and Figs. 6-1: claim 9.	Claim Terms Des. AUC
	"266 Prosecution History U.S. Patent No. 5,181,132 (Shindo et al.) in general, esp.: 2:9-18 and Fig. 2; 2:19-37 and Fig. 3; 10:39-49 and Fig. 10; 11:15-22 and Fig. 12; 13:27-32 and Fig. 16. U.S. Patent No. 5,338,240 (Kim) in general, esp.: 1:64-66 and Fig. 1; 4:31-34 and Fig. 3.	266 Specification Abstract; 2:17-18, and Fig. 2; 6:26-43, 6:47-51, and Figs. 6-11; 7:51-8:39, esp. 8:35-39; claim 9.	AUO Construction

J-2

Claim Terms	Des.	Agreed Constructions
color filter	T	A filter that modifies light from a source so as to allow one or more selected colors to pass
		through to the viewer side of the display. A color filter is formed on the color filter
		substrate.
color filter substrate	Α	the structure on which the color filter is formed that faces the TFT substrate
active element	Α	an element that controls voltage or current, typically one or more transistors located at each
		pixel location

Disputed Constructions

	common electrode	Claim Terms Des.
		AUO Construction
Intrinsic Support Abstract; 1:57-2:04; 2:25-42; 2:43-3:65; 5:07-10; 7:09-14; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11.	a conductor, typically made of a transparent material, on the color filter substrate that receives a reference voltage relative to the pixel electrode voltages	LGD Construction

	objects formed on the array substrate	,	Claim Terms pillars formed higher than other portions of the color filter
	L		Des.
			AUO Construction
Intrinsic Support Abstract; 2:13-19; 3:66-4:21; 4:21-30; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	structures having one or more patterned layers in the pixel array	Intrinsic Support Abstract; 2:13-19; 3:66-4:21; 4:21-30; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	patterned structures of the color filter that protrude toward the pixel array beyond the height of non-pillar portions of the color filter substrate to act as a spacer

	pillars being formed higher than other portions of the facing substrate	,	the pillars are covered with the common electrode
	Ţ		L L
			AUO Construction
Intrinsic Support Abstract; 2:13-19; 3:66-4:21; 4:21-30; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	patterned structures that protrude toward the pixel array beyond the height of non-pillar portions of the color filter substrate to act as a spacer	Intrinsic Support Abstract; 1:57-2:04; 2:13-19; 2:25-42; 2:43-3:65; 3:66-4:21; 4:21-30; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	the common electrode is formed to cover the protruded surface of the pillars

	the common electrode being electrically connected to the storage capacitance line at the portions of the common electrode covering the pillars		Claim Terms Do Do Common electrode for all pixels I covering at least some of the pillars
	L		Des.
			AUO Construction
Intrinsic Support Abstract; 1:45-48; 1:57-2:04; 2:13-19; 2:25-42; 2:43-3:65; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	the common electrode is electrically connected to the storage capacitance line in the pixel area where the pillars covered with the common electrode contact the objects on the array substrate	Intrinsic Support Abstract; 1:57-2:04; 2:25-42; 2:43-3:65; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	the common electrode is formed on the protruded surface of at least some of the pillars

	storage capacitance line		storage capacitance line for outputting the reference potential of the storage capacitance	Claim Terms
	Α		L	Des.
				AUO Construction
Intrinsic Support Abstract; 1:45-48; 1:57-2:04; 2:25-42; 2:43-3:65; 4:31-49; 4:65-5:06; 5:07-10; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	a pattern of electrically conductive material within the pixel area for providing a reference voltage to the storage capacitors	Intrinsic Support Abstract; 1:45-48; 1:57-2:04; 2:25-42; 2:43-3:65; 4:31-49; 4:65-5:06; 5:07-10; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	a pattern of electrically conductive material within the pixel area for providing a reference voltage to the storage capacitors	LGD Construction

	injecting liquid crystal between the array substrate and the color filter substrate	pillars of a color filter	Claim Terms
	L	L	Des.
			AUO Construction
Intrinsic Support 7:62-8:39	providing liquid crystal through an injection hole between the sealed array and color filter substrates	patterned structures that protrude toward the pixel array, to act as a spacer, and are made of color filter material Intrinsic Support Abstract; 2:13-19; 3:66-4:21; 4:21-30; 4:31-49; 4:51-64; 4:65-5:06; 5:07-10; 5:57-6:05; 7:09-14; 7:32-43; 7:44-60; 7:62-8:39; 8:40-45; Figures 1-11; JP H08-262484 at paragraphs [0017]-[0032]; App 08/615,012, 7/7/1997 Amendment, pages 2-7.	LGD Construction

K-1

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L conductive patterns on the substrate that electrically connect the plurality of wiring t	connection pads
circuits located external to the substrate	
Des. Agreed Constructions	Claim Terms

sputed Construction

Claim Terms	Des.	AUO Construction	LGD Construction
a layer of an insulating substrate,	T	plain meaning	
having an area		Intrinsic Support	-
		'629 Specification	-
		Abstract; 1:12-20, esp. 14-20; 1:32-46, esp. 39-44; 2:13-24, esp. 17-21; 3:11-28, esp.	
		11-14; 3:29-47, esp. 29-37; 4:33-41; 6:17-34, esp. 23-27, 30-34; claims 1, 9; Figures 1, 5a-5c, 11, 12a-12b.	
		'629 Prosecution History	
		May 29, 2003 Office Action, esp. at 2.	
		U.S. Patent No. 5,285,301 (Shirahashi et al.) 3:37-44, esp. 39-40.	
		Incorporated Disputed Terms	
		Included is the intrinsic support for the disputed term: "area".	
area	A	a specified region	
		Intrinsic Support	
		'629 Specification	
		1:61-67, esp. 63-66; 2:51-62, esp. 51-54; 3:11-28, esp. 18-19; 3:29-47, esp. 38-39; 5:20 42 esp. 20 33 38 42: 5:43 53: 5:54	

	Incorporated Disputed Terms		
	U.S. Patent No. 5,285,301 (Shirahashi et al.) 6:10-20.		
	May 29, 2003 Office Action, esp. at 2.		
	'629 Prosecution History		
	esp. 35-40; claims 1, 2, 10; Figures 1, 3, 4, 5a-5c, 11, 12a-12b; Japanese Laid Open H10-90706, esp. ¶ 0009; Japanese Laid Open H10-240150, esp. ¶¶ 0002, 0003, 0013.	TO THE PERSON OF	
	4:33-41, esp. 38-41; 5:29-42, esp. 29-33, 38-42; 6:17-34, esp. 23-27, 30-34; 6:35-47,		
	1:32-46, esp. 39-44; 2:13-24, esp. 17-21; 3:11-28, esp. 13-24; 3:29-47, esp. 32-47;		
	Abstract; 1:12-20, esp. 14-20; 1:28-30;		
	'629 Specification		
	Intrinsic Support		
	two or more conductive paths disposed on the insulating substrate	T	a plurality of wiring arranged on the insulating substrate
-	U.S. Patent No. 5,285,301 (Shirahashi et al.) 11:11-14; 11:54-58.		
	May 29, 2003 Office Action, esp. at 2.		
	'629 Prosecution History		
	Laid Open No. H10-90706, esp. at ¶¶ 0003, 0015, 0017, 0020, 0023, 0024, and Figure 5.		
	60, esp. 54-57; 5:61-6:6, esp. 5:61-6:1, 6:4-6; 6:35-47, esp. 35-40; claims 1, 9; Japanese		
LGD Construction	AUO Construction	Des.	Claim Terms

								•		
dummy patterns comprising at least about 30% of the area of the insulating substrate, the dummy conductive patterns situated between the connection pads and the pixel electrodes								dummy conductive patterns		Claim Terms
T								A		Des.
dummy conductive patterns cover at least 30% of the region specified by where the dummy conductive patterns are formed; the dummy conductive patterns are situated between the connection pads and the pixel electrodes	U.S. Patent No. 5,285,301 (Shirahashi et al.) 6:10-18; 13:30-61, esp. 45-61; claims 3, 4; Figures 1, 14, 15.	U.S. Patent No. 6,163,356 (Song et al.) 7:31-63; 8:27-40; 8:41-67.	May 29, 2003 Office Action, esp. at 2.	'629 Prosecution History	Abstract; 1:12-20, esp. 14-20; 1:32-46, esp. 39-44; 1:46-59, esp. 49-54; 2:13-24, esp. 17-21; 3:11-28, esp. 17-22; 3:29-47, esp. 35-41; 3:66-4:2; 5:29-42, esp. 29-33, 38-42; 5:43-53; 6:14-17; 6:37-38; 6:52-55; claims 1, 9; Figures 2-4, 5a-5c.	'629 Specification	Intrinsic Support	a metal pattern that does not conduct signals or current used in the operation of the display	Included is the intrinsic support for the disputed term: "a layer of an insulating substrate, having an area".	AUO Construction
										LGD Construction

icat icat 44-20 11; 35-2 25-6 (8 6 (8 6 (8 6 (8 6 (8 6 (8 6 (8 6 (8	'629 Specification		Included is the intrinsic support for disputed terms: "dummy conductive patterns," "a layer of an insulating substrate, having an area," "area," "pixel electrodes". A an electrode A an electrode for applying a driving voltage	U.S. Patent No. 6,163,356 (Song et al.) 1:55-64; 7:31-63; 8:27-40; 8:41-67. U.S. Patent No. 5,285,301 (Shirahashi et al.) 6:10-18; 13:30-61, esp. 45-61; claims 3, 4; Figures 1, 14, 15.	%29 Prosecution History May 29, 2003 Office Action, esp. at 2-3.	Abstract; 1:12-20, esp. 14-20; 1:32-46, esp. 39-44; 2:13-24, esp. 17-21; 3:11-28, esp. 17-22; 3:29-47, esp. 35-41; 3:66-4:2; 5:29-42, esp. 29-33, 38-42; 5:43-53; 5:54-60, esp. 54-57; 5:61-6:6, esp. 5:61-6:1, 6:4-6; 6:7-17, esp. 9-12, 14-17; 6:17-34, esp. 23-27, 30-34; 6:35-47, esp. 35-40; claims 1, 9; Figures 2-4, 5a-5c.	intrinsic Support 629 Specification
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K-2

	connection pads	Claim Terms
	Г	Des.
circuits located external to the substrate	conductive patterns on the substrate that electrically connect the plurality of wiring to	Agreed Constructions

Disputed Constructions

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	a plurality of wiring arranged on the insulating substrate			area		having an area	a layer of an insulating substrate,	Claim Terms
	T	·		Α			L	Des.
								AUO Construction
Intrinsic Support 4:39-42.	portions of the layer that convey voltages or signals from the connection pads to the thin-film transistors in the pixel array	(see above)	Or	Indefinite	Intrinsic Support 1:63-67; 2:9-12; 2:58-63; 2:67- 3:6; 4:39-42; 5:11-13; 5:34-38; 5:55-61; 6:38-48; 6:64-67; 7:5-12; 7:50-57; 8:47; Figs. 8, 9 and 10; App 10/068,500, 5/29/2003, Office Action.	substrate, such as glass, that covers part of	material deposited and patterned on a	LGD Construction

Claim Terms	Des.	AUO Construction	LGD Construction
dummy conductive patterns	A		portions of the layer that do not receive or convey voltages or signals
			Intrinsic Support 3:21-23; 3:40-42; 5:11-13; 5:38-54; 6:35-38; 6:52-55; Figs. 2-4.
dummy patterns comprising at least about 30% of the area of the insulating substrate, the dummy conductive patterns situated between the connection pads and the rivel electroder.	L		approximately 30% or more of the area of the layer is made of dummy conductive patterns that are located between the connection pads and an outer edge of the pixel electrodes in the pixel array
the bryet executones			Intrinsic Support 1:61-67; 3:3-6; 3:17-20; 3:35-40; 5:34-38; 5:46-48; 5:55-60; 5:62-6:17; 6:30-34; 6:38-48; 7:8-18; Figs. 2-4; App 10/068,500, 5/29/2003, Office Action.
pixel electrode	A		patterns of transparent electrically conductive material that stores charge to drive the liquid crystal material within an individual element of the liquid crystal display device
			Intrinsic Support 1:12-21; 4:45-51; 6:48-52; Figs 2-5.
each wiring			Indefinite

L-1

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a pillar formed between the first and second substrates to set or maintain the size of the gap between substrates	A	a spacer
maintains a uniform spacing within a manufacturing tolerance between the two substrates in the display region	L	regulates a cell gap between the first and the second substrates
Agreed Constructions	Des.	Claim Terms

Disputed Constructions

Claim Terms	Des.	AUO Construction LGD Construction
at least one of the group consisting of	T	at least one of the characteristics listed as (a) through (e)
		Intrinsic Support '944 Specification
		2:51-54; 6:47-65; claim 4.
elastic coefficient	A	a value that defines the elasticity of the resin, that is, the resin's ability to change shape or volume in response to force, and then return to its original shape or volume.
		Intrinsic Support '944 Specification
		2:58-3:2; 6:15-24; claim 4.
		7944 Prosecution History January 16, 2002 Office Action, esp. at 5;
		January 28, 2003 Office Action, esp. at 3-5.
		U.S. Patent No. 6,299,949 (Shioda et al.) in

The state of the s	The length of one side of the upper spacer	L	The length of one side of the
	Intrinsic Support '944 Specification 4:18-51; 7:27-30; claims 1 and 4. '944 Prosecution History May 16, 2002 Response, esp. at 21-22; November 13, 2002 Response, esp. at 22-23; January 28, 2003 Office Action, esp. at 8-9; June 27, 2003 Office Action, esp. at 10-11; November 28, 2003 Response, esp. at 10-11; November 28, 2003 Response, esp. at 7-8. U.S. Patent No. 6,299,949 (Shioda et al.) in general, esp.: 14:29-15:16.		
	Defined by the formula in the claim	T	Hardness value of plastic deformation (HV)
	Intrinsic Support '944 Specification 3:54-4:17; 7:27-30; claims 1 and 4. '944 Prosecution History May 16, 2002 Response, esp. at 21-22; November 13, 2002 Response, esp. at 22-23; January 28, 2003 Office Action, esp. at 8-9; June 27, 2003 Office Action, esp. at 10-11; November 28, 2003 Response, esp. at 17-8. U.S. Patent No. 6,299,949 (Shioda et al.) in general, esp.: 14:29-15:16.		
	Defined by the formula in the claim	T	Dynamic hardness value (DH)
LGD Construction	AUO Construction general, esp.: 3:23-26; 13:1-15; 13:59-67.	Des.	Claim Terms

Claim Terms	Des. AUO Construction	LGD Construction
upper spacer surface	surface, measured using a tangent line parallel to the substrate, at 90% of the height	
	Intrinsic Support '944 Specification 5:49-6:14, and Figs. 2A and 2B; claims 2 and 4.	

L-2

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a pillar formed between the first and second substrates to set or maintain the size of the gap between substrates	A	a spacer
in the display region		first and the second substrates
maintains a uniform spacing within a manufacturing tolerance between the two substrates	L	regulates a cell gap between the
Agreed Constructions	Des.	Claim Terms

Disputed Constructions

Indefinite		A	elastic coefficient
Intrinsic Support 3:55-4:54; 4:56-5:30; 6:47-52; 8:09-20.			
means one or more of the limitations selected from (a) to (e)			
Or			COMPTONING OF
Indefinite		J	at least one of the group
LGD Construction	s. AUO Construction	Des.	Claim Terms

Hardness value of plastic deformation (HV)		Claim Terms Dynamic hardness value (DH)
		Des. AUO Construction
Intrinsic Support App 09/558,819, 1/16,2002 Office Action, pages 2-3; App 09/558,819, 5/16/2002 Amendment, pages 21-25; App 09/558,819, 8/13/2002 Office Action, pages 2, 5; App 09/558,819, 11/13/2002 Amendment, pages 22-27; App 09/558,819, 1/28/2003 Office Action, pages 2, 8-11; App 09/558,819, 6/27/2003 Office Action, pages 2, 3, 11-13; App 09/558,819, 11/28/2003 Amendment, pages 7-8.	Intrinsic Support App 09/558,819, 1/16,2002 Office Action, pages 2-3; App 09/558,819, 5/16/2002 Amendment, pages 21-25; App 09/558,819, 8/13/2002 Office Action, pages 2, 5; App 09/558,819, 11/13/2002 Amendment, pages 22-27; App 09/558,819, 1/28/2003 Office Action, pages 2, 8-11; App 09/558,819, 6/27/2003 Office Action, pages 2, 3, 11-13; App 09/558,819, 11/28/2003 Amendment, pages 7-8.	LGD Construction Indefinite

	,	upper spacer surface	Claim Terms Des
			. AUO Construction
Intrinsic Support: 5:51-6:14; Figures 2A, 2B; JP 2000321580A at paragraphs [0009]-[0041]; App 09/558,819, 1/16,2002 Office Action, pages 2-3; App 09/558,819, 5/16/2002 Amendment, pages 21-25; App 09/558,819, 8/13/2002 Office Action, pages 2, 5; App 09/558,819, 11/13/2002 Amendment, pages 22-27; App 09/558,819, 1/28/2003 Office Action, pages 2, 8-11; App 09/558,819, 6/27/2003 Office Action, pages 2, 3, 11-13.	The distance between two specific points on opposite sides of the spacer (The location of the two points are determined by where a line that runs parallel to the one side and parallel to the substrate intersects the opposite sides. The location of the parallel line is determined by multiplying the height of the spacer by a constant. The height of the spacer is determined by the shortest perpendicular distance measured from the bottom of the spacer to a line tangent to the top of the spacer and parallel to the substrate)	Or	LGD Construction

M-1

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	'160 Prosecution History		
	Abstract; 3:26-39, esp. 26-30; 5:30-38; claims 8, 12; Figure 1.		
	'160 Specification		
	Intrinsic Support		logic
	memory for storing a previous level of light intensity of a video signal input through input logic	L	a storage for storing the previous brightness level of the video signal input through said input
	7160 Specification 5:6-14, esp. 6-7, 12-14; 6:51-65, esp. 53-60; 7:17-30, esp. 21-25; claims 1, 3, 4, 6; Figure 1. 7160 Prosecution History December 12, 2002 Office Action, esp. at 2-3; March 12, 2003 Amendment, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-3, 7-8, 10, 12; March 19, 2004 Notice of Allowability, esp. at 2.		
	Intrinsic Support		
	a signal comprising video information	L	video signal
LGD Construction	AUO Construction	Des.	Claim Terms

determinator for determining an output brightness level		Claim Terms
L logic, such as a circoutput brightness volume intrinsic Support 160 S Abstract; 3:26-39, 4:61-67; 6:37-40; 6 claims 4; Figure 1. 160 Pros December 12, 2003 5; March 12, 2003 5; March 12, 2003 May 19, 2003 Offin December 22, 2003 9, 12; March 19, 20 Allowability, esp. 3	December 4; March 1 May 19, 2) December 8, 10-13; N Allowabili U.S. Paten Abstract; 3 1, 3, 4. Incuded is terms: "br signal"	Des.
logic, such as a circuitry, for determining an output brightness value 1160 Specification 160 Specification Abstract; 3:26-39, esp. 30-34; 4:61-5:6, esp. 4:61-67; 6:37-40; 6:66-7:16, esp. 6:66-7:5; claims 4; Figure 1. 160 Prosecution History December 12, 2002 Office Action, esp. at 2-5; March 12, 2003 Amendment, esp. at 1-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-9, 12; March 19, 2004 Notice of Allowability, esp. at 2.	December 12, 2002 Office Action, esp. at 2-4; March 12, 2003 Amendment, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-8, 10-13; March 19, 2004 Notice of Allowability, esp. at 2. U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:26-32; 3:39-48; 3:49-55; claims 1, 3, 4. Incorporated Disputed Terms Included is the intrinsic support for disputed terms: "brightness level" and "video signal"	AUO Construction
-		LGD Construction

	U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:26-32; 3:33-38; 3:39-48; 3:49-		
	5; March 12, 2003 Amendment, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-8, 10-12; March 19, 2004 Notice of Allowability, esp. at 2.		
	7160 Prosecution History December 12, 2002 Office Action, esp. at 2-		
	4:7, esp. 3:60-64; 4:42-60; 6:4-6; 8:20-34, esp. 30-34; 8:35-40, esp. 38-40; 10:57-67, esp. 57-62; Figures 2, 4-8, 11.		
-	2:26-39, esp. 32-37; 2:50-3:2, esp. 2:63-3:2; 3:15-18; 3:35-37; 3:40-59, esp. 56-59; 3:60-		
	'160 Specification		
	Intrinsic Support		
	level of intensity of light	Α	brightness level
	"ideal quantity of light in a stationary state," time integration quantity of a brightness level," "substantially equal"		
-	ideal quantity of light in a stationary state with respect to the next brightness level,"		
	make a time integration quantity of a		
	brightness level of the video signal input to said inpult logic," "video signal," "so as to	•••••	
	Included is the intrinsic support for disputed terms: "brightness level," "the next		
	Incor		
LGD Construction	s. AUO Construction	Des.	Claim Terms

so as to make a time integration L so a	Incl disp		U.S Abs 22;	Dec 5; N Ma: Dec 8, 1		Sur Des 6:1	(next video signal input to said Intri) L	U.S esp	U.S esp	55; 19,	Claim Terms Des.
so as to make a time integration quantity of	Included is the intrinsic support for the disputed term: "video signal"	Incorporated Disputed Terms	U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:26-32; 3:39-48; 3:49-55; 4:14- 22; 4:23-36; 7:4-22; 8:23-37; claims 1, 3, 4.	December 12, 2002 Office Action, esp. at 2-5; March 12, 2003 Amendment, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-8, 10-13; March 19, 2004 Notice of Allowability, esp. at 2.	'160 Prosecution History	Summary of the Invention and Detailed Description of the Invention, generally; 6:11-27, esp. 11-17; 6:37-40; 6:66-7:17, esp. 7:13-15; claim 12; Figures 7, 9, 10.	7160 Specification	Intrinsic Support	plain meaning	U.S. Patent No. 5,956,014 (Kuriyama et al.), esp. 1:55-62.	U.S. Patent No. 6,326,938 (Ishida et al.), esp. 1:33-50, esp. 40-42.	55; 3:56-61; 4:7-13; 4:14-22; 4:23-36; 9:7- 19, esp. 13-18; claims 1-5.	AUO Construction
				-			-	-	1				LGD Construction

	ideal quantity of light in a A stationary state							Claim Terms Quantity of a brightness change substantially equal to an ideal quantity of light in a stationary state with respect to the next brightness level
Intrinsic Support	the quantity of light emitted by a pixel during one time increment when the pixel is in a non-changing state	Included is the intrinsic support for disputed terms: "time integration quantity of a brightness level," "substantially equal," "ideal quantity of light in a stationary state," "the next brightness level of the next video signal input to said input logic"	Incorporated Disputed Terms	December 12, 2002 Office Action, esp. at 2-5; March 12, 2003 Amendment, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-13; March 19, 2004 Notice of Allowability, esp. at 2.	'160 Prosecution History	7160 Specification 8:35-40; 9:8-25, esp. 8-23; claims 4, 5, 12; Figures 2, 4-8, 11.	Intrinsic Support	a brightness change substantially equal to an ideal quantity of light in a stationary state with respect to the next brightness level; the next brightness level is the brightness level that immediately follows the previous brightness level.
				-				LGD Construction

Claim Terms	Des.	AUO Construction	LGD Construction
		7160 Specification	
		4:42-60, esp. 42-47; 6:11-27, esp. 14-19; 8:35-40; claims 4, 12; Figures 2, 4-6, 8, 11.	
		7160 Prosecution History	-
		December 12, 2002 Office Action, esp. at 2-3; March 12, 2003 Amendment, esp. at 2-3;	
		May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-	-
		4, 7-8, 12; March 19, 2004 Notice of Allowability, esp. at 2.	
image displaying liquid crystal cell	Т	an image display element with a liquid crystal	
		Intrinsic Support Intrinsic Support	
		'160 Specification	
		1:39-45, esp. 39-41; 3:40-59, esp. 40-44; 7:17-30, esp. 25-28; Figure 1.	-
		7160 Prosecution History	
		December 12, 2002 Office Action, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 9-12.	
first brightness information for an input pixel	П	first brightness information for an input pixel, where "brightness information" is a brightness level	
		Intrinsic Support	
		'160 Specification	
		Summary of the Invention and Detailed	

May 19, 2003 Office Action, esp. at 2-6;	7160 Prosecution History	1:39-45, esp. 43-45; 2:44-49, esp. 44-47; 2:50-3:2, esp. 50-54; 3:40-59, esp. 40-50; 3:60-4:7, esp. 3:64-4:4; 4:42-60, esp. 42-47; 5:51-65, esp. 54-65; 5:67-6:3, claims 4, 7, 9, 10.	7160 Specification	pixel L abbreviation for "picture element"	Included is the intrinsic support for disputed terms: "pixel" and "brightness level".	Incorporated Disputed Terms	U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:26-32; 3:39-48; 3:49-55; 4:14- 22; 4:23-36; 7:4-22; 8:23-37; claims 1, 3, 4.	4; March 12, 2003, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-9, 12, 13; March 19, 2004 Notice of Allowability, esp. at 2.	December 12, 2002 Office Action, esp. at 2-	13; Figures 7, 9, 10.	Abstract; 3:27-39, esp. 27-29; 4:61-5:6, esp. 4:61-64; 6:66-7:16, esp. 7:13-15; claims 1,	Description of the Important account to

			frame buffer				Claim Terms
							Des.
December 12, 2002 Office Action, esp. at 2-5; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-8, 10-13; March 19, 2004 Notice of Allowability, esp. at 2. U.S. Patent No. 5,347,294 (Usui et al.) 4:64-67, esp. 64-65; 9:28-32, esp. 28-31; 12:53-57, esp. 53-55.	5:30-38, esp. 30-36; 6:11-27; 6:66-7:16, esp. 7:5-10; claims 8, 12, 13; Figure 1. '160 Prosecution History	7160 Specification	storage for video information contained in a frame	U.S. Patent No. 6,064,359 (Lin et al.) 1:12-18, esp. 12-15; 1:21-34, esp. 28-31; 1:35-58, esp. 46-49; 4:60-5:4, esp. 1-4.	U.S. Patent No. 5,483,634 (Hasegawa) 4:23-57, esp. 30-36.	U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 2:23-33, esp. 23-27; 3:26-32; 3:39-48; 3:49-55; 4:14-22; 4:23-36; 7:4-22; 7:46-60, esp. 56-60; 8:23-37, esp. 23-25; claims 1, 3, 4; Figure 6.	AUO Construction December 22, 2003 Appeal Brief, esp. at 2-7, 10-12.
		-					LGD Construction

an offset for making the time				-					second brightness information for the next input pixel			Claim Terms
L									T			Des.
a modification to the second brightness	Included is the intrinsic support for disputed terms: "pixel" and "brightness level".	Incorporated Disputed Terms	U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:26-32; 3:39-48; 3:49-55; 4:14- 22; 4:23-36; 7:4-22; 8:23-37; claims 1, 3, 4.	December 12, 2002 Office Action, esp. at 2-4; March 12, 2003, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-9, 12, 13; March 19, 2004 Notice of Allowability, esp. at 2.	7160 Prosecution History	Summary of the Invention and Detailed Description of the Invention, generally; Abstract; 3:26-39, esp. 30-37; 4:61-5:6, esp. 4:61-67; 6:66-7:16, esp. 7:13-15; claims 2, 12; Figures 7, 9, 10.	'160 Specification	Intrinsic Support	a level of light intensity for a next input pixel	U.S. Patent No. 5,483,634 (Hasegawa) 4:26-28, esp. 26-27.	U.S. Patent No. 6,333,727 (Mizumaki) 3:26-32; 5:10-18, esp. 15-18; 6:8-11.	AUO Construction
							-					LGD Construction

	time integration quantity of a brightness level						(stationary state to said second brightness information	which is the brightness in a	brightness change substantially	integration quantity of a	Claim Terms Des.
Intrinsic Support	a quantity of light equal to the actual brightness level output through a liquid crystal, summed over a time period including the rise and fall response time of the liquid crystal	Included is the intrinsic support for disputed terms: "time integration quantity of a brightness level," "substantially equal," "ideal light quantity which is the brightness in a stationary state," "brightness level".	Incorporated Disputed Terms	December 12, 2002 Office Action, esp. at 2-5; March 12, 2003, esp. at 2-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-13; March 19, 2004 Notice of Allowability, esp. at 2.	'160 Prosecution History	2:4-12, esp. 4-10; 5:15-21; 5:22-29, esp. 27-29; 9:1-7; 9:8-24, esp. 8-23; 9:40-63; claims 4, 5; Figures 2, 7-8.	'160 Specification	Intrinsic Support	which is the brightness in a stationary state	quantity of the brightness change	information for making the time integration	AUO Construction
			-									LGD Construction

at 2- ber esp. esp. el is at 2- 1	December 12, 2002 Office Action, esp. at 2-5; March 12, 2003, esp. at 2-6; December 22, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 3-9, 12; March 19, 2004 Notice of Allowability, esp. at 2. Included is the intrinsic support for the disputed term: "brightness level". A the quantity of light emitted by a pixel during one time increment when the pixel is in a non-changing state Intrinsic Support '160 Specification 4:42-60, esp. 42-47; 6:11-27, esp. 11-19; 8:35-40; 10:49-56, esp. 49-52; claims 4, 12; Figures 2, 4-6, 8, 11. '160 Prosecution History December 12, 2003, esp. at 2-6: December 2, 2003 Office Action, esp. at 2-6: December 2, 2003 office Action, esp. at 2-6: December 2.	A	ideal light quantity which is the brightness in a stationary state
	7160 Prosecution History		
-6,	4:42-60, esp. 53-56; 8:20-34, esp. 30-34; 11:1-9, esp. 1-4; claims 5, 11; Figures 4-6, 11.		
	'160 Specification		

						*				
						substantially equal				Claim Terms
					n				1000	Des.
U.S. Patent No. 6,333,727 (Mizumaki) Abstract; 3:33-38; 3:56-61; 4:7-13; 4:23-36; 7:4-22; 8:38-57; 9:7-19; claims 1-5.	December 12, 2002 Office Action, esp. at 2-3; March 12, 2003, esp. at 1-3; May 19, 2003 Office Action, esp. at 2-6; December 22, 2003 Appeal Brief, esp. at 2-10, 12; March 19, 2004 Notice of Allowability, esp. at 2.	'160 Prosecution History	4:42-60, esp. 56-58; 8:41-61, esp. 45-47; 9:26-39, esp. 32-35; claim 4; Figures 4-6, 11.	'160 Specification	Intrinsic Support	a level that is not completely the same but can be accepted as a substantially equal level	Included is the intrinsic support for the disputed term: "brightness level".	Incorporated Disputed Terms	March 19, 2004 Notice of Allowability, esp. at 2.	AUO Construction
	-					1			TOD COMPT REPORT	I.GD Construction

M-2

a table for storing	Claim Terms
I	Des.
logic operable to hold data in table form	Agreed Constructions

Disputed Constructions

a storage for storing the previous brightness level of the video signal input through said input logic	video signal	Claim Terms 1
L	L	Des.
		AUO Construction
memory that temporarily holds the brightness level of the video signal received from the host through input logic for the previous time increment Intrinsic Support 4:47-50; 5:30-38; 6:11-26; 6:51-7:30; 9:25-39; 9:40-10:14; 10:49-66; Figs. 1, 7; JP 2001-202051A at paragraphs [0010]-[0023].	a signal carrying a brightness level from a predetermined range Intrinsic Support 4:47-50; 5:07-15; 5:54-65; 6:27-36; 6:51-7:30; 7:31-45; 10:26-40; 10:57-62; Figs. 1, 2, 8.	LGD Construction

	the next brightness level of the next video signal input to said input logic		brightness level	output brightness level
	el of the L		Α	nining an
2 3 4 1	T t	1 3 2 1	tto	
Intrinsic Support 4:47-50; 5:30-38; 6:11-26; 6:51-7:30; 9:25-39; 9:40-10:14; 10:49-66; Figures 1, 7; JP 2001-202051A at paragraphs [0010]-[0023].	the brightness level of the video signal received from the host input to the input logic for the next time increment	Intrinsic Support 4:47-50; 5:54-65; 6:51-7:30; 7:31-45; 9:25-39; 9:40-10:14; 10:26-40; 10:57-62; Figures 1, 2, 7, 8.	gray scale value or luminance value	circuit or logic that determines the output brightness level by applying an offset to the next brightness level that is predetermined based on a difference in quantity of light between the actual and ideal response characteristics of the liquid crystal cell Intrinsic Support 1:51-2:12; 4:42-56; 4:61-67; 5:15-30; 5:30-38; 5:51-65; 6:11-26; 6:37-40; 6:51-7:30; 7:31-45; 8:41-61; 9:01-39; 10:26-40; 10:49-66; Figs. 1, 2, 5A, 5B, 6, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023]; App 09/760,131, 12/22/2003, Appeal Brief, pages 2-13.

	so as to make a time integration quantity of a brightness change substantially equal to an ideal quantity of light in a stationary state with respect to the next brightness level
	L ACO CONSTRUCTION
Intrinsic Support 1:39-43; 1:51-2:12; 4:42-56; 4:61-67; 5:15-30; 5:16-22; 5:66-6:06; 6:11-26; 6:51-7:30; 7:31-45; 8:35-40; 8:41-61; 9:01-39; 10:26-40; 10:49-66; Figures 1, 2, 4, 5A, 5B, 6, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023]; App 09/760,131, 12/22/2003, Appeal Brief, pages 2-13.	so that the quantity of light based on the actual response characteristic of the liquid crystal cell is substantially equal to the quantity of light based on the ideal response characteristic of the liquid crystal cell when the liquid crystal cell is provided with the next brightness level during the next time increment and the previous brightness level before and after the next time increment

	image displaying liquid crystal		ideal quantity of light in a stationary state	Claim Terms
	Г		A	Des.
				AUO Construction
characteristic at the maximum brightness change given the predetermined range of brightness levels Intrinsic Support 2:25-3:02; 5:40-45; 6:51-7:30; 7:31-45; 7:66-8:25; 10:26-40; Figures 1, 2, 3, 7, 8.	an image display element with a liquid	Intrinsic Support 1:39-43; 4:42-56; 5:66-6:06; 7:31-45; 8:35-40; 8:41-61; 9:01-39; 10:26-40; 10:49-66; Figures 2, 4, 5A, 5B, 6, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023].	quantity of light based on the ideal response characteristic of the liquid crystal cell when the liquid crystal cell is provided with the next brightness level during the next time increment and the previous brightness level before and after the next time increment	LGD Construction

	frame buffer L		pixel L		input pixel	
						s. AUO Construction
Intrinsic Support 1:43-45; 5:31-33; 6:11-26; 6:51-7:30; 9:25-39; 9:40-10:14; 10:49-66; Figures 1, 7.	a memory circuit or device that temporarily holds brightness levels for all pixels that form one complete picture on the liquid crystal display	Intrinsic Support 2:25-3:02; 5:40-45; 6:51-7:30; 7:31-45; 7:66-8:25; 10:26-40; Figures 1, 2, 3, 7, 8.	an image display element with a liquid crystal that has the ideal response characteristic at the maximum brightness change	Intrinsic Support 4:47-50; 5:07-15; 5:30-38; 5:54-65; 6:11- 26; 6:27-36; 6:51-7:30; 7:31-45; 9:25-39; 9:40-10:14; 10:26-40; 10:49-66; Figures 1, 2, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023].	the brightness level of an input signal for a pixel	LGD Construction

	an offset for making the time integration quantity of a brightness change substantially equal to an ideal light quantity which is the brightness in a stationary state to said second brightness information	Claim Terms Des. second brightness information for L the next input pixel	
		AUO Construction	
Intrinsic Support 1:39-43; 1:51-2:12; 4:42-56; 4:61-67; 5:15-30; 5:30-38; 5:51-65; 5:66-6:06; 6:11-26; 6:37-40; 6:51-7:30; 7:31-45; 8:35-40; 8:41-61; 9:01-39; 10:26-40; 10:49-66; Figures 1, 2, 4, 5A, 5B, 6, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023]; App 09/760,131, 12/22/2003, Appeal Brief, pages 2-13.	a value predetermined based on difference in quantity of light between the actual and ideal response characteristics of the pixel so that the quantity of light based on the actual response characteristic of the pixel to be substantially equal to the quantity of light based on the ideal response characteristic of the pixel when the pixel is provided with the second brightness level during the next frame and the first brightness level before and after the next frame	the brightness level for the next frame of the input signal for the pixel Intrinsic Support 4:47-50; 5:30-38; 6:11-26; 6:51-7:30; 9:25-39; 9:40-10:14; 10:49-66; Figures 1, 7; JP 2001-202051A at paragraphs [0010]-[0023].	

ideal light quantity which is the brightness in a stationary state			brightness change	Claim Terms time integration quantity of a
A				Des.
				AUO Construction
(see above term)	Intrinsic Support 1:39-43; 4:42-56; 4:61-5:06; 5:16-22; 5:66-6:06; 7:31-45; 8:41-61; 9:01-39; 10:26-40; 10:49-66; Figures 2, 5A, 5B, 6, 7, 8; JP 2001-202051A at paragraphs [0010]-[0023].	quantity of light based on the actual response characteristic of the liquid crystal cell when the liquid crystal cell is provided with the next brightness level during the next time increment and the previous brightness level before and after the next time increment	Or	LGD Construction Indefinite

			Claim Terms substantially equal
			Des.
			AUO Construction
Intrinsic Support 4:56-60.	A level which is not completely the same but can be accepted as a substantially equivalent level, and includes a level which is closer to an ideal quantity of light than no preventive measures are taken.	Or	LGD Construction Indefinite

N-1

Disputed Constructions

on outer surfaces of said second sidewall a plurality of second hooks are formed to protrude outwardly as said frame is mounted onto said bezel	Des. L	on outer surfaces of said second sidewall a plurality of second protruding structures, intended to be inserted into a hole for the purpose of fastening one element to another, are formed to protrude outwardly Intrinsic Support Same as for the term "hooks." during the process of mounting the frame onto the bezel	LGD Construction
as said frame is mounted onto said bezel	L	during the process of mounting the frame onto the bezel	
		Intrinsic Support	
		781 Specification 3:22-42, esp. 3:34-42.	
		781 Prosecution History January 28, 2005 Amendment, esp. at 8, amendment to Claim 1 ("Listing of Current Claims")	

Claim Terms	Des.	AUO Construction	LGD Construction
bezel	A	A frame, typically made of metal	
		Intrinsic Support	
		781 Specification 1:30-43, esp. 1:33 and Figure 1, element 110; 2:33-50, esp. 2:38-39; 3:14-21, esp. 3:14-18 and Figure 4; 4:7-22, esp. 4:7-9.	-
		781 Prosecution History U.S. Patent No.: 6,170,956 (Rumsey et al.): 5:58-65, esp. 5:61 and Figure 2, element 12; 10:34-11:10, esp. 11:6 and Figure 17, element 117; 12:15-44, esp. 12:15-17 and Figures 17 and 18, element 117.	
		U.S. Patent No.: 6,386,722 (Okumura): 1:20-34, esp. 1:26-27; 3:53-65, esp. 3:53-55, 3:59-60, and Figure 1, element 40.	<u>-</u>
on outside surfaces of said first edge first hooks are formed to protrude outwardly	L	on outside surfaces of said first edge first protruding structures, intended to be inserted into a hole for the purpose of fastening one element to another, are formed to protrude outwardly	
		Intrinsic Support	
		Same as for the term "hooks."	

	Same as for the term "hooks."		
	Intrinsic Support		
	purpose of fastening one element to another, are formed to protrude outwardly		,
	on outer surfaces of said first edge a plurality of second protruding structures, intended to be inserted into a hole for the	۲	on outer surfaces of said first eage a plurality of second hooks are formed to protrude outwardly
		-	
	Same as for the term "hooks."		
	Intrinsic Support		
	purpose of fastening one element to another, are formed to protrude outwardly		
	plurality of first protruding structures, intended to be inserted into a hole for the	t	sidewall a plurality of first hooks are formed to protrude outwardly
	on outer surfaces of said second sidewall a	-	on outer surfaces of said second
	Same as for the term "hooks."		
	Intrinsic Support		
	fastening one element to another, are formed to protrude outwardly		
	inserted into a hole for the purpose of		protrude outwardly
	on outside surfaces of said fourth edge second protruding structures, intended to be	Ļ	on outside surfaces of said fourth edge second hooks are formed to
LGD Construction		Des.	Claim Jerms

January 28, 2005 Amendment, esp. at 8, amendment to Claim 1 ("Listing of Current Claims")	 fastening said frame and said 3:22-42, esp. 3:34-42.	engaged in said second holes for '781 Specification	first hooks are inserted and	of said second sidewall, and said <u>Intrinsic Support</u>	is disposed onto outside surfaces	simultaneously said second edge L Plain meaning	Claim Terms Des. AUO Construction
			-				LGD Construction

N-2

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Disputed Constructions

hooks		Claim Terms on outer surfaces of said first edge a plurality of first hooks are formed to protrude outwardly
A		d first edge L s are wardly
		AUO Construction
(see above term)	Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/27/2005 Notice of Allowability, pages 2-3.	LGD Construction two or more protrusions that are part of the frame and that extend outwardly from the first edge for fastening the frame to the bezel

		,	·	
Said Dezei	as said frame is mounted onto		on outer surfaces of said second sidewall a plurality of second hooks are formed to protrude outwardly	Claim Terms
	Ţ		L	Des.
				AUO Construction
Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/8/2005 Notice of Allowability, pages 2-3.	at the same time when the frame and bezel	Intrinsic Support 1:44-2:25, 28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/27/2005 Notice of Allowability, pages 2-3.	two or more protrusions that are part of the bezel and that extend outwardly from the second sidewall for fastening the bezel to the frame	LGD Construction

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	on outside surfaces of said first edge first hooks are formed to protrude outwardly		bezel Claim Terms
	L		Des.
			AUO Construction
Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/27/2005 Notice of Allowability, pages 2-3.	two or more protrusions that are part of the frame and that extend outwardly from the first edge for fastening the frame to the bezel	Intrinsic Support 1:30-43; 1:66-2:7; 3:14-31; 4:7-9; Figs. 1, 2, 3, 4 and 5.	LGD Construction the outermost back cover for the backlight module

protrude outwardly	on outside surfaces of said fourth edge second hooks are formed to	
	L	Des.
		AUO Construction
Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/8/2005 Notice of Allowability, pages 2-3.	frame and that extend outwardly from the	LGD Construction

	on outer surfaces of said second sidewall a plurality of first hooks are formed to protrude outwardly	Claim Terms 1
	Г	Des.
	,	AUO Construction
Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/27/2005 Notice of Allowability, pages 2-3.	two or more protrusions that are part of the bezel and that extend outwardly from the second sidewall for fastening the bezel to the frame	LGD Construction

simultaneously said second edge is disposed onto outside surfaces of said second sidewall, and said first hooks are inserted and engaged in said second holes for fastening said frame and said bezel		on outer surfaces of said first edge L a plurality of second hooks are formed to protrude outwardly
		AUO Construction
the first hooks are inserted and engaged with the second holes at the same time the second hooks are inserted and engaged with the first holes to join the frame and bezel Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5.	Intrinsic Support 1:44-2:25; 2:28-32; 3:4-21, 31-42, 49-66; 4:16-22, 26-33; Figs. 1, 2, 3, 4 and 5; App 10/446,103, 9/28/2004 Office Action, pages 4-8; App 10/446,103, 1/28/2005 Response, pages 5, 6, 8-10; 13-14; App 10/446,103, 3/8/2005 Final Office Action, pages 3-5, 7- 9; App 10/446,103, 6/8/2005 Response, page 5; App 10/446,103, 6/27/2005 Notice of Allowability, pages 2-3.	two or more protrusions that are part of the frame and that extend outwardly from the first edge for fastening the frame to the bezel

O-1

Disputed Constructions

	'506 Prosecution History		
	Abstract; 1:7-10; 1:11-21, and Fig. 1; 1:25-34; 1:60-2:15, and Fig. 2; 2:61-64; 3:2-6; 3:7-15; claims 1, 5-9, 13-17, and 20-23.		
	Intrinsic Support '506 Specification		
	an LCD module	Α	display module
	'506 Prosecution History October 28, 2005 Office Action, esp. at 2-3; February 14, 2006 Office Action, esp. at 2; May 10, 2006 Response, esp. at 10. U.S. Patent Application Publication No. 2005/0185127 A1 (Fujiyama et al.) in general, esp. 0026 and Figs. 1, 5.		
	Abstract; 1:12-21, and Fig. 1; 1:25-34; 1:60-2:5, esp. 1:65-67, and Fig. 2; 2:38-48, and Figs 4a and 4b; claims 1, 5, 9, 13, 17 and 20.		
-	Intrinsic Support '506 Specification		
	a first printed circuit made on a flexible film that electrically connects the display module and the system	Ľ	a first flexible printed circuit board, electrically connecting the display module and the system
LGD Construction	AUO Construction	Des.	Claim Terms

Claim Terms	Des.	AUO Construction	LGD Construction
		October 28, 2005 Office Action, esp. at 2-3; February 14, 2006 Office Action, esp. at 2;	
		May 10, 2006 Response, esp. at 10.	
		U.S. Patent Application Publication No. 2005/0185127 A1 (Fujiyama et al.) in	
		general, esp.: Abstract; 0003; 0008; 0018	
		and Fig. 1. U.S. Patent No. 5,684,550 (Shibata et al.) in	
		general, esp.: Abstract; 3:63-67 and Figs.	-
		23, 24(a)-24(E); 17:16-47 and Figs. 23-39.	
a second flexible printed circuit board, electrically connecting the	T	a second printed circuit made on a flexible film that electrically connects the display	
display module and the first flexible printed circuit board		module and the first printed circuit made on a flexible film	
		Intrinsic Support '506 Specification	-
		Abstract; 1:12-21, and Fig. 1; 1:25-34; 1:60-2:15, esp. 2:6-15, and Fig. 2; 2:38-57, and	
		Figs 4a and 4b; claims 1, 6, 7, 9, 14, 15, 17, 21, and 22.	
		'506 Prosecution History October 28, 2005 Office Action, esp. at 2-3;	
		February 14, 2006 Office Action, esp. at 2; May 10, 2006 Response, esp. at 10.	
		U.S. Patent Application Publication No.	
		general, esp. 0026 and Figs. 1, 5.	

printed circuit boards are joined by hot bar soldering	the first and second printed circuits made on flexible film are joined by a soldering process where the solder and flux are applied to the contact area and the contact area is heated with a bar to melt the solder
	Intrinsic Support '506 Specification
	Abstract; 1:25-34, esp. 1:30-34; 1:60-2:15, and Fig. 2; 2:16-37, and Figs. 2, 3a, and 3b; 2:64-67; claim 1.
	7506 Prosecution History October 28, 2005 Office Action, esp. at 2-3. U.S. Patent Application Publication No. 2005/0185127 A1 (Fujiyama et al.) in general, esp.: 0021, 0045, and Fig. 1.
the first and second flexible printed circuit boards are joined by anisotropic conductive film (ACF) bonding	L both flexible circuit boards are connected to each other by a material that is conductive in one direction after being pressed between the two circuit boards
	Intrinsic Support '506 Specification
	Abstract; 1:25-34, esp. 1:30-34; 2:40-57, and Figs. 2, 4a, and 4b; 2:64-67; claim 9.
	7506 Prosecution History October 28, 2005 Office Action, esp. at 2-3. U.S. Patent Application Publication No.

,		Claim Terms	
general, esp.: 0042, 0055, and Figs. 1, 5.	2005/0185127 A1 (Fujiyama et al.) in	Des. AUO Constructi	
 d Figs. 1, 5.	et al.) in	ion LGD Construction	

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Intrinsic Support 1:25-35; 1:60-2:25, 40-9, 58-66; Figs. 2, 3a, 3b; 4a, 4b; App 10/921,462, 2/14/06 Office Action, pages 2-3; App 10/921,462, 5/10/06 Response, pages 9-14.			display module and the first flexible printed circuit board
Intrinsic Support 1:13-21, 25-35, 61-65; 2:58-64; 3:2-6; Figs. 1 and 2. a second flexible film with conductive		П	a second flexible printed circuit
an assembly that includes an LCD panel, a touch panel and a light source		>	display module
Intrinsic Support 1:25-35; 1:60-2:25, 40-9, 58-66; Figs. 2, 3a, 3b; 4a, 4b; App 10/921,462, 2/14/06 Office Action, pages 2-3; App 10/921,462, 5/10/06 Response, pages 9-14.			
a first flexible film with conductive patterns printed on its surface that electrically connects the display module and the system	s. AUO Construction	Des. L	Claim Terms a first flexible printed circuit board, electrically connecting the display module and the system

the first and second flexible	Des.	AUO Construction	both flexible printed circuit boards are
printed circuit boards are joined by hot bar soldering			connected to each other by a soldering process where the circuit boards are heated with a bar to melt the solder at multiple points simultaneously along each circuit board while pressure is applied to the connection
			Intrinsic Support 1:25-35; 2:6-37, 46-49, 58-67; Figs. 2, 3a, 3b; App 10/921,462, 2/14/06 Office Action, pages 2-3; App 10/921,462, 5/10/06 Response, pages 9-14; .App 10/921,462, 5/19/06 Notice of Allowability, page 2.
the first and second flexible printed circuit boards are joined by anisotropic conductive film (ACF) bonding	L		both flexible printed circuit boards are connected to each other by a process where a material that is conductive in one direction is pressed between the two circuit boards
			Intrinsic Support 1:25-35; 2:6-20, 40-49, 58-67; Figs. 2, 4a, 4b; App 10/921,462, 2/14/06 Office Action, pages 2-3; App 10/921,462, 5/10/06 Response, pages 9-14; App 10/921,462, 5/19/06 Notice of Allowability, page 2.

P-1

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Claim Terms	Des.	AUO Construction	LGD Construction
a fitting portion	T	a structure for accommodating an illumination tube	
		Intrinsic Support	
		'069 Specification	
		Abstract; 1:43-52, esp. 44-45; 1:57-65, esp. 62-65; 2:39-43; 2:50-54; 2:55-3:2, esp.	-
		2:63-3:2; 3:9-14, esp. 9-10; claims 1, 3, 7, 8, 16-18; Figures 3, 4, 5A-5G.	
		7069 Prosecution History	
		May 3, 2005 Office Action, esp. at 2-3; January 9, 2006 Response After Final Rejection, esp. at 6.	
comprises two side walls extending upwardly and	T	having at least two sidewalls extending upwardly and separately	
separately		Intrinsic Support	
		'069 Specification	
		Abstract; 1:43-52, esp. 44-45; 1:57-65, esp. 62-65; 2:39-43; 2:50-54; 2:55-3:2, esp. 2:63-64: 3:9-14: claims 1 7 & 16-18:	
		Figures 3, 4, 5A-5G.	
		'069 Prosecution History	
		May 3, 2005 Office Action, esp. at 2; October 20, 2005 Office Action, esp. at 2-3;	
		January 9, 2006 Response After Final Rejection, esp. at 6; April 20, 2006 Notice	

						has two side walls extending L P P P P P P P P P P P P P P P P P P		Claim Terms Des.
JP 2001-210126, esp. ¶¶ 0012, 0014, 0016-0020, 0030, 0038 and Figures 4-5.	January 9, 2006 Response After Final Rejection, esp. at 6; April 20, 2006 Notice of Allowability.	'069 Prosecution History	Figures 3, 4, 5A-5G; claims 1, 7, 8, 16-18.	'069 Specification	Intrinsic Support	having two sidewalls extending upwardly and separately	JP 2001-210126, esp. ¶¶ 0012, 0014, 0016- 0020, 0030, 0038 and Figures 4-5.	AUO Construction of Allowability.
		4		-				LGD Construction

In	2: 4: 6: 6:4	<u>In:</u>	supporting portion A Aı (ir	Sa	<u>n</u>	Claim Terms a first supporting portion, disposed on the frame frame (i. (ir. culture))
Incorporated Disputed Terms Included is the intrinsic support for disputed term "constraining portion."	7157 Specification 2:61-62; 2:66-3:4; 3:5-3:12; 4:17-24, esp. 4:17-21 and Figures 2A and 2B; 6:4-8, esp. 6:4-6 and Figures 3A and 3B; 6:31-42, esp. 6:40-42 and Figure 3C; 7:39-45 and Figures 4A – 4D; claim 10, 22.	Intrinsic Support	Any structure protruding from the frame, (including but not limited to a cylinder or a cuboid) intended to support the optical film	Same as for the term "supporting portion."	Intrinsic Support	AUO Construction A first supporting portion, disposed on the frame, wherein the term "supporting portion" has the meaning proposed by AUO (i.e. any structure protruding from the frame (including but not limited to a cylinder or a cuboid) intended to support the optical film).
		-				LGD Construction

P-2

The second secon			
has two upright structures that are spaced apart and that are designed to hold the illumination tube Intrinsic Support 2:44-9, 55-61; Figs. 5B, 5C, 5F, and 5G; App 10/613,493, 1/9/06 Response, pages 2, 4-7; App 10/613,493, 4/20/06 Notice of Allowability, page 2.		F	has two side walls extending upwardly and separately
Intrinsic Support 2:44-9, 55-61; Figs. 5B, 5C, 5F, and 5G; App 10/613,493, 1/9/06 Response, pages 2, 4-7; App 10/613,493, 4/20/06 Notice of Allowability, page 2.			
includes two upright structures that are spaced apart and that are designed to hold the illumination tube		۲	comprises two side walls extending upwardly and separately
Intrinsic Support 1:64-65; 2:41-43; 2:50-53; 2:62-3:3; Abstract; Figs. 3, 5A-G; App 10/613,493, 1/9/06 Response, pages 2, 4-7; App 10/613,493, 4/20/06 Notice of Allowability, page 2.			
the portion of the support designed to hold an illumination tube		T	a fitting portion
LGD Construction	AUO Construction	Des.	Claim Terms

Q-1

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	Same as for the term "constraining portion."		
	Intrinsic Support		
	A first constraining portion, wherein the term "constraining portion" has the meaning proposed by AUO (i.e. any formation on or in the optical film (including but not limited to a hole or a groove) intended to restrict the movement range of the film).	m L	a first constraining portion
	Same as for the term "supporting portion."		
-	Intrinsic Support		
	not limited to a cylinder or a cuboid) intended to support the optical film).		
	"supporting portion" has the meaning proposed by AUO (i.e. any structure		
	A second supporting portion, further disposed on the frame, wherein the term	ion, L	a second supporting portion, further disposed on the frame
LGD Construction	AUO Construction	Des.	Claim Terms

			a second constraining portion				constraining portion
			L				A A
Same as for the term "constraining portion."	Intrinsic Support	in the optical film (including but not limited to a hole or a groove) intended to restrict the movement range of the film)	A second constraining portion, wherein the term "constraining portion" has the meaning proposed by AITO (i.e. any formation on or	Incorporated Disputed Terms Included is the intrinsic support for disputed term "supporting portion."	7157 Specification 2:27-30; 2:63-65; 4:7-16, esp. 4:13-15 and Figure 2A; 6:47-49; 7:22-33, esp. 7:28-29 and Figure 3C; claims 2, 11, 17.	Intrinsic Support	Any formation on or in the optical film (including but not limited to a hole or groove) intended to restrict the movement range of the film
							LGD Construction

	Same as for the term "disposed in a first position."		
	Intrinsic Support		
	See above construction for "disposed in a first position."	Α	first position
-	Incorporated Disputed Terms Included is the intrinsic support for disputed term "disposed in a second position."		
	2:12-26, esp. 2:19-25; 2:52-60; 2:66-3:4; 4:37-42; 4:48-56, esp. Figure 3A; 5:37-54, esp. 5:39-44 and Figure 3A; 6:14-30, esp. 6:22-27 and Figure 3C; 7:22-33, esp. 7:22-23 and Figure 3C; 7:39-45 and Figures. 4A-4D; 7:46-52, esp. 7:49-50 and Fig. 4A; claim 23.		
	Intrinsic Support		
	an initial position of a liquid crystal display unit.	T	disposed in a first position
LGD Construction	AUO Construction	Des.	Claim Terms

			disposed in a second position	does not contact	positioning the film	the first supporting portion partially contacts an inner wall of the first constraining portion for	Claim Terms
			L	T		of L	Des.
Incorporated Disputed Terms Included is the intrinsic support for disputed term "disposed in a first position."	7157 Specification 2:12-26, esp. 2:19-25; 2:52-60; 3:6-11; 4:37-42; 4:48-56, esp. Figure 3B; 5:55-6:3, esp. 5:55-57 and Figure 3B; 7:22-33, esp. 7:22-23, 7:26-27, and Figure 3C; 7:39-45 and Figures. 4A- 4D; 7:53-59, esp. 7:55-57 and Figure 4B; claim 23.	Intrinsic Support	a second position of a liquid crystal display unit where the position is determined by reference to the angle of rotation between the first position and the second position.	Plain meaning	7157 Specification Figures 2A-2B, 3A-3C, 4A-4D; 5:17-22; 5:55-6:3; 6:55-61; 7:22-33; 7:46-8:2.	Plain meaning Intrinsic Support	AUO Construction
							LGD Construction

Claim Terms	Des.	AUO Construction	LGD Construction
second position	Α	See above construction for "disposed in a second position."	
		Intrinsic Support	
•		Same as for the term "disposed in a second position."	
the second supporting portion		Plain meaning	
the second constraining portion for positioning the film		Intrinsic Support	-
C		7157 Specification Figures 2A-2B, 3A-3C, 4A-4D; 5:17-22; 5:55-6:3; 6:55-61; 7:22-33; 7:46-8:2.	
on opposite corners of the film	L	Plain meaning	
on adjacent corners of the film	T	Plain meaning	
frame comprising a first supporting portion and a second	٦	See above constructions for "a first supporting portion, disposed on the frame"	
supporting portion		and "a second supporting portion, further disposed on the frame."	
		Intrinsic Support	
		Same as for the term "supporting portion."	
a third constraining portion and a fourth constraining portion disposed on the frame		Plain meaning	

Claim Terms Des.	s. AUO Construction	LGD Construction
the third constraining portion and	Plain meaning	
the fourth constraining portion		
pass through the first constraining		
portion and the second		-
constraining portion, respectively		

O-2

further disposed on the frame	supporting portion	a first supporting portion, disposed on the frame
		L L
		AUO Construction
Intrinsic Support 1:27-51; 4:48-64; 5:36-6:8; 6:17-22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	(see above)	a first projection from the frame that supports the film when the backlight is in a first position Intrinsic Support 1:27-51; 2:1-8; 4:18-24; 4:48-64; 5:17-22; 5:45-6:8; 6:17-22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.

		constraining portion	•	a first constraining portion	Claim Terms
		A		T	Des.
				ACC COMSTACTOR	AUO Construction
The second pulsar production of the second pro	Intrinsic Support 1:27-51; 2:66-3:19; 5:45-6:3; 6:17-22; 7:21- 27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	a passage through the film that has a gap in the gravity acting direction after receiving a supporting portion	Intrinsic Support 1:27-51; 2:66-3:19; 5:39-6:3; 6:17-22; 7:21- 27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	a first passage through the film that has a gap in the gravity acting direction after receiving a supporting portion	LGD Construction

first position		disposed in a first position	,	Claim Terms a second constraining portion
A		1		on L
				AUO Construction
(see above)	Intrinsic Support 1:27-51; 2:1-8; 2:66-3:19; 5:36-6:3; 6:17- 22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	in an orientation where the first projection is located near an upper edge of the frame	Intrinsic Support 1:27-51; 2:66-3:19; 5:36-6:3; 6:17-22; 7:21- 27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	a second passage through the film that has a gap in the gravity acting direction after receiving a supporting portion

	does not contact	the first supporting portion partially contacts an inner wall of the first constraining portion for positioning the film
	L	Des. L vall of n for
		AUO Construction
Intrinsic Support 1:27-51; 2:1-8; 2:66-3:19; 5:36-6:3; 6:17- 22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	does not touch	the first projection touches a top portion of the first passage to support the film and has a gap below the first projection Intrinsic Support 1:27-51; 2:1-8; 2:66-3:19; 5:17-22; 5:36-6:3; 6:17-22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8-9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.

			·	
on obbosic connexs of the min	the second supporting portion partially contacts an inner wall of the second constraining portion for positioning the film	second position		Claim Terms disposed in a second position
t	L	Α		Des.
				AUO Construction
intersect such that the areas do not share an edge of the film Intrinsic Support 2:47-9; 7:34-9; Fig. 3C.	the second projection touches a top portion of the second passage to support the film and has a gap below the second projection Intrinsic Support 1:27-51; 2:1-8; 2:66-3:19; 5:17-22; 5:36-6:3; 6:17-22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8-9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	(see above)	Intrinsic Support 1:27-51; 2:1-8; 2:66-3:19; 5:36-6:3; 6:17- 22; 7:21-27; Figs. 2A-B, 3A-C, 4A-D; App 10/902,914, 1/25/06 Office Action, pages 8- 9; App 10/902,914, 3/20/06 Response, pages 8-9; App 10/902,914, 5/22/06 Notice of Allowability, pages 2-3.	in an orientation rotated from the first position so that the second projection is located near an upper edge of the frame

R-1

	optical symmetry axis		Claim Terms a layer of a birefringent material
	. L		Des.
Intrinsic Support 2:61-3:17; 10:27-11:8; 12:23-38; 16:1- 17:35; 17:59-20:51; Fig. 14	the extraordinary optic axis in uniaxial materials and the principal optic axis in biaxial materials. A uniaxial material has two axes with the same index of refraction and another axis, the extraordinary axis, that has a different index of refraction. A biaxial material has three axes each with a different index of refraction, and the axis with the highest index of refraction is the principal optic axis	Intrinsic Support 2:53-3:14; 10:27-11:8; 12:23-38; 16:1- 17:35; 17:59-20:51; Fig. 14	a layer of material that has varying indices of refraction depending on the direction light travels through the material. An index of refraction is the ratio of the speed of light in a medium relative to the speed of light in a vacuum
	•	-	LGD Construction

normal to	normal to said layer		is different than the tilt angle at a top surface of the layer relative to an axis normal (perpendicular) to the layer Intrinsic Support 3:50-61; 11:13-17; 12:42-54; 17:59-20:51; Fig. 2; Fig. 12; Application 08/313,476, Response, January 22, 1996 A contrast ratio that exceeds a threshold for a specified range of viewing angles. The contrast ratio is a luminance at a bright state divided by a luminance at a dark state. Intrinsic Support 1:57-2:21; 5:1-8:42; 10:17-25; 10:49-59; 17:59-20:51; Fig. 4; Fig. 5; Fig. 6; Fig. 7; Fig. 8; Fig. 9; Fig. 10
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R-2

optical symmetry axis	a layer of a birefringent material	Claim Terms D
-		Des.
		CMO Construction
the extraordinary axis of the molecules Intrinsic Support 2:53-3:19; 9:37-10:47; 10:51-64.	a thickness of material including positively birefringent molecules that are uniaxial or near uniaxial in character Intrinsic Support 2:53-3:19; 7:08-22; 8:16-53; 9:37-10:47; 10:51-64; 12:45-50; 13:08-20; 14:48-57; 15:63-67; 16:03-10; Figs. 7-14; Abstract; App 08/223,251, 8/23,1995, Amendment, pages 6-9.	LGD Construction

a desired viewing characteristic	7:08-22; 10:65-11:21; 14:33-44; 16:16-19; F Abstract; App 08/223 Amendment, pages 6- 1/22/1996, Amendme	Intrinsic Support	normal to said layer normal to said layer the filt angle of the compensation of the filt angle o	Des. CMO Construction	
	7:08-22; 10:65-11:21; 12:23-26; 14:04-07; 14:33-44; 16:16-19; Figs. 7-14; Title & Abstract; App 08/223,251, 8/23,1995, Amendment, pages 6-9; App 08/690,033, 1/22/1996, Amendment, pages 9-11.	ort	the tilt angle of the compensator varies along an axis normal to the layer of birefringent material and is limited to values between approximately 25 degrees and approximately 65 degrees	LGD Construction	

S-1

driver means L Function (plain meaning): driving the display cell with grey scale data signals Corresponding structure: X-driver 3, Y-driver 3, Y-driver 5 (Fig. 1) and equivalents Intrinsic Support 1:27-46; 1:47-52; 6:1-9; and exhibits referenced therein, including Fig. 1 Intrinsic Support L Function (plain meaning): receiving gray scale data signals to the driver with a predetermined timing Corresponding structure: computing circuit 32, buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 4:31-37; 5:23-30; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5	Claim Terms 1	Des.	CMO Construction	LGD Construction
	driver means	L	Function (plain meaning): driving the display cell with grey scale data signals	
L			Corresponding structure: X-driver 3, Y-driver 5 (Fig. 1) and equivalents	
L			Intrinsic Support	-
T			1:27-46; 1:47-52; 6:1-9; and exhibits referenced therein, including Fig. 1	-
Corresponding structure: computing circuit 32, buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 4:31-37; 5:23-30; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5	data control means		Function (plain meaning): receiving gray scale data signals and outputting the gray scale data signals to the driver with a predetermined timing	
Intrinsic Support 4:31-37; 5:23-30; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5			Corresponding structure: computing circuit 32, buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents	
4:31-37; 5:23-30; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5			Intrinsic Support	
THE PROPERTY OF THE PROPERTY O			4:31-37; 5:23-30; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5	

			computing means				said data control means (claim 11)	Claim Terms
			L					Des.
4:31-37; 5:58-63; 2:1-23; 3:25-31; 4:55-57; 6:1-9; and exhibits referenced therein, including Fig. 5	Intrinsic Support	Corresponding structure: computing circuit 32 (Fig. 5) and equivalents	Function (plain meaning): changing the level of the gray scale data signals for at least one color relative to the other colors to a different gray scale level to compensate for a variation in intensity between the colors due to wavelength related differences in transmissivity between the colors the light transmitting medium	3:25-31; 4:31-37; 5:58-63; 2:1-23; 4:55-57; 6:1-9; and exhibits referenced therein, including Fig. 5	Intrinsic Support	see also claim 7, "calculation logic" below	structure that can add or subtract a binary signal representing a change of at least one gray scale level for at least one color	CMO Construction
			-					LGD Construction

changing the level of the gray scale data signals for at least one color relative to the other colors to a different gray scale level L plain meaning or, if the Court determines construction is necessary, memory where gray scale data signals can be temporarily stored and delayed if interpreted pursuant to 35 U.S.C. §112, ¶6: Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected gray scale data signal being structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5	Claim Terms	Des.	CMO Construction
L	changing the level of the gray scale data signals for at least one color relative to the other colors to a different gray scale level	Г	see claim 1 "computing means" above
or, if the Court determines construction is necessary, memory where gray scale data signals can be temporarily stored and delayed if interpreted pursuant to 35 U.S.C. §112, 6: Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5	buffer means	L	plain meaning
memory where gray scale data signals can be temporarily stored and delayed if interpreted pursuant to 35 U.S.C. §112, ¶6: Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			or, if the Court determines construction is necessary,
if interpreted pursuant to 35 U.S.C. §112, ¶6: Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			memory where gray scale data signals can be temporarily stored and delayed
Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected Corrected Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			if interpreted pursuant to 35 U.S.C. §112, ¶6:
Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected
Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents
5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5			Intrinsic Support
			5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5

l by	Claim Terms delaying any uncorrected gray scale signal related to the other	Des.	CMO Construction see claim 1 "buffer means" above
L	scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected		
Corresponding structure: computing circuit 32 (Fig. 5) and equivalents Intrinsic Support 5:37-43; 4:31-37; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5	adjusting means	T	Function (plain meaning): varying the amount of correction accorded to the gray scale data signals for said at least one color
Intrinsic Support 5:37-43; 4:31-37; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5			Corresponding structure: computing circuit 32 (Fig. 5) and equivalents
5:37-43; 4:31-37; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5			Intrinsic Support
			5:37-43; 4:31-37; 3:25-31; 5:58-63; 6:1-9; and exhibits referenced therein, including Fig. 5

scale data signal related to at least one of the multicolors supplied to the display cell to create a corrected gray scale data signal Intrinsic Support 4:31-37; 5:58-63; 2:1-23; 3:25-31; 4:55-57; 6:1-9; and exhibits referenced therein
el of gray scale ted to at least one ts supplied to the eate a corrected ignal with a level ie inputted gray
Intrinsic Support 5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein, including Fig. 5
Corresponding structure: buffer circuit 26, delay circuit 24 (Fig. 5) and equivalents
said adjusting means (claim 3) Function (plain meaning): delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being
Claim Terms Des. CMO Construction

	plain meaning		dienlay cells
	3:29-31; 4:19-21; 5:23-30; 4:11-18; 6:1-9; and exhibits referenced therein		
	Intrinsic Support		
ne	outputting the gray scale data of all the multicolors from a buffer at about the same time	, , , , , , , , , , , , , , , , , , , ,	
	or, if the Court determines construction is necessary,		
	plain meaning	Ţ	simultaneously output the gray scale data of all said multicolors
	5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein	Wile 145 C 1 S 2 S 2 S 2 S 2 S 2 S 2 S 2 S 2 S 2 S	-
-	Intrinsic Support		
of	delaying the output for at least one other of the multicolors by the time taken for correction of said at least one color		
	or, if the Court determines construction is necessary,		taken for correction of said at least one color
	plain meaning	L	delaying the output for at least one other of the multicolor by the time

gray scale data of all said multicolors"		
plain meaning See also claim 5 "simultaneously output the	L	synchronize the timing of the gray scale data signals for all said
5:23-30; 4:11-21; 6:1-9; and exhibits referenced therein		
Intrinsic Support		
delaying the output for any uncorrected color of the multicolors by the amount of time taken for correction of the one color		color
or, if the Court determines construction is necessary,		scale data signals not subject to a correction by the amount of time taken for correction of the one
plain meaning	L	delaying the output for any other color of the multicolors with grav
4:31-37; 5:58-63; 2:1-23; 3:25-31; 4:55-57; 6:1-9; and exhibits referenced therein		
Intrinsic Support		
changing the gray scale data signals for at least one of the multicolors		
or, if the Court determines construction is necessary,		multicolors
plain meaning	L	changing the gray scale data signals related to one of the

S-2

Disputed Constructions

said data control means (claim 11)		·	,	data control means			,	driver means	Claim Terms
				T				L	Des.
									CMO Construction
Indefinite	Intrinsic Support 1:27-46; 1:66-2:27; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; 5:58-63; Figs. 1, 2, 5, 6, 7.	structure: Fig. 5, all elements; Figs 6-8	function: receiving gray scale data signals related to the setting of a gray scale for the display cell and outputting said gray scale data signals to said driver with a predetermined timing	Interpreted per 35 USC §112¶6	Intrinsic Support 1:27-46; 2:46-3:11; 3:64-4:06; Fig. 1.	structure: Fig. 1, element 3	function: driving the display cell with sets of grey scale data signals	Interpreted per 35 USC §112¶6	LGD Construction

changing the level of the gray scale data signals for at least one color relative to the other colors to a different gray scale level Intrinsic: Abstract; 3:12-32; 5:11-43; H09-319 App 08/8 pages 4-7 Office A	function: scale date relative te gray scal variation to wavele transmiss the light structure: 6-8 Intrinsic 4:07-56; 5, 6, 7, 8	compunity T
adding or subtracting compensation values to modify the gray scale levels of one or more, but not all, color video signals Intrinsic Support Abstract; 1:27-46; 1:66-2:27; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 1, 2, 5, 6, 7, 8; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	function: changing the level of the gray scale data signals for at least one color relative to the other colors to a different gray scale level to compensate for a variation in intensity between the colors due to wavelength related differences in transmissivity between the colors through the light transmitting medium structure: Fig. 5, elements 32, 33, 34; Figs. 6-8 Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 5, 6, 7, 8.	Interpreted per 35 USC §112¶6

	delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected		Claim Terms buffer means
	L		Des. L
		- ·	CMO Construction
Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 5, 6, 7; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	holding or deferring at least one color video signal that is not subjected to a compensation value by the amount of time taken to modify another color video signal Intrinsic Support	function: delaying any uncorrected gray scale signal related to the other colors for the time delay caused by said corrected gray scale data signal being corrected structure: Fig. 5, element 24 Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 5:11-43; 4:07-56; Figs. 5, 6, 7.	LGD Construction Interpreted per 35 USC §112¶6

changing the level of gray scale data signals related to at least one of the multicolors supplied to the display cell to create a corrected gray scale data signal with a level different from the inputted gray scale data signal	said adjusting means (claim 3)				Claim Terms Des. adjusting means L
					CMO Construction
adding or subtracting compensation values to modify the gray scale levels of one or more, but not all, input color video signals Intrinsic Support Abstract; 1:27-46; 1:66-2:27; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 1, 2, 5, 6, 7, 8; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	Indefinite	Intrinsic Support 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 5, 6, 7, 8.	structure: Fig. 5, elements 33, 34; Figs. 6-8	function: varying the amount of correction accorded to the gray scale data signals for said at least one color	LGD Construction Interpreted per 35 USC §112¶6

disp		simu scale	,	delar othe taker
display cells		simultaneously output the gray scale data of all said multicolors		Claim Terms delaying the output for at least one other of the multicolor by the time taken for correction of said at least one color
		T		Des.
				CMO Construction
Indefinite	Intrinsic Support Abstract; 1:27-46; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 1, 5, 6, 7; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	provides all multicolor gray scale data to the data driver during the same predetermined time interval	Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 5, 6, 7; JP H09- 319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	holding or deferring the output of at least one color video signal that is not subject to a compensation value by the amount of time taken to modify another color video signal

driver circuit for any other of the colors without the calculation logic in its driver circuit	calculation logic for changing the level of the gray scale data signals of said at least one color to a different gray scale level
	CMO Construction
at least one color video signal path that does not include calculation logic Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 5, 6, 7; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	calculation logic for adding or subtracting compensation values to modify one or more, but not all, color video signals Intrinsic Support Abstract; 1:27-46; 1:66-2:27; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 1, 2, 5, 6, 7, 8; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.

	changing the gray scale data signals related to one of the multicolors		Claim Terms delaying the gray scale signals for the other of the colors
	T		Des.
			CMO Construction
Intrinsic Support Abstract; 1:27-46; 1:66-2:27; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 4:55-5:10; 5:11-43; 5:58-63; Figs. 1, 2, 5, 6, 7, 8; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	adding or subtracting compensation values to modify the gray scale level of one of the color video signals	Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 5, 6, 7; JP H09- 319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	LGD Construction holding or deferring the output of the unmodified color video signals

		t		
	synchronize the timing of the gray scale data signals for all said multicolors	COLOR	delaying the output for any other color of the multicolors with gray scale data signals not subject to a correction by the amount of time taken for correction of the one	
	T		t	Des.
		-		CMO Construction
Intrinsic Support Abstract; 1:27-46; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 1, 5, 6, 7; JP H09-319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	provides all multicolor gray scale data signals to the data driver during the same predetermined time interval	Intrinsic Support Abstract; 2:46-3:11; 3:12-32; 3:64-4:06; 4:07-56; 5:11-43; Figs. 5, 6, 7; JP H09- 319334A at paragraphs [0013]-[0026]; App 08/832,640, 3/23/1999 Amendment, pages 4-7; App 08/832,640, 7/19/1999 Office Action, page 2.	holding or deferring the output of the remaining color video signals that are not subject to compensation values by the amount of time taken to modify the one color video signal	LGD Construction

T-1

Disputed Constructions

Claim Terms	Des.	CMO Construction	LGD Construction
source line	L	plain meaning	
		or, if the Court determines that construction is necessary,	
		conductor that connects the source terminals of pixel transistors and leads to the source amplifiers	
		Intrinsic Support	
	.,	4:65-66; 5:1-5:6; 7:22-31; 7:66-8:2 and exhibits referenced therein	
gate line	T	plain meaning	
		or, if the Court determines that construction is necessary,	
		conductor that connects the gate terminals of pixel transistors and leads to the gate driver circuit	
		Intrinsic Support	
		4:64-65; 4:66-5:1; 7:22-31; 7:66-8:2 and exhibits referenced therein	

Claim Lerms during formation of said gate lines	L	during the manufacturing stages in which the gate lines are formed and connected Intrinsic Support	LGD Construction
		7:22-31; 4:64-5:1; 5:27-40; 7:49-55; 5:41-64; 1:55-62; 7:66-8:2 and exhibits referenced therein	
shorting element	L	plain meaning	
		Intrinsic Support	
		see, e.g., 1:64-2:3 and exhibits referenced therein	
protection element	L	element protecting from electrostatic discharge (ESD)	
		Intrinsic Support	
		5:60-6:13; 4:24-26; 2:61-67; 7:66-8:2 and exhibits referenced therein	

		electrically coupling said shorting elements			during formation of said source lines	Claim Terms
		Ţ			Т	Des.
5:57-64; 7:66-8:2 and exhibits referenced therein	Intrinsic Support	electrically connecting the shorting elements	7:22-31; 5:1-5:6; 7:49-55; 5:30-34; 5:48-57; 1:55-62; 7:66-8:2 and exhibits referenced therein	Intrinsic Support	during the manufacturing stages in which the source lines are formed and connected	CMO Construction
						LGD Construction

T-2

Disputed Constructions

	during formation of said gate lines		gate line		Claim Terms source line
	Т		Г		Des.
					CMO Construction
Intrinsic Support Abstract; 1:6-11; 1:12-2:17; 2:58-65; 3:6-31, 3:39-43; 3:45-4:31; 4:64-5:15; 5:27-47; 5:65-6:19; 7:1-31; 7:49-8:2; Figs. 3-9; App. No. 09/000,479, 11/3/1997, PCT International Preliminary Examination Report, pages 2-4.	at the same time when the electrically conductive material that forms the gate lines is deposited and etched	Intrinsic Support Abstract; 1:6-11; 1:12-2:17; 2:58-65; 3:6-31, 3:39-43; 3:45-4:31; 4:64-5:15; 5:27-47; 5:65-6:19; 7:1-31; 7:49-8:2; Figs. 1-3, 6-8.	a pattern of electrically conductive material that conveys gate signals to transistors within the TFT array	Intrinsic Support Abstract; 1:6-11; 1:12-2:17; 2:58-65; 3:6-31, 3:39-43; 3:45-4:31; 4:64-5:15; 5:27-41; 5:48-6:19; 7:1-31; 7:49-8:2; Figs. 1-3, 6-8.	a pattern of electrically conductive material that conveys data signals to transistors within the TFT array

	protection element	snorting element	Claim Terms
	T	F	Des.
			CMO Construction
Intrinsic Support 1:5-10; 1:12-20; 1:24-26; 1:31-43; 1:55- 3:43; 3:45-50; 3: 54-61; 4:5-22; 4:27-32; 5:33-41; 5:50-6:13; 6:19-57; 7:15-40; 7:49- 8:2; Figs. 3-9; App. No. 09/000,479, 11/3/1997, PCT International Preliminary Examination Report, pages 2-4.	a circuit component designed to protect against electrostatic discharge and to allow for testing	a pattern of conductive material for electrically connecting, with low resistance, the gate lines to each other or the source lines to each other Intrinsic Support Abstract; 1:55-2:3; 1:7-10; 1:12-20; 1:24-27; 1:44-2:10; 2:19-28; 2:44-51; 2:58-68; 3:6-30; 3:54-62; 4:5-31; 5:38-64; 6:14-35; 6:47-57; 7:1-21; 7:36-40; 7:49-8:2; Figs. 3-9; App. No. 09/000,479, 11/3/1997, PCT International Preliminary Examination Report, pages 2-4.	LGD Construction

elements	during formation of said source lines	Oloim Torme
t	T E	Doc
FP	The construction of the co	CMO Construction
Elements without intervening protection elements Intrinsic Support Abstract; 1:55-2:3; 1:7-10; 1:12-20; 1:24-27; 1:44-2:10; 2:19-28; 2:44-51; 2:58-68; 3:6-30; 3:54-62; 4:5-31; 5:7-14; 5:38-64; 6:14-35; 6:47-57; 7:1-21; 7:36-40; 7:49-8:2; Figs. 3-9; App. No. 09/000,479, 11/3/1997, PCT International Preliminary Examination Report, pages 2-4.	at the same time when the electrically conductive material that forms the source lines is deposited and etched Intrinsic Support Abstract; 1:6-11; 1:12-2:17; 2:58-65; 3:6-31, 3:39-43; 3:45-4:31; 4:64-5:15; 5:27-41; 5:48-6:19; 7:1-31; 7:49-8:2; Figs. 3-9; App. No. 09/000,479, 11/3/1997, PCT International Preliminary Examination Report, pages 2-4.	I CD Construction

U-1

Disputed Constructions

Claim Terms peripheral portion	Des.	plain meaning	LGD Construction
		or, if the Court determines that construction is necessary,	· -
		a portion of the waveguide that is covered by a cover	-
		Intrinsic Support	
		5:9-14; 6:66-7:2; 7:12-15; 9:30-12:9; Fig. 12; Fig. 13	
a series of point light sources	T	plain meaning	
		or, if the Court determines that construction is necessary,	
		three or more solid state light sources	
		Intrinsic Support	
		1:24-34; 1:54-56; 3:18-22; 7:3-5; 9:30-12:9	

				diffusive reflective surfaces L	Claim Terms Des.
3:44-47; 4:24-54; 5:61-6:7; 7:16-26; 7:44-61; 9:30-12:9; Fig. 2; Fig. 4; Fig. 8; Fig. 13; Fig. 13A	Intrinsic Support	surfaces, including a surface that extends upward relative to a planar surface, that diffusively reflect light	or, if the Court determines that construction is necessary,	plain meaning	CMO Construction
					LGD Construction

						waveguide so as to introduce light	Claim Terms Oriented relative to the series of noint light sources and the
3:54-57; 3:65-4:3; 7:16-23; 7:44-61; 9:30- 12:9; Fig. 2; Fig. 3; Fig. 13; Fig. 13A	Intrinsic Support	the diffusive reflective surfaces are angled relative to each other to direct light from the point light sources into the waveguide	to mean:	"the diffusive reflective surfaces oriented relative to the series of point light sources and the waveguide so as to introduce light in regions of said waveguide between pairs of said point light sources"	construe:	or, if the Court determines that construction is necessary,	Des. CMO Construction L plain meaning
				·			LGD Construction

Claim Terms	Des.	CMO Construction	LGD Construction
whereby the peripheral portion of the waveguide is substantially	CL	not a claim limitation	
uniformly illuminated		or	
		plain meaning	
		or, if the Court determines that construction is necessary,	-
		The portion of the waveguide, that is covered by a cover and intersects an aperture, is substantially uniformly illuminated. The aperture is an area of the waveguide through which light escapes the illumination device.	
		Intrinsic Support	
		1:17-23; 5:49-54; 5:9-14: 6:66-7:2; 7:12- 15; 7:36-39; 9:30-12:9; Fig. 12; Fig. 13	-
light-emitting diodes mounted on an electrical-conductive strip of material	T	plain meaning	

mouth Claim Frims	T Tes.	nlain meaning	LGD Construction
	t	or, if the Court determines that	
		construction is necessary,	
		construe:	
		"entry mouth"	
		to mean:	
		a region of the optical cavity that is located nearest to the point light source	
		and construe:	
		"exit mouth"	
		to mean:	
		a region of the optical cavity that is located the farthest from the point light source	
		Intrinsic Support	
		4:10-23; 7:16-30; 9:30-12:9; Fig. 3; Fig. 13	

cavities or, if the Court determines that construction is necessary, a space between diffusive reflective surfaces Intrinsic Support 3:44-47; 4:24-54; 5:61-6:7; 7:5-12; 7:16-26; 7:44-61; 9:30-12:9; Fig. 2; Fig. 8; Fig. 11; Fig. 12; Fig. 13; Fig. 13A guide members positioned along a periphery of the optical cavity or, if the Court determines that construction is necessary, guide members are spaced apart along a side of the optical cavity Intrinsic Support 3:42-44; 9:30-12:9; Fig. 2; Fig. 3; Fig. 11; Fig. 13; Fig. 13A	Claim Terms	Des.	CMO Construction	LGD Construction
Н	diffusive reflective optical cavities	L	plain meaning	
Г			or, if the Court determines that construction is necessary,	<u> </u>
Г			a space between diffusive reflective surfaces	
			Intrinsic Support	-
H			3:44-47; 4:24-54; 5:61-6:7; 7:5-12; 7:16- 26; 7:44-61; 9:30-12:9; Fig. 2; Fig. 8; Fig. 11; Fig. 12; Fig. 13; Fig. 13A	
	guide members positioned along a	L	plain meaning	
guide members are spaced apart along a side of the optical cavity Intrinsic Support 3:42-44; 9:30-12:9; Fig. 2; Fig. 3; Fig. 11; Fig 13; Fig. 13A	peripitety of the obtical cavity		or, if the Court determines that construction is necessary,	-
Intrinsic Support 3:42-44; 9:30-12:9; Fig. 2; Fig. 3; Fig. 11; Fig 13; Fig. 13A			guide members are spaced apart along a side of the optical cavity	
3:42-44; 9:30-12:9; Fig. 2; Fig. 3; Fig. 11; Fig 13; Fig. 13A			Intrinsic Support	
			3:42-44; 9:30-12:9; Fig. 2; Fig. 3; Fig. 11; Fig 13; Fig. 13A	

Claim Terms whereby light is injected from	Des.	not a claim limitation
portion of said optical cavity		Or
		plain meaning
		or, if the Court determines that construction is necessary,
		light is injected from regions of the optical cavities farthest from the point sources of light into a portion of the optical cavity that is covered by a cover
		Intrinsic Support
		3:18-22; 5:9-14; 6:66-7:26; 9:30-12:9; Fig. 3; Fig. 11; Fig. 12; Fig. 13; Fig. 13A

U-2

Disputed Constructions

erms	CMO Construction
peripheral portion	
a series of point light sources L	-
diffusive reflective surfaces L	

	light-emitting diodes mounted on L an electrical-conductive strip of material		whereby the peripheral portion of the waveguide is substantially uniformly illuminated		oriented relative to the series of L point light sources and the waveguide so as to introduce light	Claim Terms Des.
						CMO Construction
Intrinsic Support 3:15-31; 6:45-54; Figs. 2, 13, and 13A.	components, each containing a semiconductor diode chip as part of their structure, that provide the desired light that illuminates the waveguide or optical cavity and that are attached to a strip of material that provides electrical signals to the components	Intrinsic Support 1:47-52; 2:11-17; 3:15-20, 5:1-8; 7:3-15; 7:55-59.	such that the same or nearly the same amount of light is provided along a boundary adjacent a side edge of the waveguide	Intrinsic Support 1:43-52; 3:15-22, 42-4:3; 5:9-15; 7:3-31, 55-9; Figs. 11, 13, 13A.	arranged to be substantially perpendicular to the top surface of the waveguide so as to introduce scattered light reflected directly from the point light sources into the waveguide	LGD Construction

Intrinsic Support 1:43-52, 66-7; 3:18-22; 4:10-23; 5:9-15; 7:3-31, 26-30, 55-9; Figs. 5, 6A, 13, 13A.			
such that light is injected from said exit mouths into a boundary adjacent a side edge of the optical cavity		С	whereby light is injected from said exit mouths into a peripheral portion of said optical cavity
Intrinsic Support 3:15-20; 3:42-67; 4:10-24; 7:3-31; 7:50-60; Figs. 3, 4, 11, 13.		***************************************	
separate structures, unattached from one another, each adjacent a side edge of the optical cavity		L	guide members positioned along a periphery of the optical cavity
Intrinsic Support 1:61-65; 2:1-9; 4:10-23; 7:3-15; 7:44-61; Fig. 13A.			
optical passages having non-transparent surfaces that reflect and scatter light from the point light source		L	diffusive reflective optical cavities
Intrinsic Support 4:10-23; 6:48-9; Figs. 2, 3, 10, 13 and 13A.			·
an optical opening through which light passes		L	mouth
LGD Construction	. CMO Construction	Des.	Claim Terms

V-1

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Disputed Constructions

Claim Terms	Des.	CMO Construction LGD Construction
display apparatus	T	plain meaning
		Intrinsic Support
		Abstract, 1:7-11, 36-39, 2:17-3:24, 3:63-4:12, 4:50-5:21, 5:37-6:14, 6:28-50, 6:65-7:16, 7:24-33, 7:52-8:3, 8:28-33, Figs. 4-13
upper frame	T	plain meaning
		Intrinsic Support
		1:39-44, 2:17-24, 33-35, 51-54, 2:66-3:2, 4:1-3, 50-51, 5:1-3, 37-38, 55-58, 6:31-34, 8:28-33, Figs. 1, 4-13
an array of light tubes disposed	T	plain meaning
ormin are dispiray pairei		Intrinsic Support
		Abstract, 1:10-11, 45-53, 2:1-11, 17-22, 33-37, 51-55, 2:66-3:4, 4:1-5, 50-51, 5:1-5, 37-38, 55-59, 6:31-35, 8:28-33, Figs. 1, 4-13
The state of the s		And the state of t

being separated from the side portion by a gap	T	plain meaning	
•		or, if the Court determines that construction	
		is necessary,	-
		there is a space between one side of a subframe of the supporting frame and the side portion of the reflecting plate	
		Intrinsic Support	
		2:24-32, 4:7-20, 50-62, 8:28-33, Figs. 4-5	
a circuit board installed within the	T	plain meaning	
the display apparatus		or, if the Court determines that construction is necessary,	
		a rigid or printed circuit board for controlling certain operations of the display apparatus located in the space defined above	
		Intrinsic Support	
		2:24-32, 2:44-50, 4:7-20, 4:32-39, 50-62, 5:7-22, 30-33, 37-38, 41-51, 8:28-33, Figs. 4-7	

Claim Tarms	Jac	OMO Construction	
e side	L	plain meaning	
a gap		or, if the Court determines that construction is necessary,	
		there is a space between one side of a subframe of the supporting frame and the side portion of the supporting plate	
		Intrinsic Support	
		2:44-50, 5:7-20, 37-38, 41-51, 8:28-33, Figs. 6-7	
a circuit board installed on the	L	plain meaning	
for controlling operations of the display apparatus		or, if the Court determines that construction is necessary,	
		a rigid or printed circuit board for controlling certain operations of the display apparatus mechanically supported by the side portion of the reflecting plate	
		Intrinsic Support	
		2:58-65, 5:62-6:23, 8:28-33, Figs. 8-9	
		Comments of the Comments of th	

integrated supporting unit L a component including a supporting frame portion and either a reflecting plate portion or a supporting plate portion Intrinsic Support

Claim Terms	Des CMO Construction
a circuit board installed on at least one of the side portions of the reflecting plate for controlling operations of the display apparatus	a rigid or pr controlling apparatus m side portion unit
	Intrinsic Support
	2:58-65, 5:62-6:23, 6:67-7:17, 8:28-33, Figs. 8-9, 12
a circuit board installed on at least one of the side portions of the supporting plate for controlling operations of the display apparatus	a rigid or printed circuit board for controlling certain operations of the display apparatus mechanically supported by the side portion of the integrated supporting unit
	Intrinsic Support
	3:3-17, 6:38-62, 7:27-43, 8:28-33, Figs. 10- 11
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V-2

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Disputed Constructions

	being separated from the side L portion by a gap		an array of light tubes disposed behind the display panel		upper frame L		display apparatus L
							CIXIO Construction
Intrinsic Support 4:35-39, 54-64; 5:15-21, 30-36, 40-51; 6:6-13, 49-51; 8:4-27; Figs. 4-7.	positioned to form a space bounded by a sub-frame and a side portion	Intrinsic Support 2:1-11; 3:18-24; 8:4-16; Figs. 4-13.	multiple fluorescent lamps arranged along the back of the direct type backlight unit	Intrinsic Support 1:8-11, 36-53; 2:1-11; 8:4-27; Figs. 1, 3-13.	the outermost front cover for the display product	Intrinsic Support 1:8-11, 36-53; 2:1-11; 8:4-27; Figs. 1, 3-13.	a display product, such as a monitor or television

	a circuit board installed on the L side portion of the reflecting plate for controlling operations of the display apparatus	a gar	being separated from the side L portion of the supporting plate by		a circuit board installed within the Egap for controlling operations of the display apparatus	Claim Terms Des.
						CMO Construction
Intrinsic Support 1:7-11; 1:54-2:7; 3:18-24, 61-63; 6:25-27, 62-64; 8:4-27; Figs. 4-13; App 10/065,039, 1/26/01 Notice of Allowability, page 2.	a control circuit board is mounted to the side of the reflecting plate and no control circuit board is located on the back of the supporting plate or reflecting plate	Intrinsic Support 4:35-39, 54-64; 5:15-21, 30-34; 5:40-51; 6:6-13, 49-51; 8:4-27; Figs. 4-7.	positioned to form a space bounded by a sub-frame and a side portion	Intrinsic Support 1:7-11; 1:54-2:7; 3:18-24, 61-63; 5:19-21, 30-36; 6:25-27, 62-64; 8:4-27; Figs. 4-13; App 10/065,039, 1/26/01 Notice of Allowability, page 2.	a control circuit board is mounted in the space bounded by the sub-frame and the side portion and no control circuit board is located on the back of the supporting plate or reflecting plate	LGD Construction

Claim Terms	Des.	CMO Construction	LGD Construction
a circuit board installed on the side portion of the supporting	T		a control circuit board is mounted to the side of the supporting plate and no control
plate for controlling operations of the display apparatus			circuit board is located on the back of the supporting plate or reflecting plate
			Intrinsic Support 1:7-11; 1:54-2:7; 3:18-24, 61-3; 6:25-27,
			62-64; 8:4-27; Figs. 4-13; App 10/065,039, 1/26/01 Notice of Allowability, page 2.
integrated supporting unit	L		a unitary structure that provides support
			Intrinsic Support 4:5-20; 6:65-7:15; 7:26-40; Fig. 4.
a circuit board installed on at least			Indefinite
one of the side portions of the			
reflecting plate for controlling			
apparatus			
a circuit board installed on at least			Indefinite
supporting plate for controlling			
operations of the display			
apparatus			

W-1

Disputed Constructions

Claim Terms forming a sealing member having a main portion enclosing a display	Des.	CMO Construction plain meaning
region		or, if the Court determines that construction is necessary,
		forming sealing material in a closed shape having four side walls for fixing a pair of substrates to each other and sealing the liquid crystal layer in the display region
		Intrinsic Support
		Abstract; 1:6-11; 1:17-39; 1:49-2:5; 2:17-28; 2:40-67; 3:7-15; 3:20-27; 3:45-54; 3:67-4:31; 4:34-37; 4:65-5:7; Figs. 1-4; App. 10/921,508, 4/26/06 Response, pages 8, 9, 10; 9/25/06 Amendment, pages 9, 10, 11, 12

one sine of the display region	overlapping area extends along				bornon suspend a grapus, region	
	Г					L L
Intrinsic Support 1:52-56; 2:56-67; 3:7-15; 4:18-31; 4:65-5:7; Figs. 1-4	plain meaning	Abstract; 1:6-11; 1:17-39; 1:49-2:5; 2:17-28; 2:40-67; 3:7-15; 3:20-27; 3:45-54; 3:67-4:31; 4:34-37; 4:65-5:7; Figs. 1-4; App. 10/921,508, 4/26/06 Response, pages 8, 9, 10; 9/25/06 Amendment, pages 9, 10, 11, 12	Intrinsic Support	sealing material in a closed shape having four side walls for fixing a pair of substrates to each other and sealing the liquid crystal layer in the display region	or, if the Court determines that construction is necessary,	plain meaning
						LGD Construction

LGD Construction

W-2

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Disputed Constructions

	the sealing member has a main portion enclosing a display region		forming a sealing member having a main portion enclosing a display region	Claim Terms Des.
				CMO Construction
Intrinsic Support 1:29-32, 49-52; 4:12-31; 5:3-7; Figs. 2, 3, and 4; App 10/921,508, 4/26/06 Response, pages 8-10, 12 and 13; App 10/921,508, 9/26/06 Response, pages 9-17; App 10/921,508, 3/1/07 Response, pages 10-16.	the sealing member has a portion of sealant material that is parallel to the edges of and encloses the display region	Intrinsic Support 1:29-32, 49-52; 4:12-31; 5:3-7; Figs. 2, 3, and 4; App 10/921,508, 4/26/06 Response, pages 8-10, 12 and 13; App 10/921,508, 9/26/06 Response, pages 9-17; App 10/921,508, 3/1/07 Response, pages 10-16.	depositing sealant material parallel to the edges of the display region so that it encloses the display region	LGD Construction

applying the sealing material along the display region to form the main portion of the sealing member	overlapping area extends along one side of the display region	Claim Terms
T	L	Des.
		CMO Construction
depositing sealant material parallel to the edges of the display region Intrinsic Support 1:29-32, 49-52; 4:1-31; 5:3-7; Figs. 2, 3, and 4; App 10/921,508, 4/26/06 Response, pages 8-10, 12 and 13; App 10/921,508, 9/26/06 Response, pages 9-17; App 10/921,508, 3/1/07 Response, pages 10-16.	a segment of the sealing member main portion where sealant material is applied on top of previously applied sealant material along one edge of the display region Intrinsic Support 1:52-61; 4:12-31; Figs. 2, 3, and 4; App 10/921,508, 3/1/07 Response, pages 10-16; App 10/921,508, 6/5/07 Reasons for Allowability, page 2.	LGD Construction